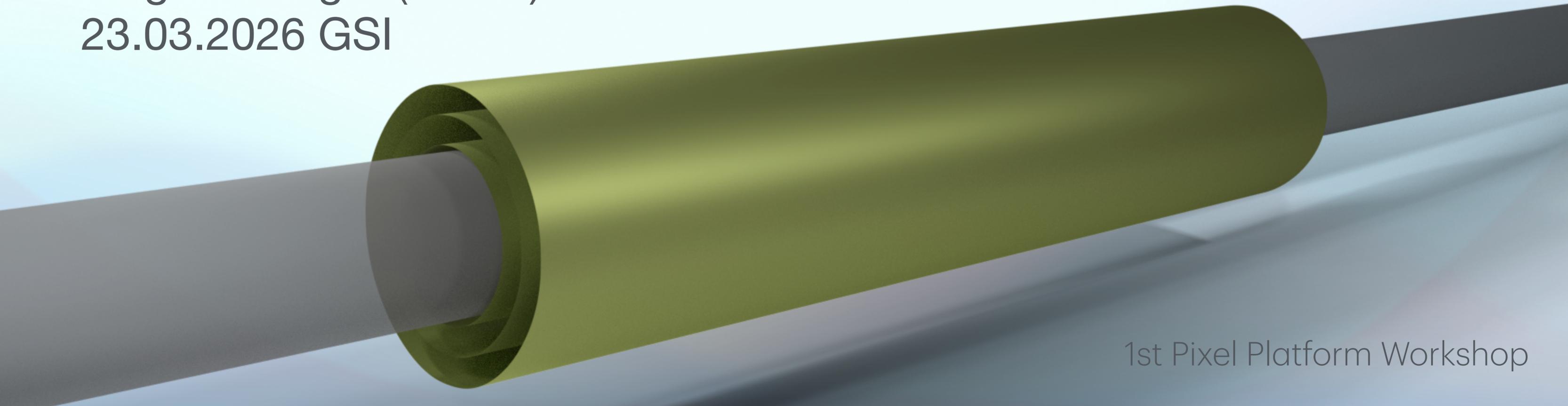


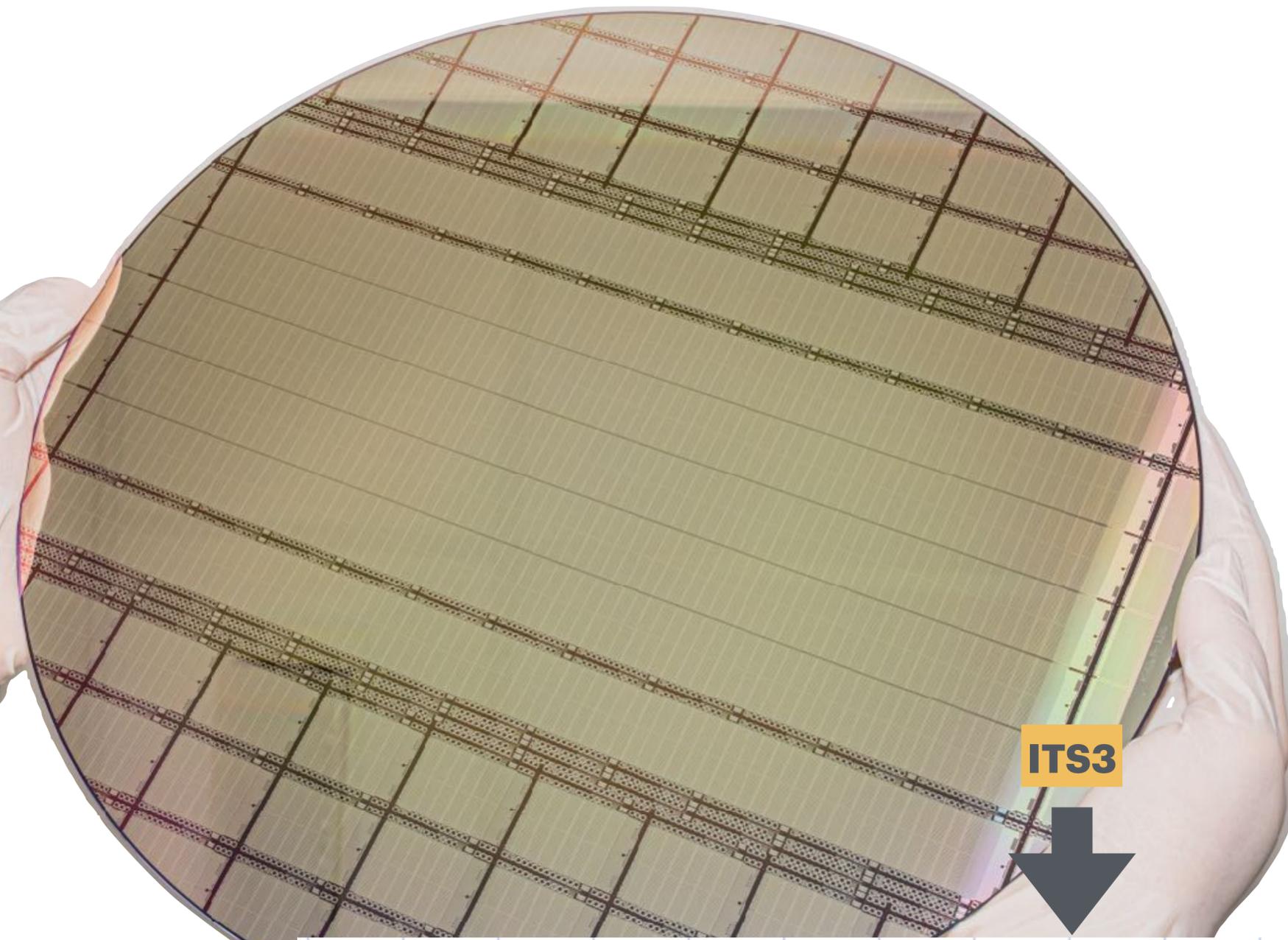
**ALICE**

# Recent and future developments in Monolithic Active Pixel Sensors ***ALICE ITS3 and ALICE 3***

Magnus Mager (CERN) on behalf of ALICE  
23.03.2026 GSI



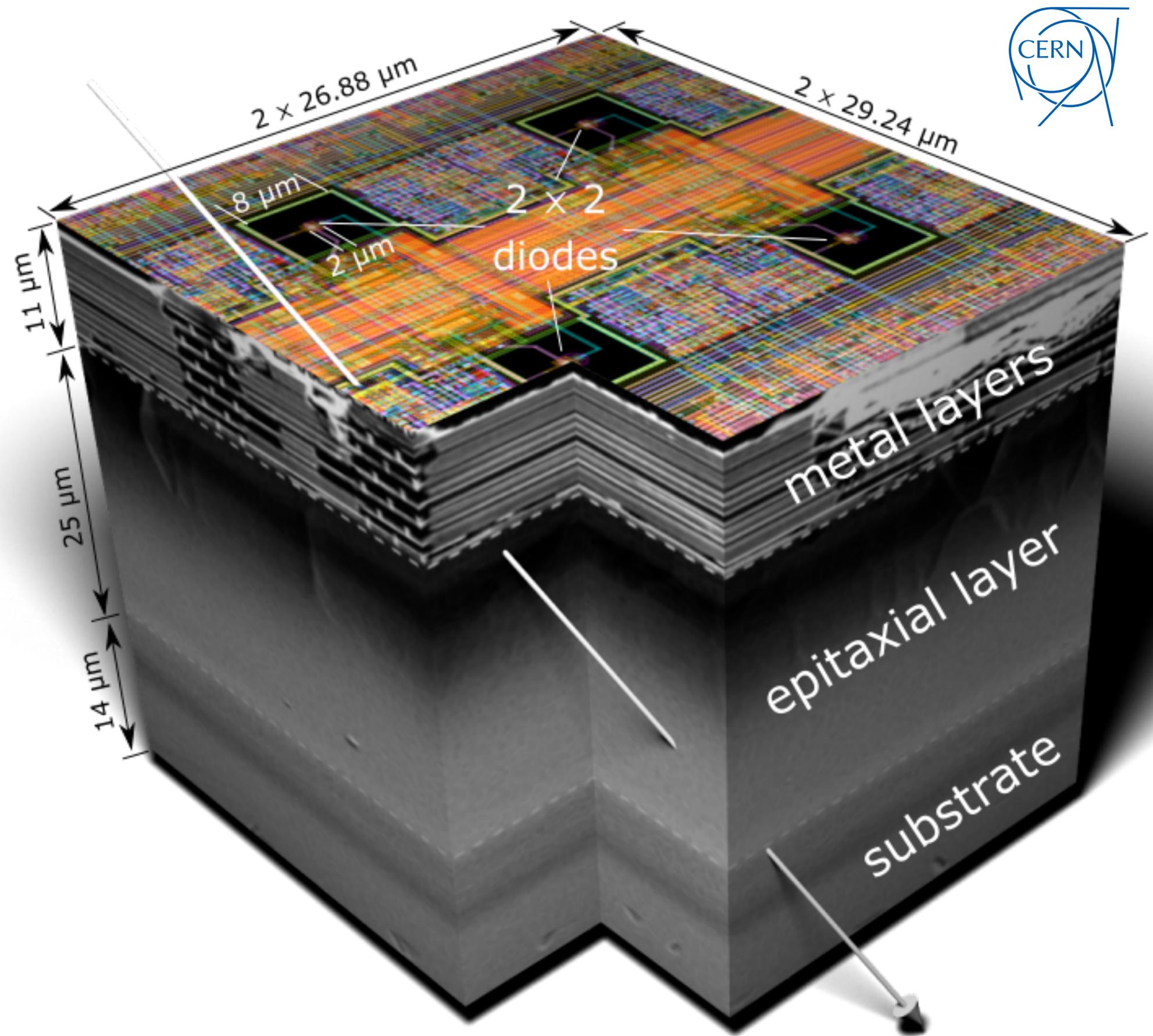
# Outline



- ▶ Monolithic Active Pixel Sensors (MAPS)
  - motivation / key specs
- ▶ Starting points
  - STAR Heavy flavor tracker (HFT)
  - ALICE Inner Tracking System 2 (ITS2, ALPIDE)
- ▶ **ALICE Inner Tracking System 3 (ITS3)**
  - 65 nm technology
  - wafer-scale
  - bent
- ▶ **ALICE 3**
  - high radiation loads
  - large area
- ▶ *More ideas*

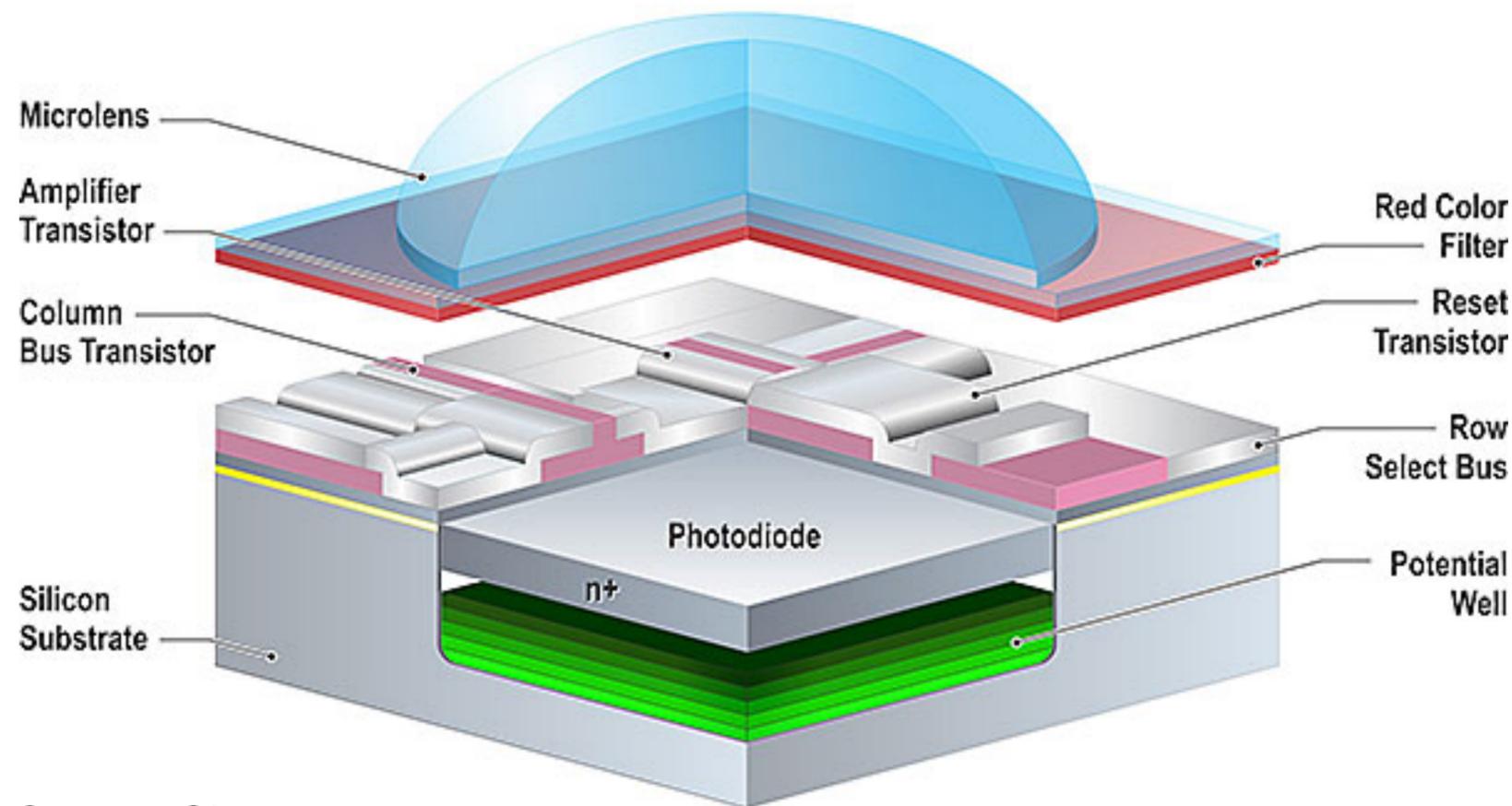
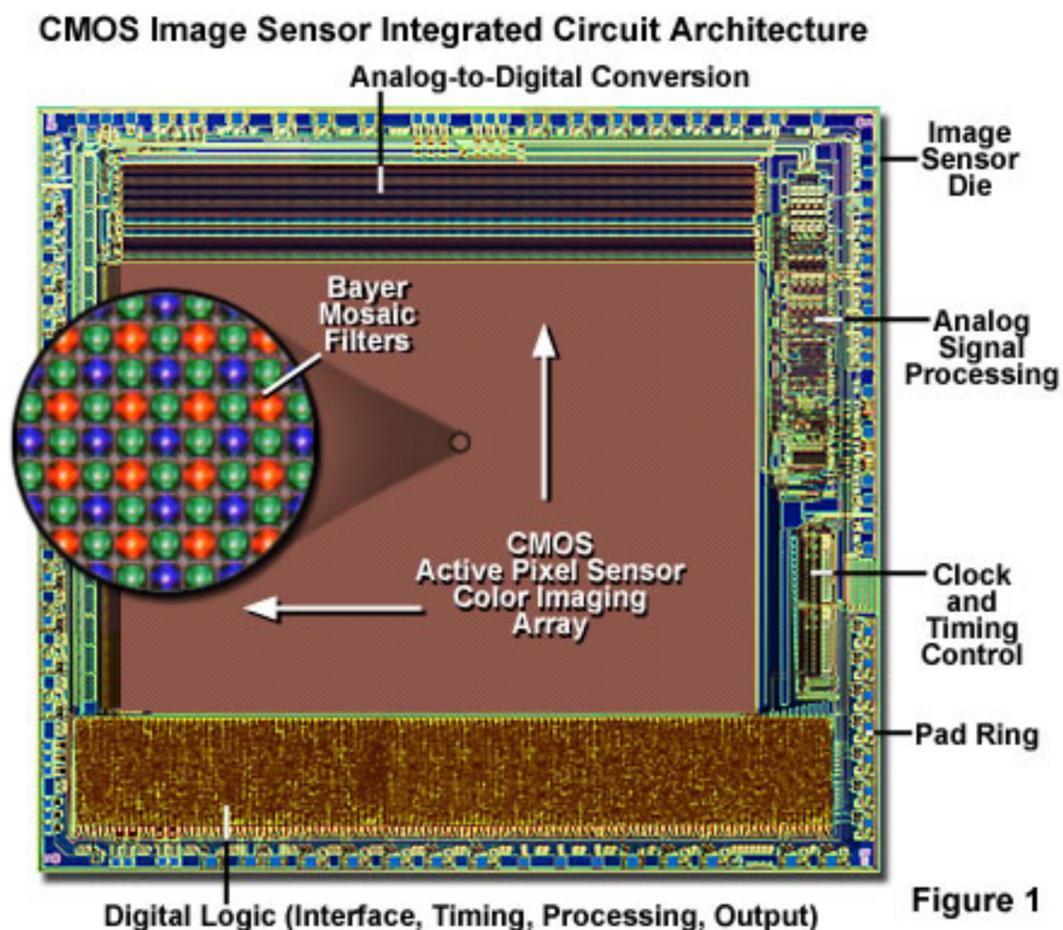


# MAPS



# Monolithic CMOS pixel sensors

sensor and readout on same chip

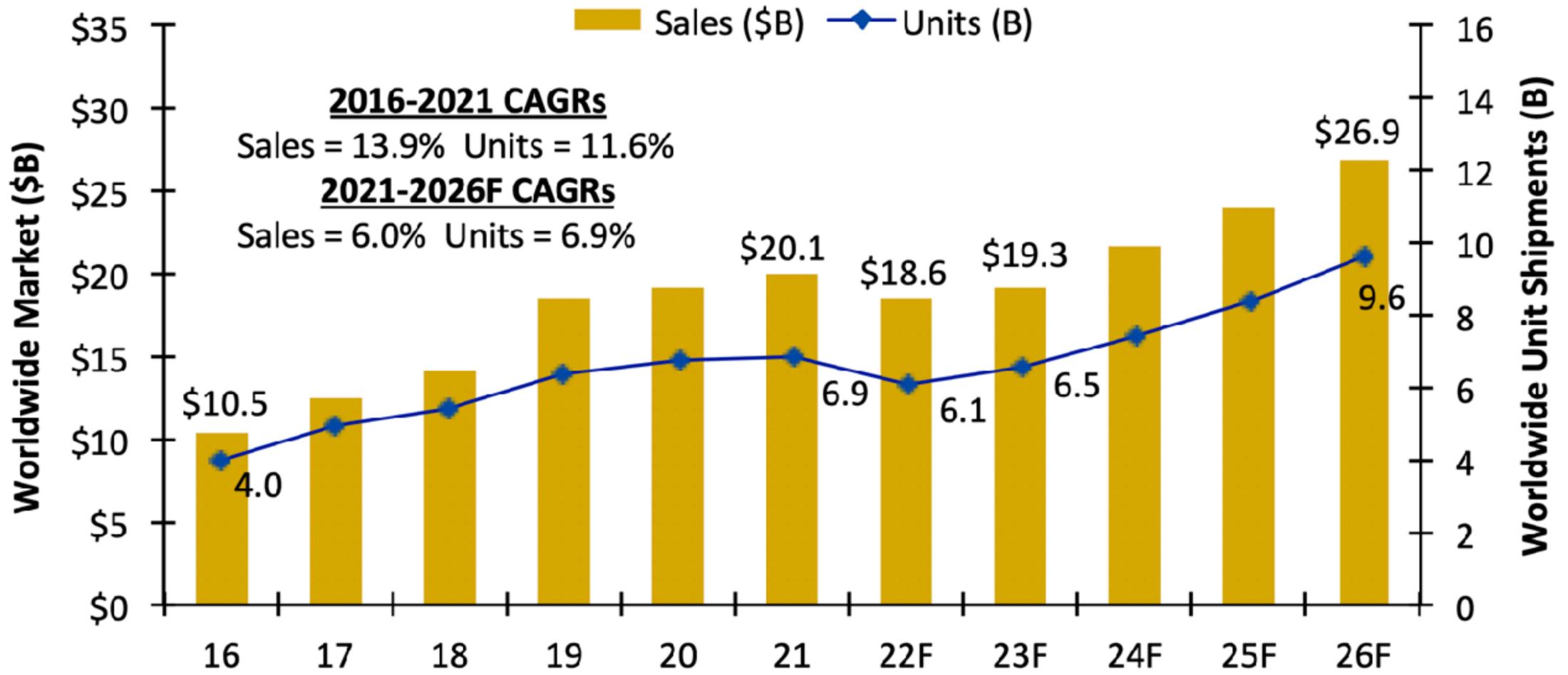


Source: Olympus

- ▶ Nowadays the most widespread implementation of image sensors
  - main advantage: price

- ▶ Light vs charged particles:
  - both generate electron/hole pairs
  - need to increase sensitive area to 100% (no focusing lenses for charged particles)

# CMOS image sensor market

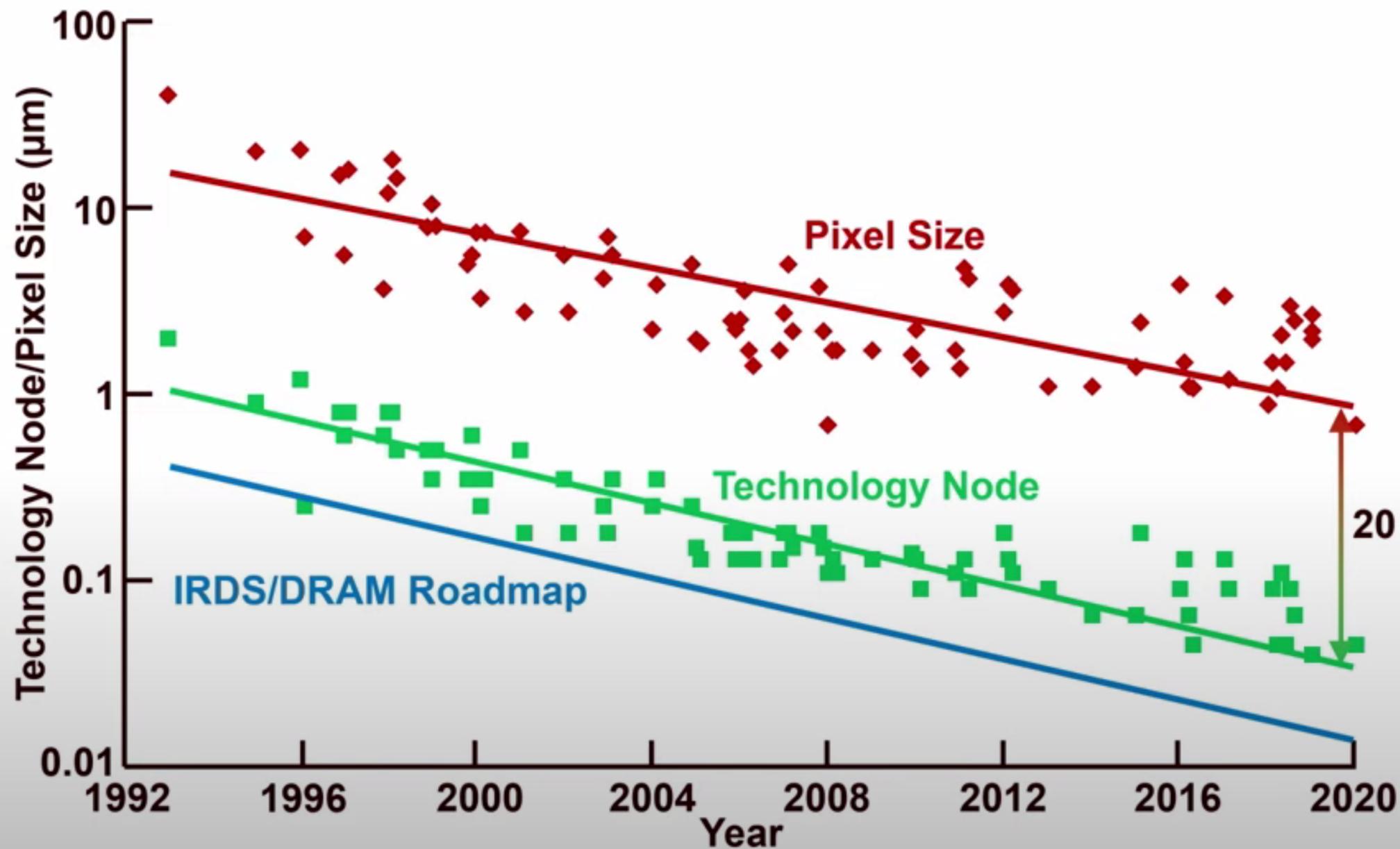


- ▶ Rapid increase of sales
- ▶ HEP *can* profit from a huge commercial interest
- ▶ Our job: make these light sensors particle sensors

[IC Insights]

# Evolution of technology node / pixel size

for image sensors



- ▶ **Pixel size:** 20x above technology feature size
- ▶ **Technology:** 10 years behind DRAM technology
- ▶ **Functionality:** typically only very few (1-4) transistors per pixel
- ▶ **HEP applications have many more transistors per pixel (see later)**

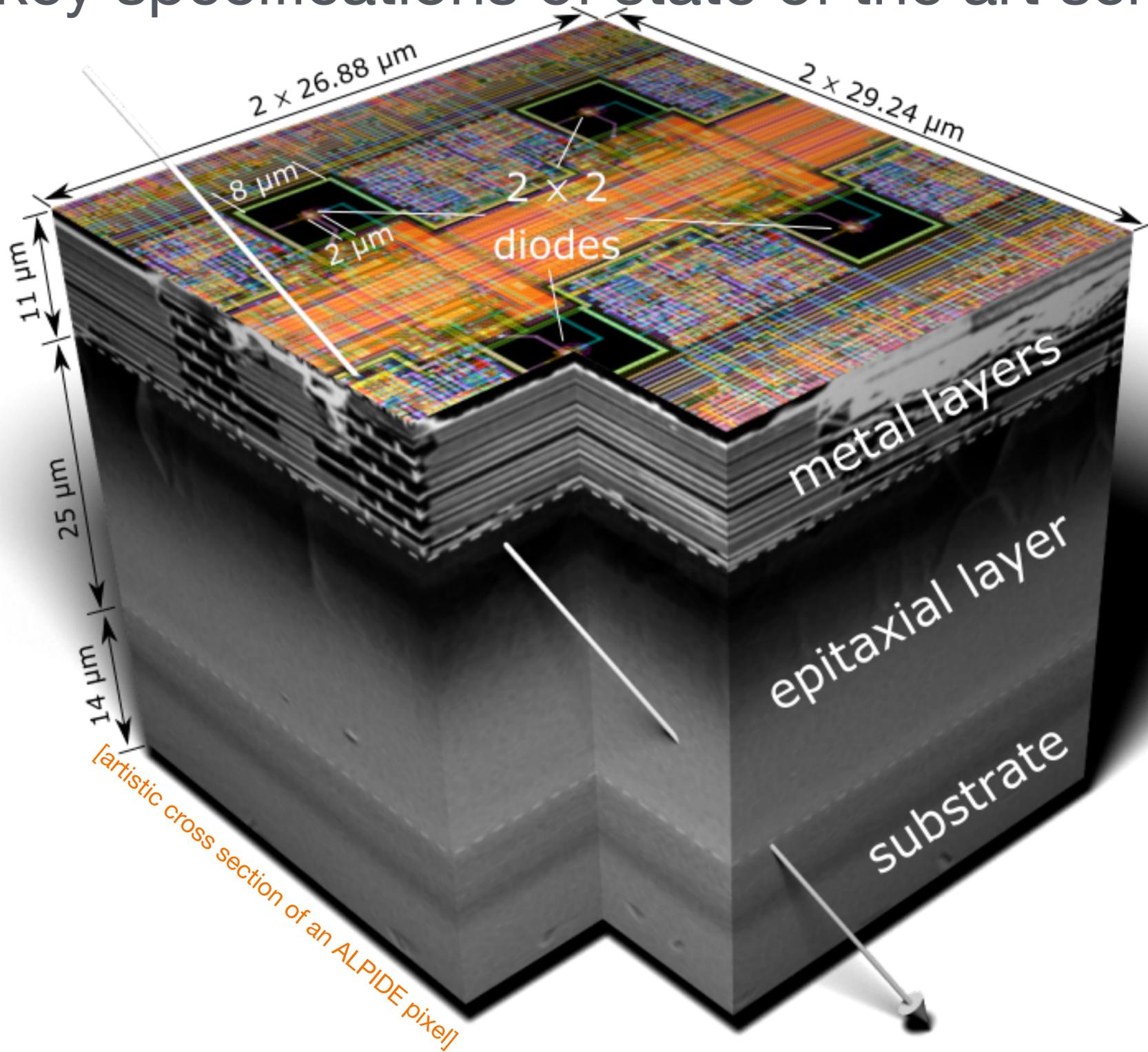
[A. Theuwissen, ISSCC 2021]

# Monolithic Active Pixel Sensors (MAPS)



ALICE

key specifications of state of the art sensors

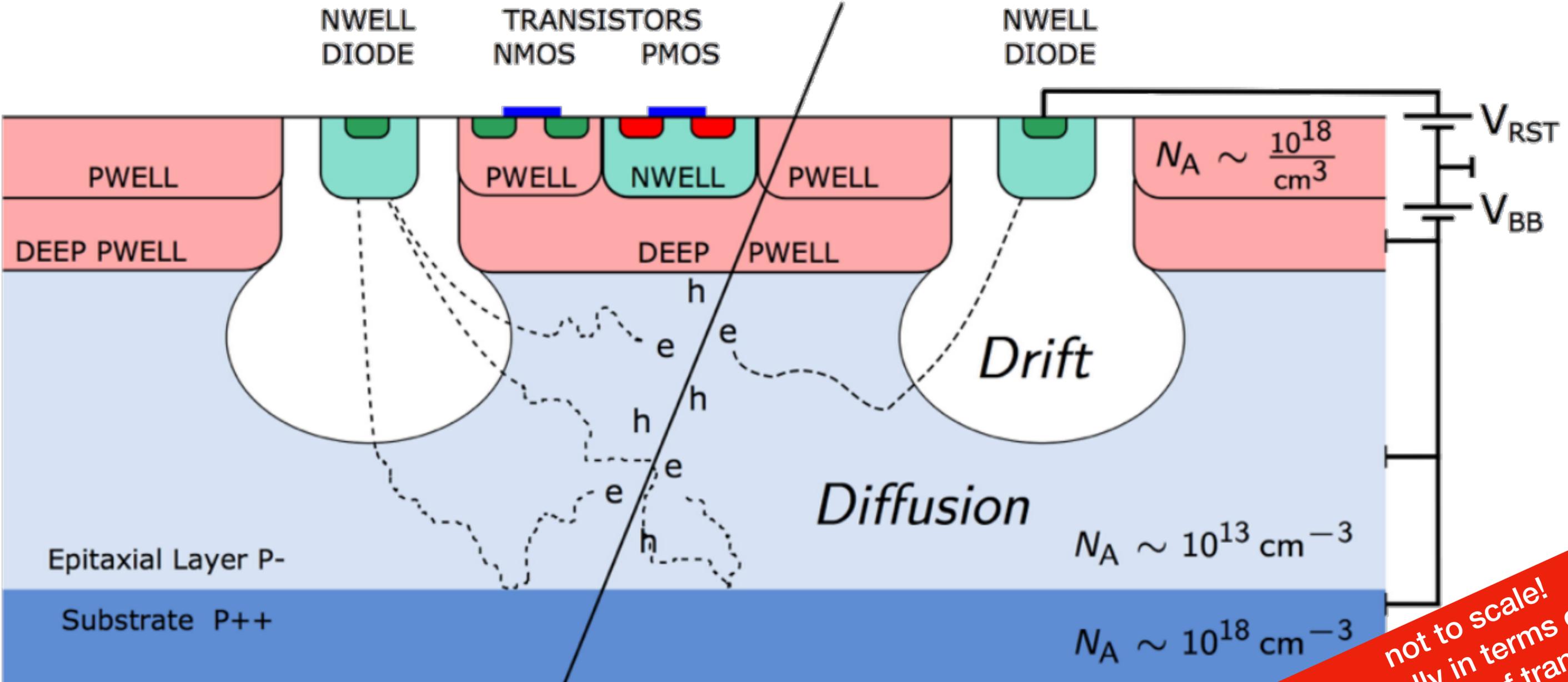


- ▶ **Thin:**  $O(50 \mu\text{m})$
- ▶ **Very granular:**  $O(10-30 \mu\text{m})$
- ▶ **Small diodes:** capacitances of  $O(1-5 \text{ fF})$
- ▶ **Highly integrated:**  $O(100)$  transistors/pixel

# Monolithic Active Pixel Sensors (MAPS)



working principle

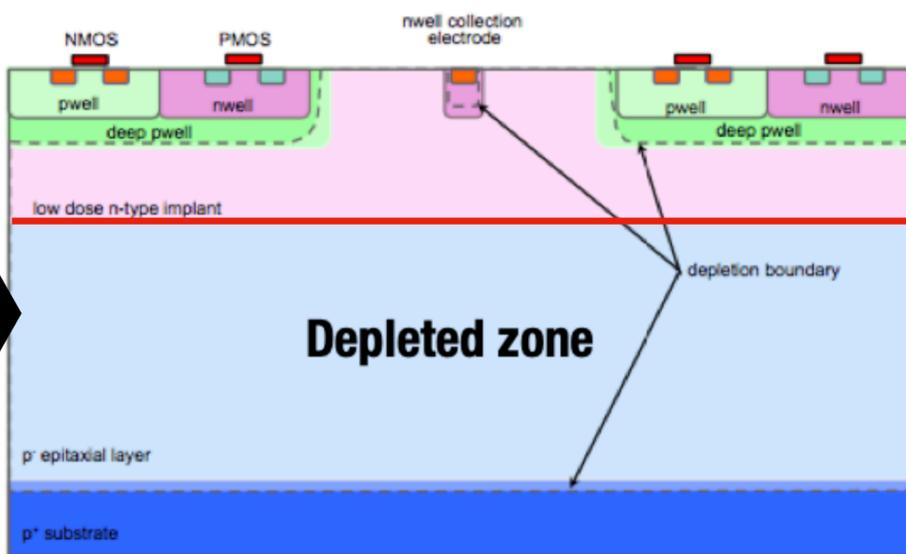
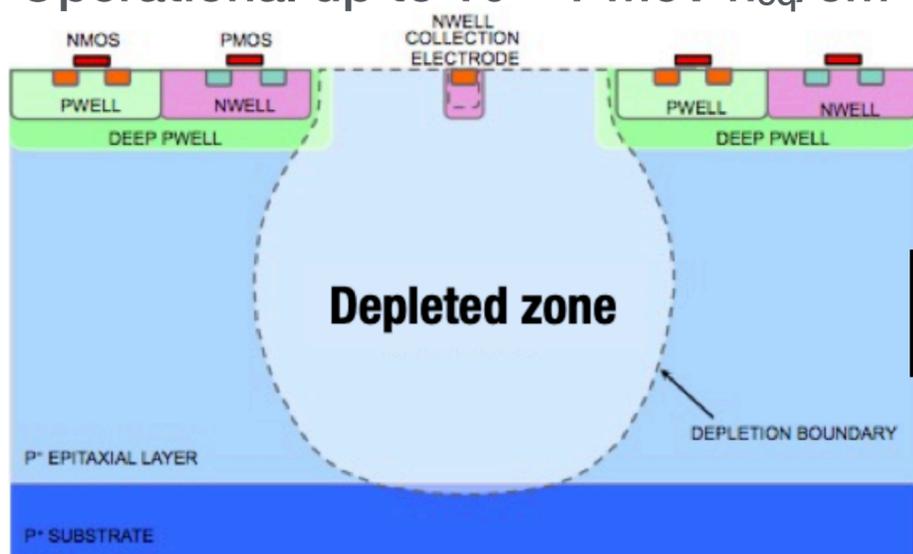


not to scale!  
especially in terms of size  
and number of transistors.

# MAPS improvements

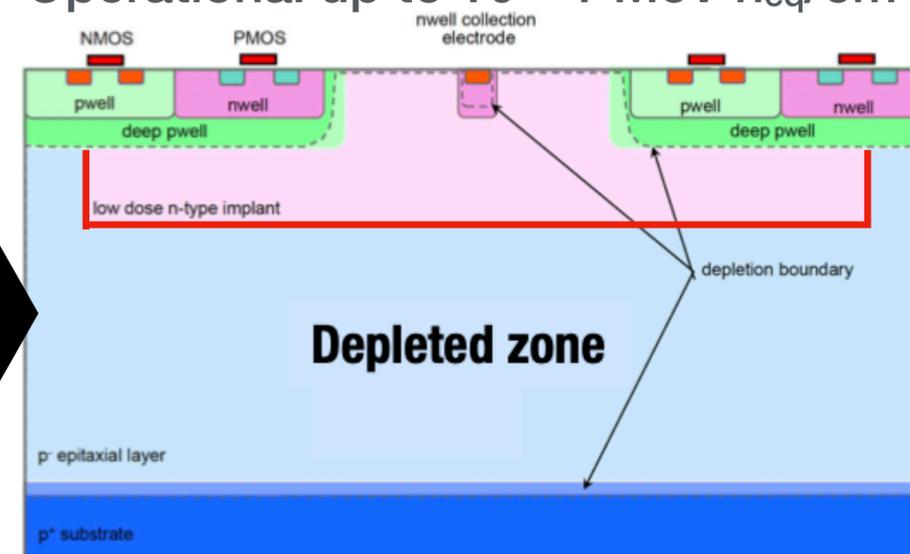
## process optimizations

Partially depleted epitaxial layer  
 Charge collection time < 30 ns  
 Operational up to  $10^{14}$  1 MeV  $n_{eq}/cm^2$



[doi:10.1016/j.nima.2017.07.046]

Fully depleted epitaxial layer  
 Charge collection time < 1 ns  
 Operational up to  $10^{15}$  1 MeV  $n_{eq}/cm^2$



[doi:10.1088/1748-0221/14/05/C05013]

- ▶ Charge collection in MAPS is a combination of:
  - diffusion (slow) in low field regions
  - drift (fast) in high field regions (i.e. in the “depleted zone”)
- ▶ Doping profiles of MAPS have been repeatedly improved to:
  - reach full depletion
  - direct the field lines towards the collection electrodes

- ▶ Resulted in significant improvements of:
  - radiation hardness
  - charge collection speed
- ▶ This optimization continues:
  - lower capacitance
  - even higher radiation hardnesses

# Key concepts

resolution, material budget

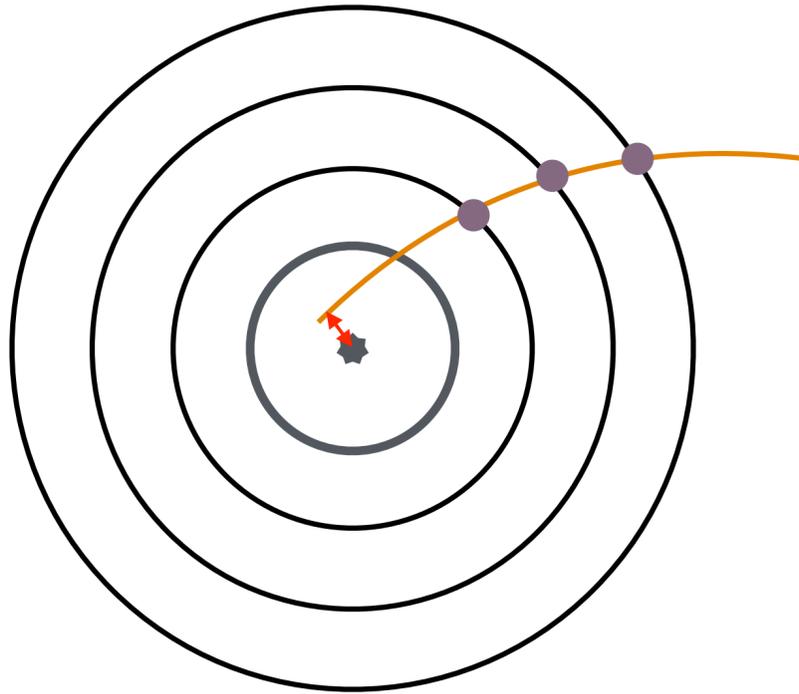
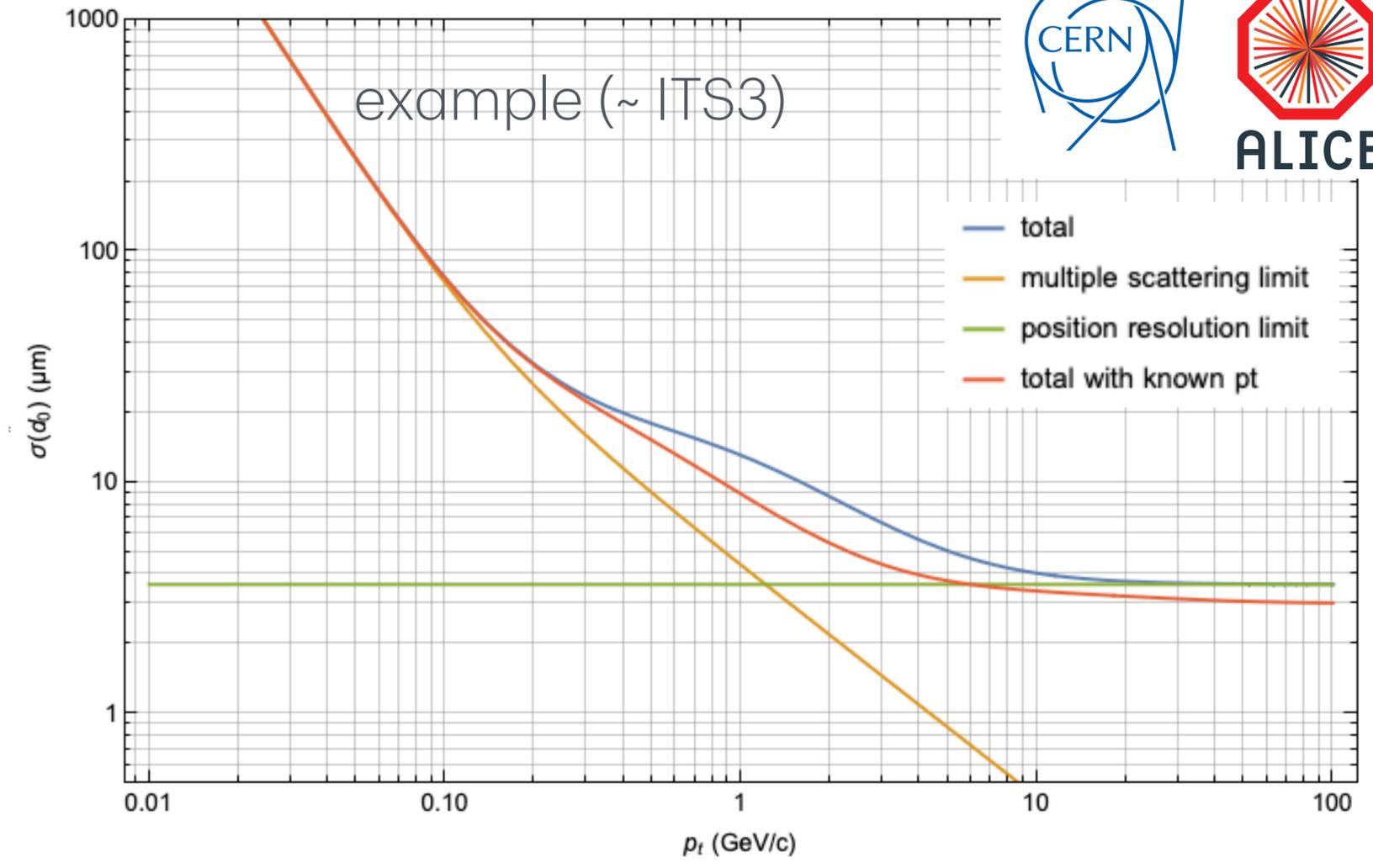
▶ Tracking and vertexing is based on finding and extrapolation of tracks

▶ **Performance figures**

- impact parameter resolution
- momentum resolution
- readout rate (“time resolution”)
- tracking efficiency

▶ **Three key contributions**

- material budget
- distance to interaction point
- intrinsic sensor position resolution
- (intrinsic detector efficiency)



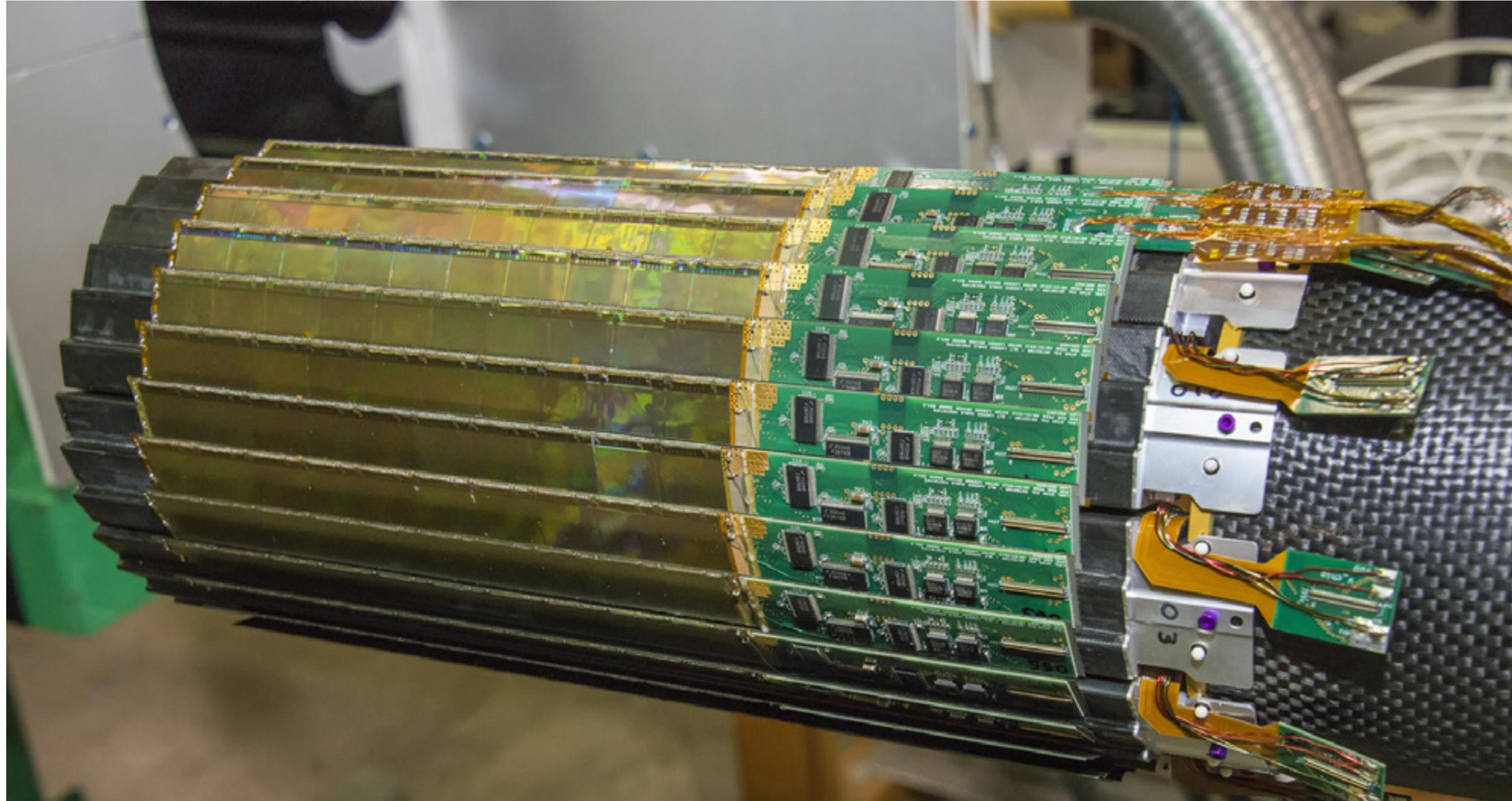
Limit	Momentum	Pointing
	$\frac{\Delta p_t}{p_t}$	$\Delta d_{0,xy}$
<b>sensor resolution</b>	$\propto \frac{\sigma p_t}{BL^2}$	$\propto r_0 \sigma$
<b>material budget</b>	$\propto \frac{1}{\beta BL} \sqrt{x/X_0}$	$\propto \frac{r_0}{\beta p_t} \sqrt{x/X_0}$

more info: [\[doi:10.1016/j.nima.2018.08.078\]](https://doi.org/10.1016/j.nima.2018.08.078)



ALICE

# Starting points



**Fig. 1.** The HFT PXL detector (*photography by Roy Kaltschmidt - Berkeley Lab*).

# STAR HFT PXL

## overview

- ▶ **First application in HEP**

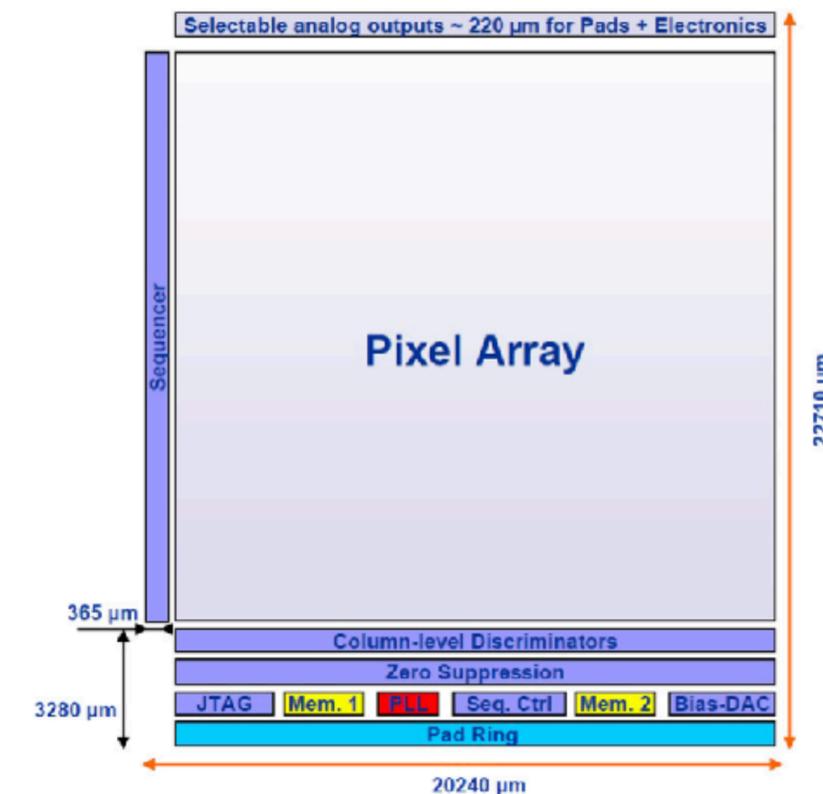
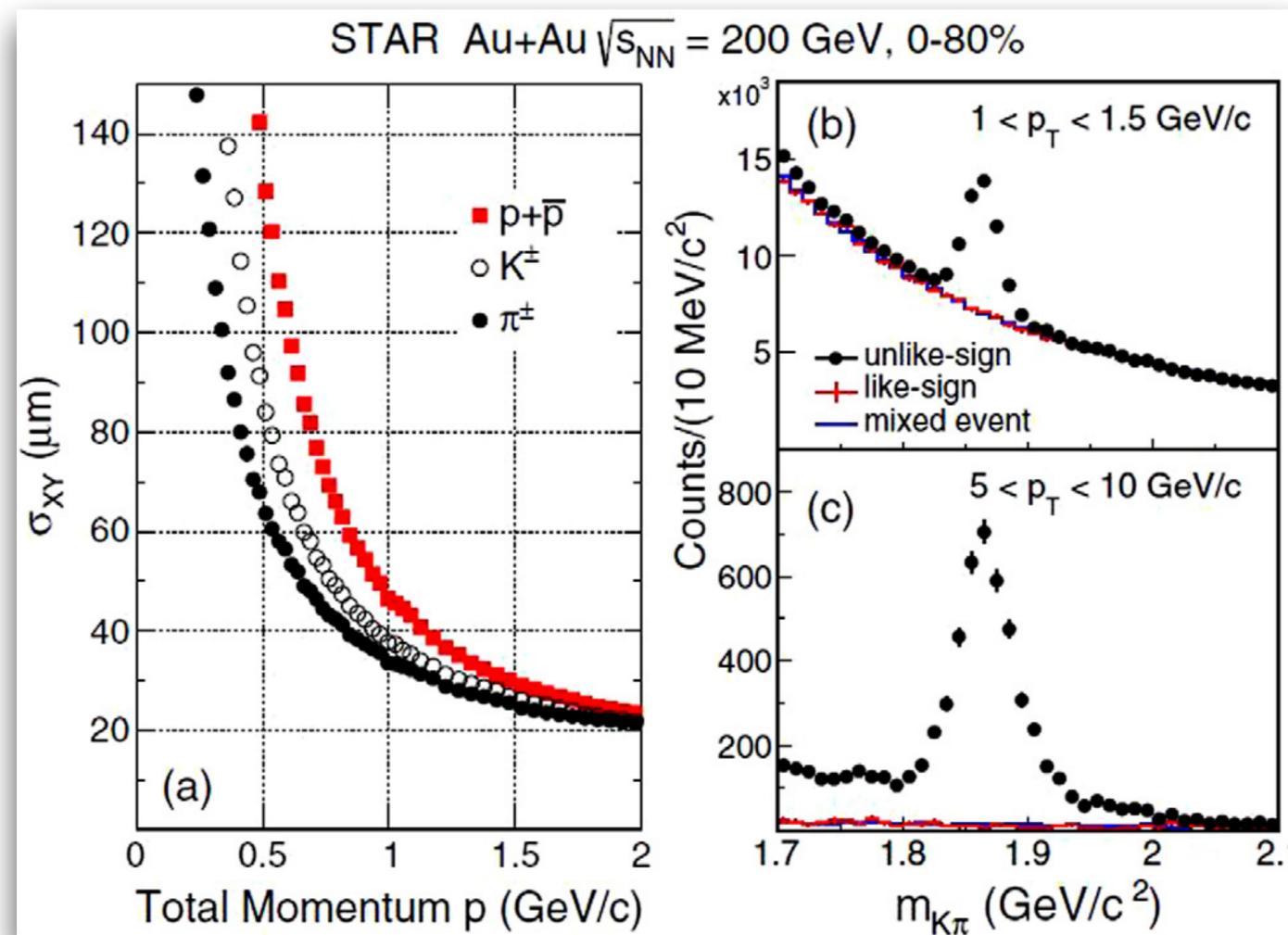
- ▶ Based the Ultimate 2 chip (aka Mimosa28)
  - 0.35  $\mu\text{m}$  technology
  - twin-well process
  - 150 mW/cm<sup>2</sup>

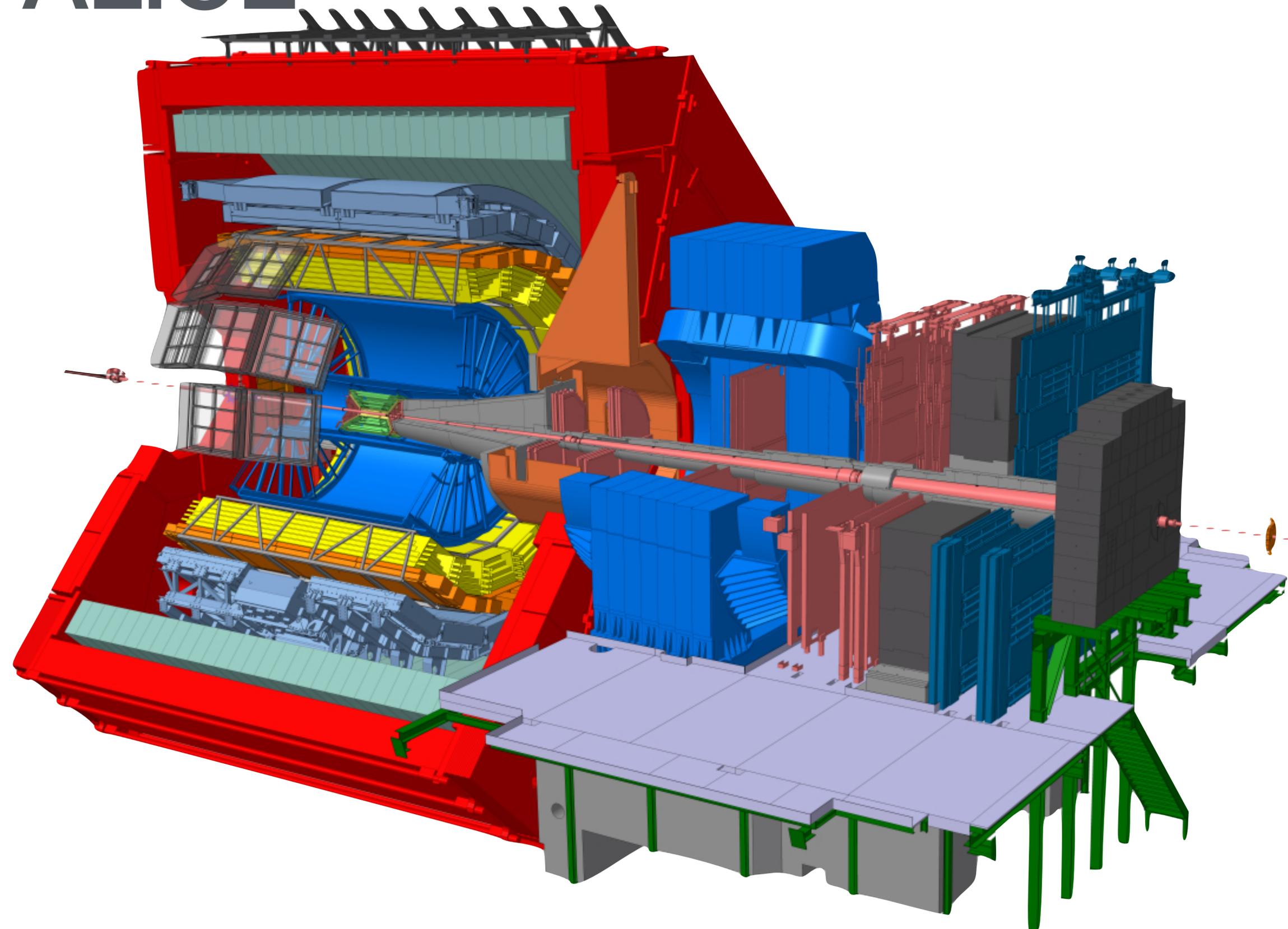
- ▶ 400 sensors

- ▶ 2 layers

- ▶ 0.16 m<sup>2</sup>

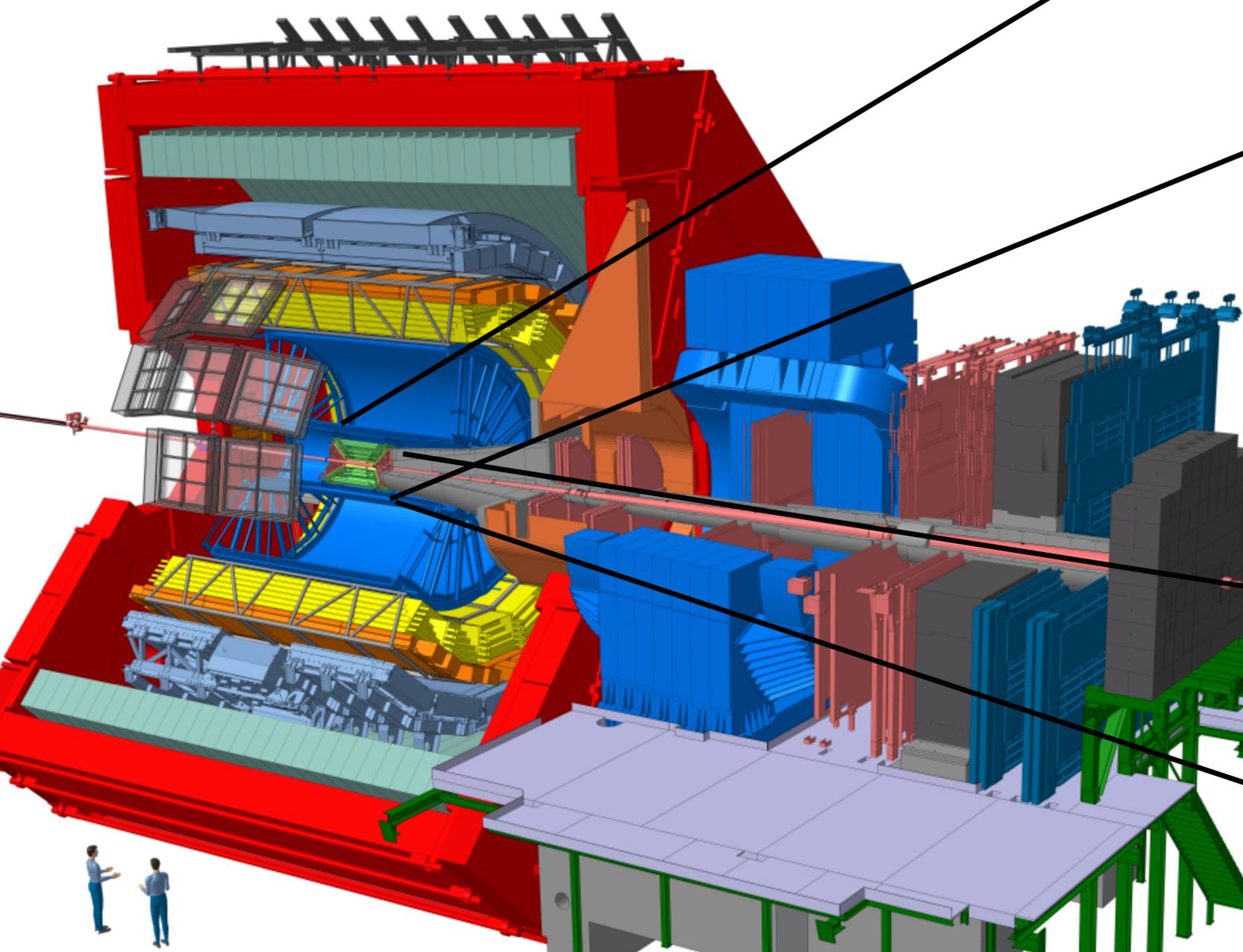
- ▶ 356 MPixel



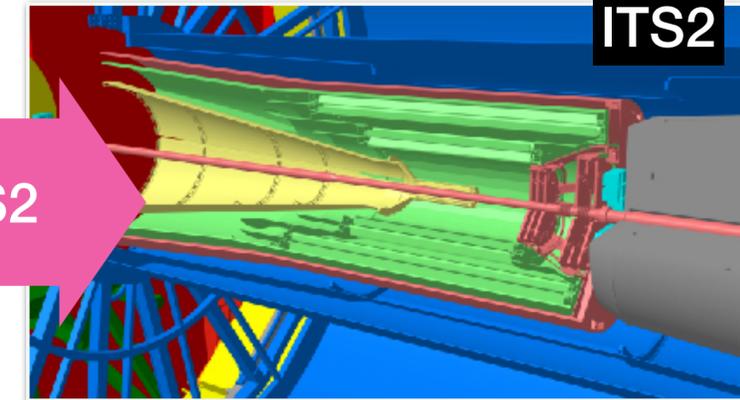
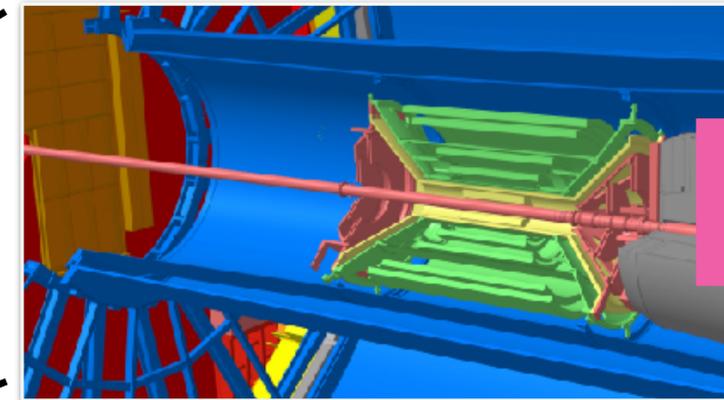


- ▶ Study of QGP in heavy-ion collisions at LHC
  - i.e. up to  $O(10k)$  particles to be tracked in a single event
- ▶ Reconstruction of charm and beauty hadrons
- ▶ Interest in low momentum ( $\lesssim 1$  GeV/c) particle reconstruction

# ALICE ITS2 upgrade (done)



## Inner Tracking System



LS2

ITS2

### 6 layers:

- 2 hybrid silicon pixel
- 2 silicon drift
- 2 silicon strip

### Inner-most layer:

- radial distance: 39 mm
- material:  $X/X_0 = 1.14\%$
- pitch:  $50 \times 425 \mu\text{m}^2$
- rate capability: 1 kHz

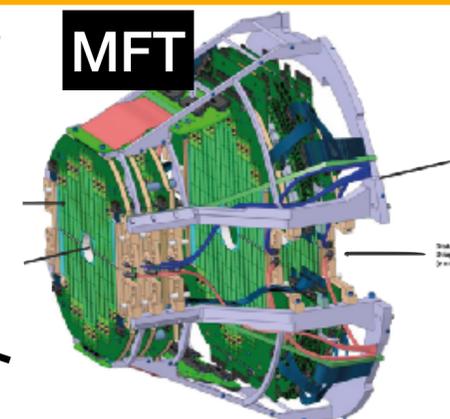
### 7 layers:

- all MAPS
- 10 m<sup>2</sup>, 24k chips, 12.5 Giga-Pixels

### Inner-most layer:

- radial distance: 23 mm
- material:  $X/X_0 = 0.36\%$
- pitch:  $29 \times 27 \mu\text{m}^2$
- rate capability: 100 kHz (Pb-Pb)

## Muon Forward Tracker

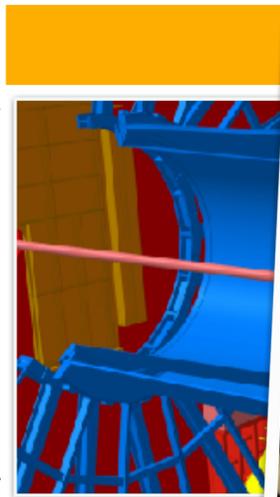
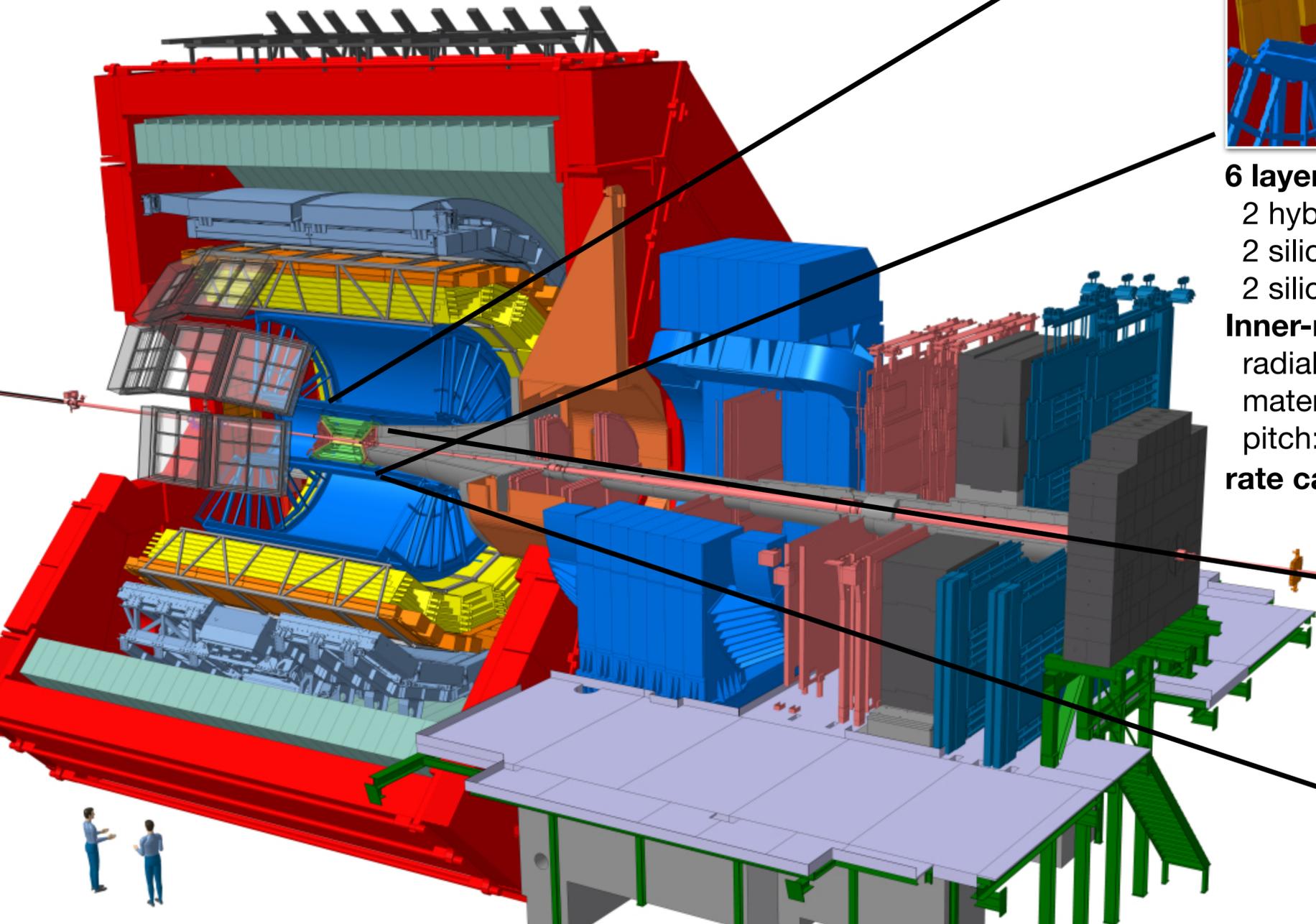


MFT

new detector

- 5 discs, double sided:**
- based on same technology as ITS2

# ALICE ITS2 upgrade (done)



**6 layers:**  
 2 hybrid silicon  
 2 silicon drift  
 2 silicon strip  
**Inner-most**  
 radial distance  
 material: X  
 pitch: 50  $\times$   
 rate capabi



## PIXEL PERFECT

Exploring the Hubble tension  
 A CERN for climate change  
 Medical technologies

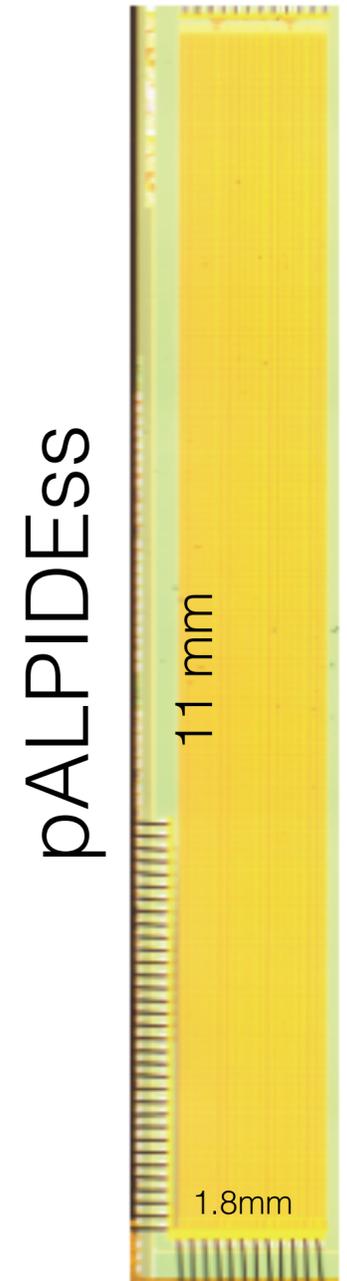
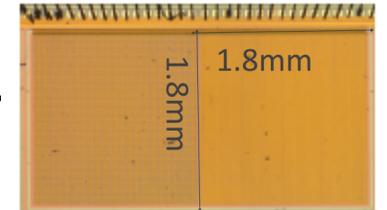
ITS2

# ITS2 chip development roadmap



2012	Explorer	<ul style="list-style-type: none"><li>• study of technology</li><li>• detection diode geometry</li><li>• starting materials</li><li>• radiation hardness</li></ul>
2013	pALPIDEss	<ul style="list-style-type: none"><li>• digital front-end</li><li>• priority-encoder readout</li></ul>
May 2014	pALPIDE-1	<ul style="list-style-type: none"><li>• full-scale sensor</li><li>• simplified interface</li></ul>
Apr 2015	pALPIDE-2	<ul style="list-style-type: none"><li>• chip-chip communication interface</li><li>• module integration</li><li>• <i>slow-speed serial link</i></li></ul>
Oct 2015	pALPIDE-3	<ul style="list-style-type: none"><li>• multiple-hit memory, final interfaces</li><li>• last optimisation of pixel</li><li>• <i>high-speed serial link (jitters)</i></li></ul>
Aug 2016	<b>ALPIDE</b>	<ul style="list-style-type: none"><li>• final chip</li></ul>

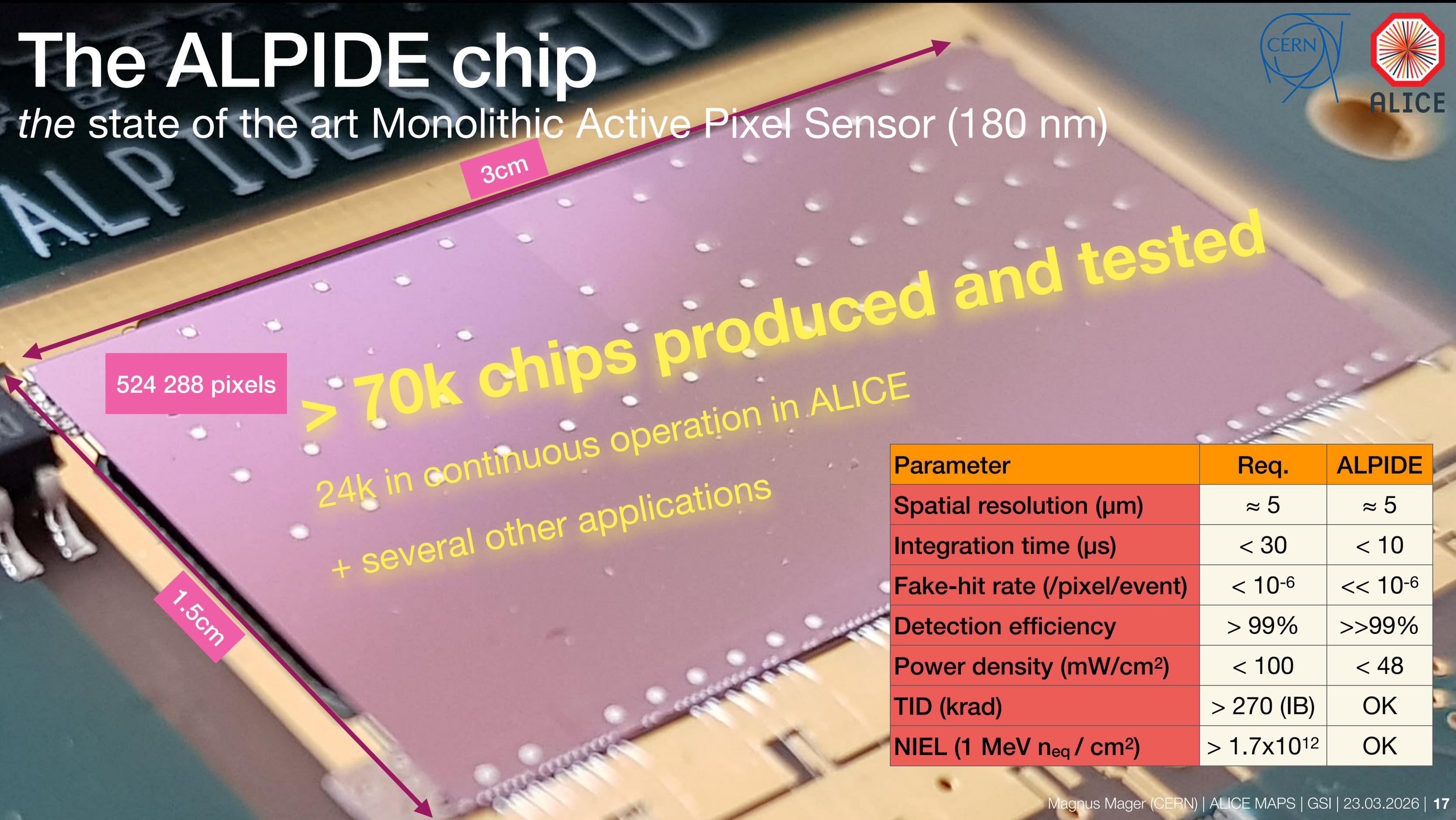
Explorer



**One needs a number of prototypes, especially of large scale (sensor+readout on same chip)**

# The ALPIDE chip

the state of the art Monolithic Active Pixel Sensor (180 nm)



524 288 pixels

3cm

1.5cm

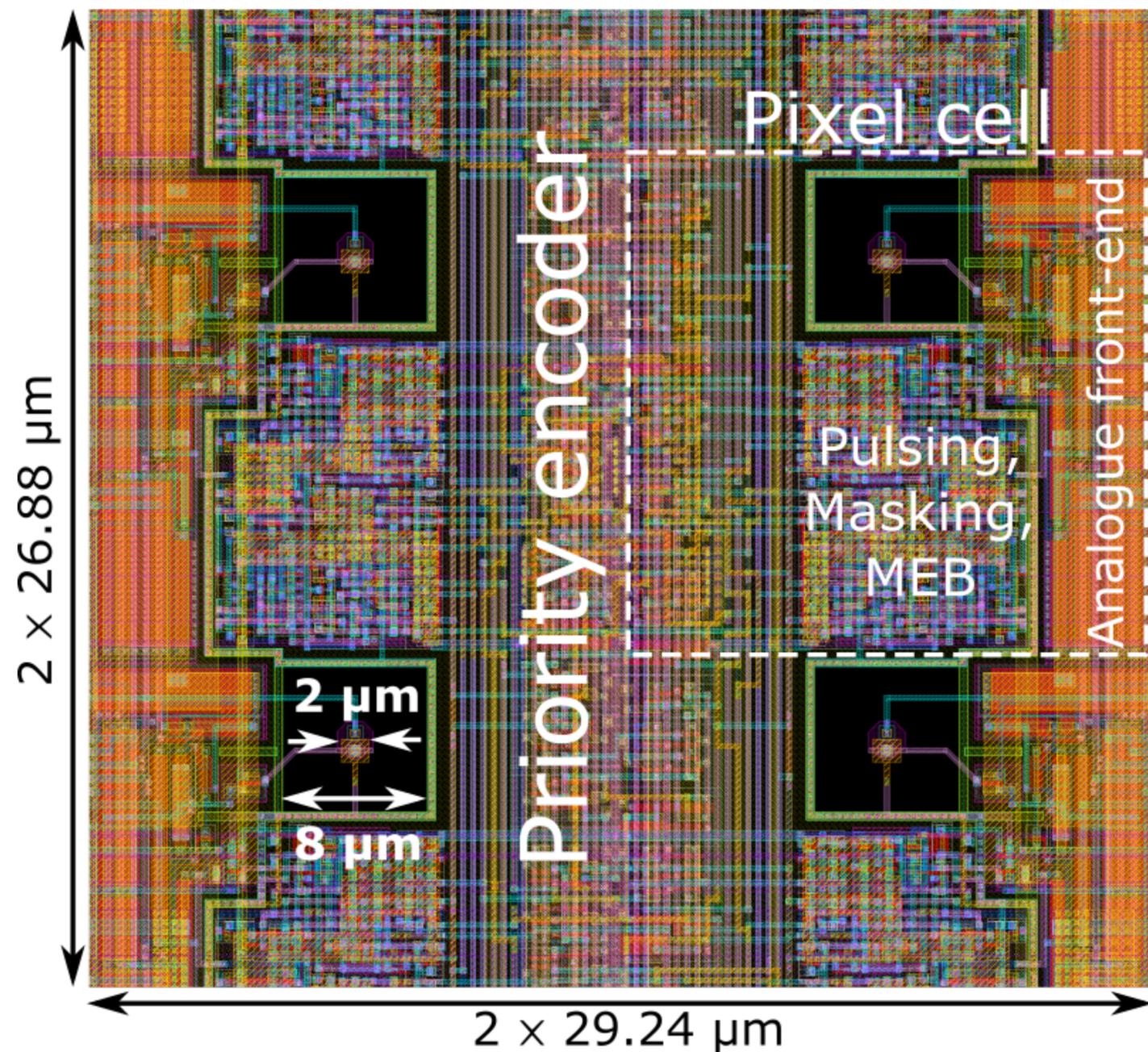
> 70k chips produced and tested

24k in continuous operation in ALICE  
+ several other applications

Parameter	Req.	ALPIDE
Spatial resolution ( $\mu\text{m}$ )	$\approx 5$	$\approx 5$
Integration time ( $\mu\text{s}$ )	$< 30$	$< 10$
Fake-hit rate (/pixel/event)	$< 10^{-6}$	$\ll 10^{-6}$
Detection efficiency	$> 99\%$	$\gg 99\%$
Power density ( $\text{mW}/\text{cm}^2$ )	$< 100$	$< 48$
TID (krad)	$> 270$ (IB)	OK
NIEL ( $1 \text{ MeV } n_{\text{eq}} / \text{cm}^2$ )	$> 1.7 \times 10^{12}$	OK

# The ALPIDE chip

pixel matrix

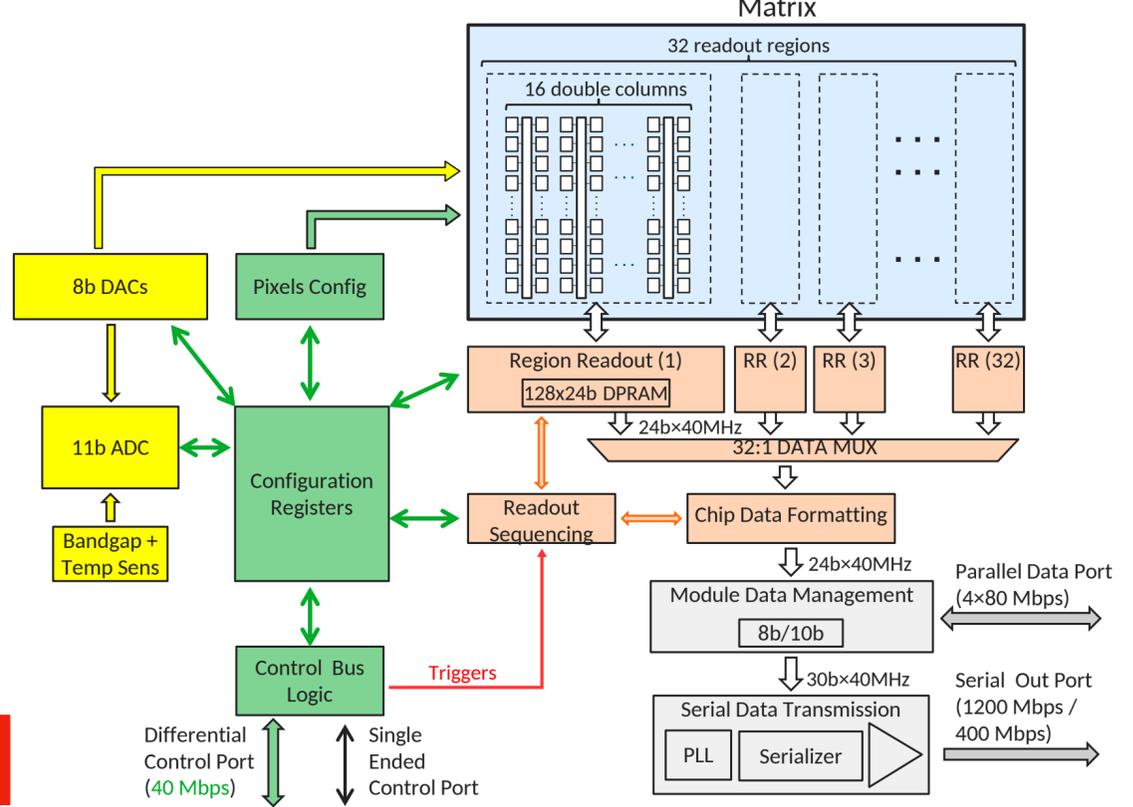
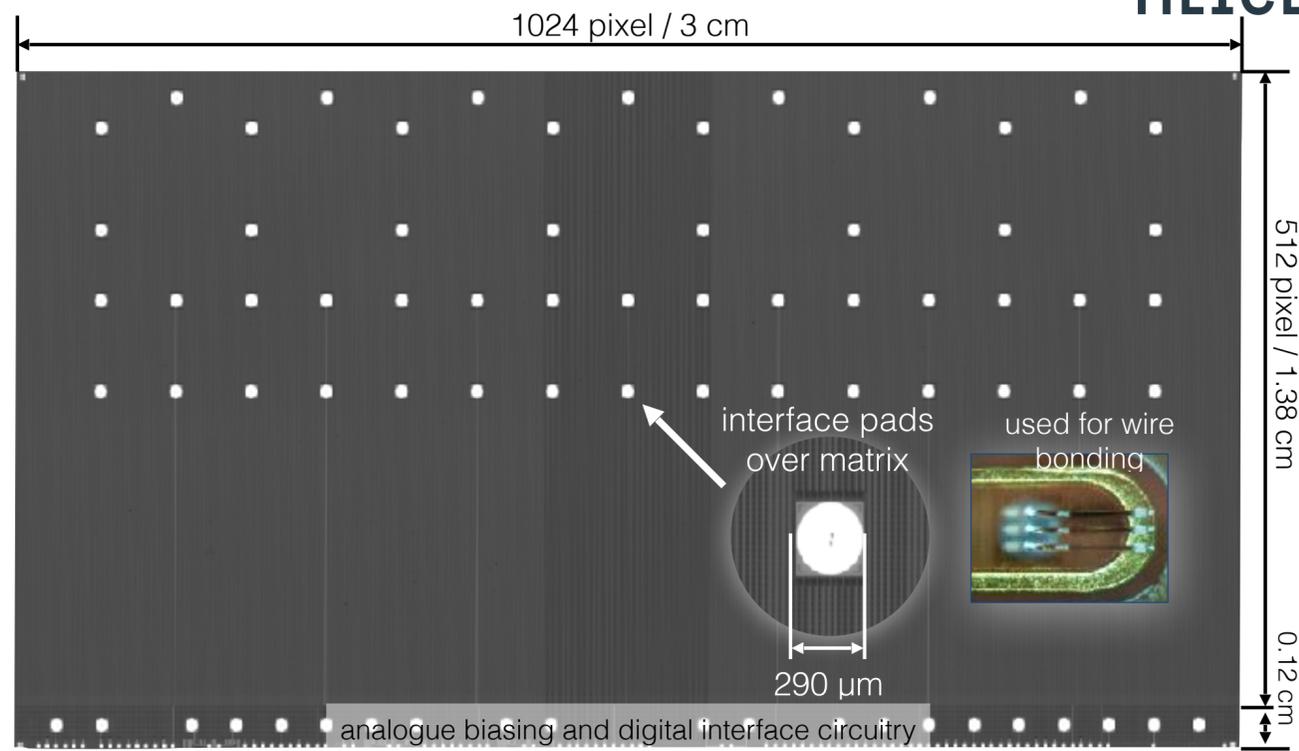


- ▶ Very dense integration inside pixel cell
  - amplifier, memories, testing
- ▶ Hit driven matrix readout
  - fast (zero skipping)
  - low power (digital information)
- ▶  $O(200)$  transistors per pixel

# The ALPIDE chip

## system level aspects

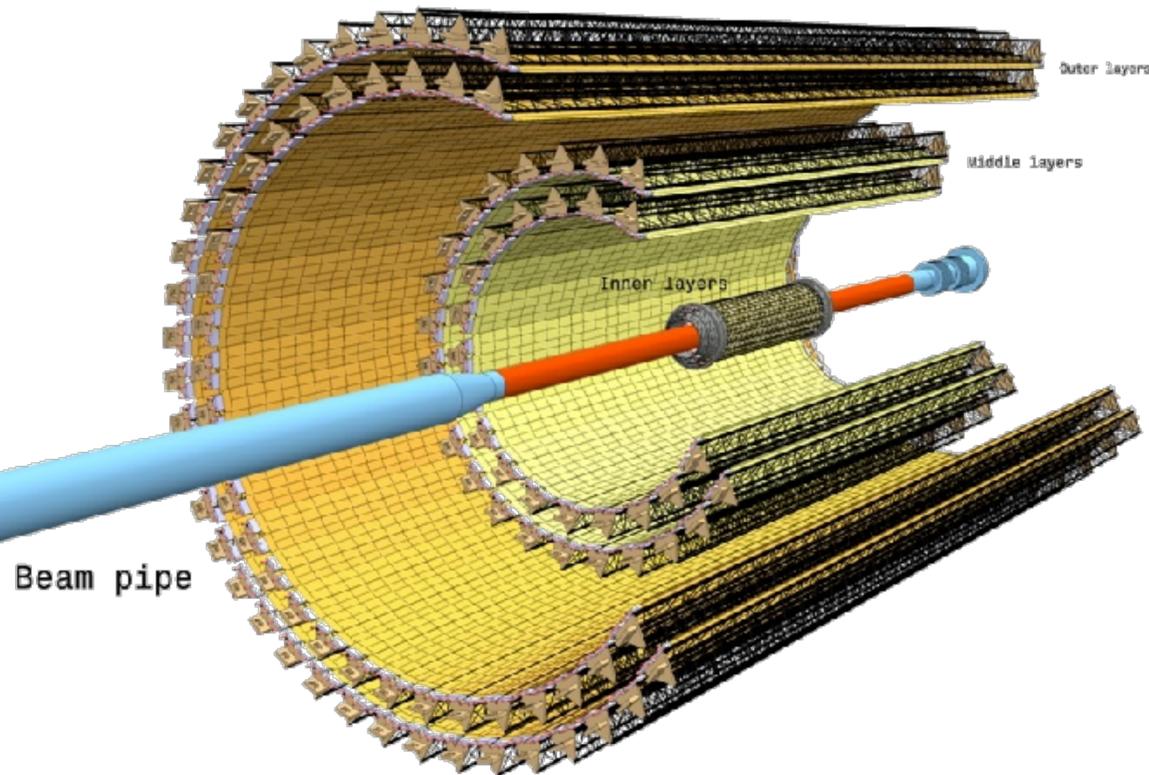
- ▶ Takes full advantage of TowerJazz CIS process:
  - 6 metal layers
  - small (180 nm) feature size
  - deep p-well
- ▶ Continuously active, in-pixel front-end, asynchronous readout (>100 transistors/pixel)
- ▶ Peripheral circuitry for biasing (DAC) and monitoring (ADC)
- ▶ On-chip PLL and serialiser to send data directly via 8 m of copper off-detector



**The final chip is much more than the pixel cell times half a million**

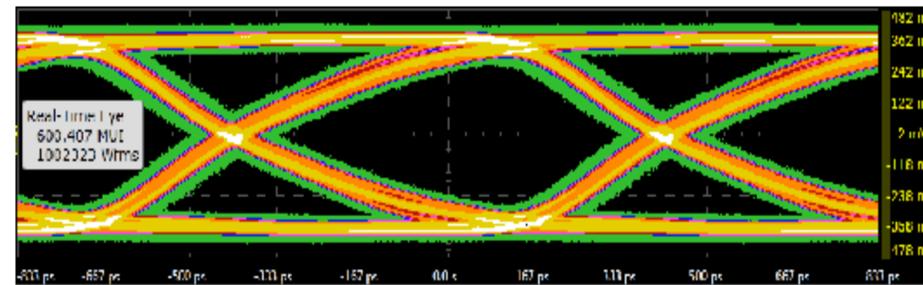
# Readout electronics

## Detector



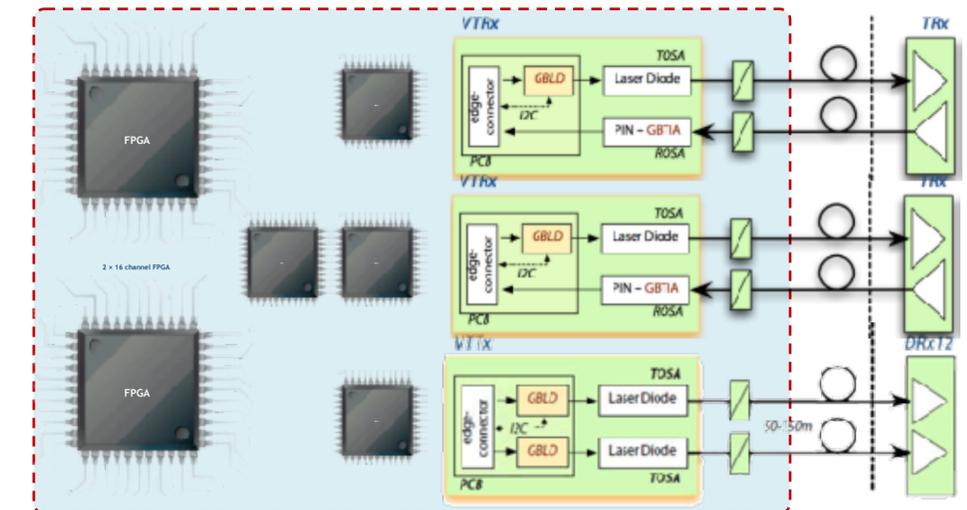
- Readout logic fully integrated into ALPIDE
- ALPIDE can directly drive 8 m cables using integrated high speed transmitters (up to 1.2 Gb/s)
- No further electronics on detector

## 8 m cable



- 1.2 Gb/s (data IB)
- 400 Mb/s (data OB)
- 80 Mb/s (ctrl IB/OB)
- clock
- power

## Readout Units



- Total: 192 Readout Units
- Distribute trigger and control signals
- Interface data links to ALICE DAQ
- Control power supply of chips
- Radiation level low enough to use (selected!) off-the-shelf electronics + soft-error mitigation techniques

**Integration of as much as possible into ALPIDE simplified system**  
**Still, radiation at position of readout unit requires work**



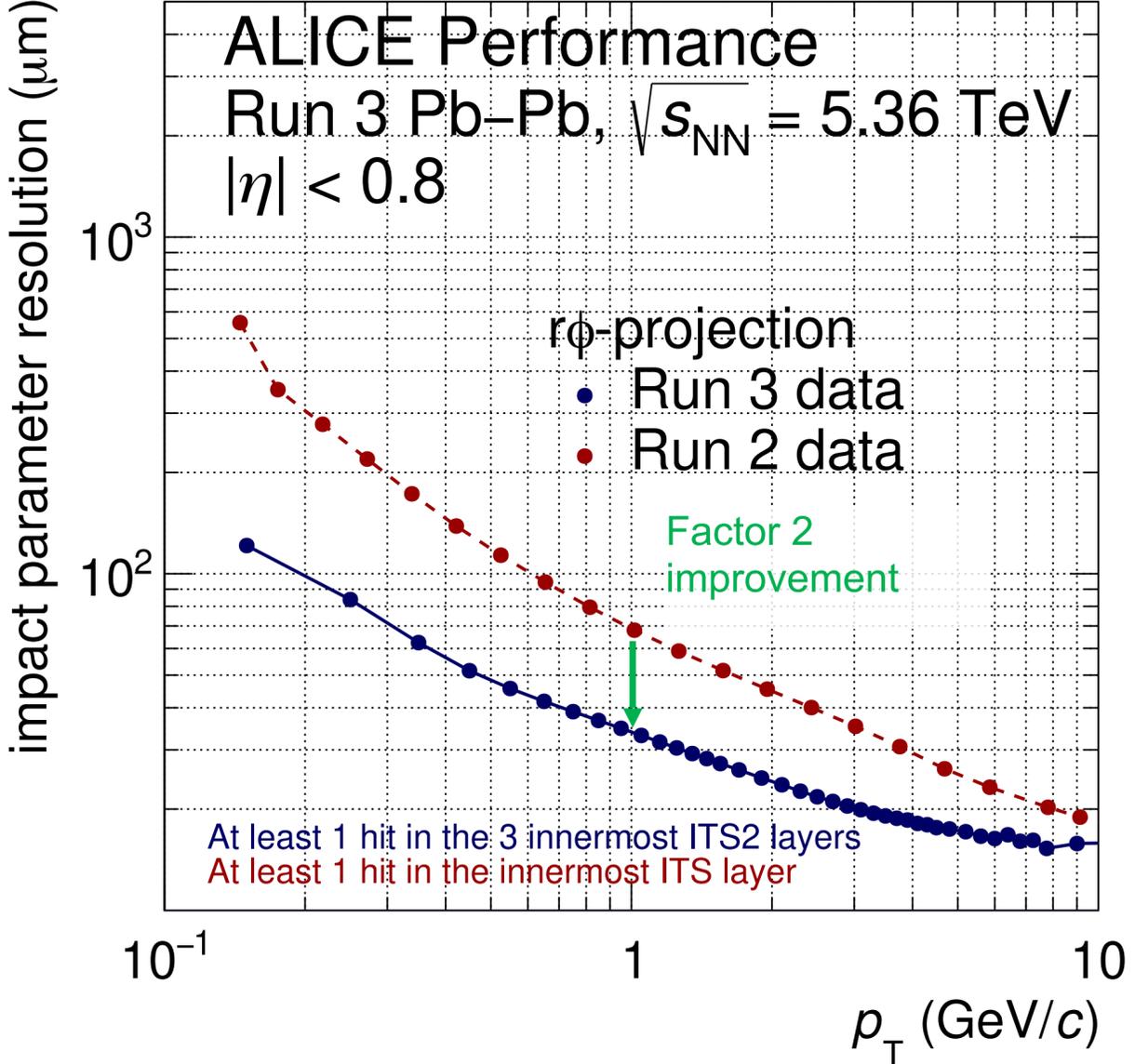
ALICE

**Pb-Pb 5.36 TeV**

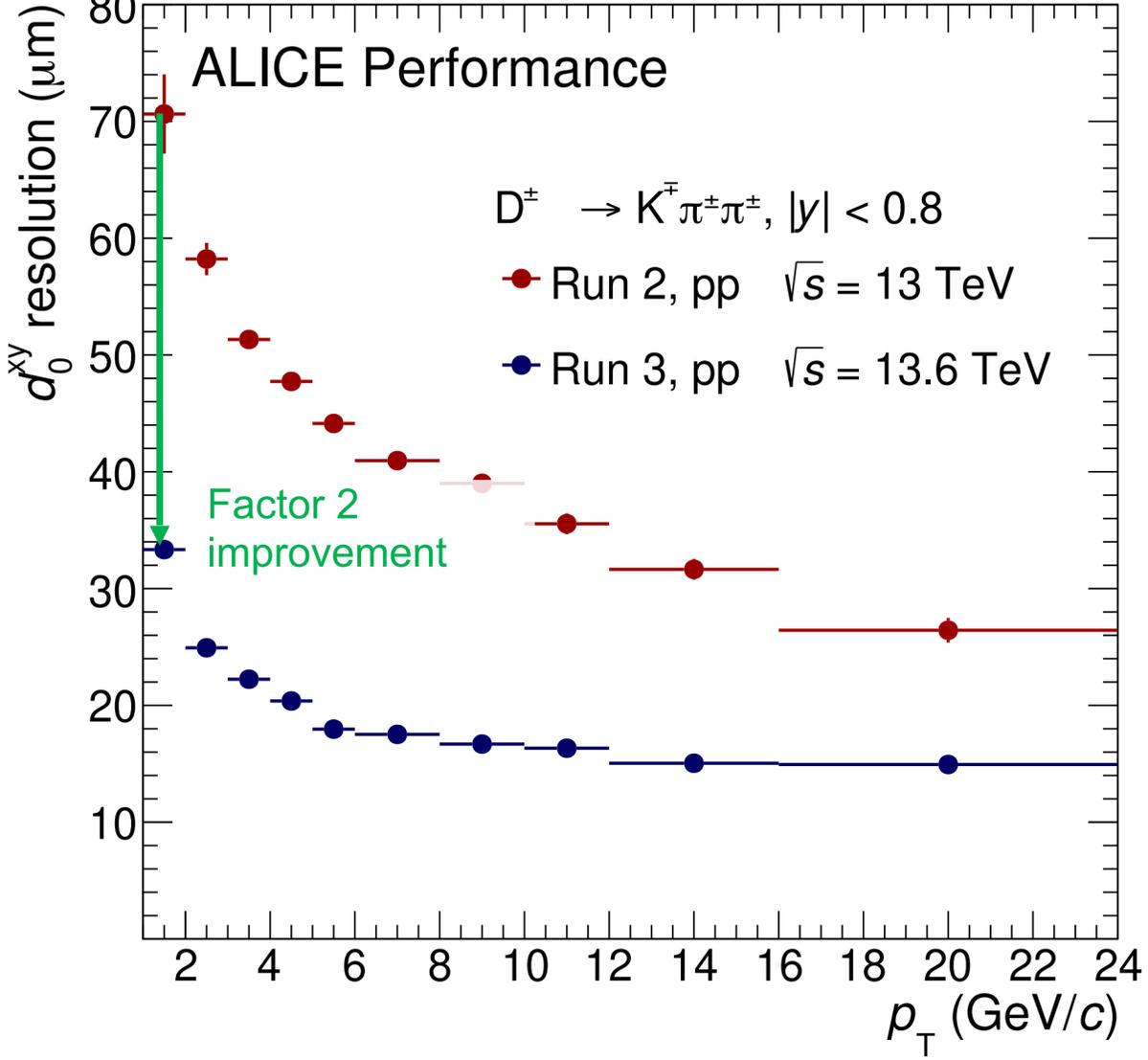
LHC22s period  
18<sup>th</sup> November 2022

16:52:47.893

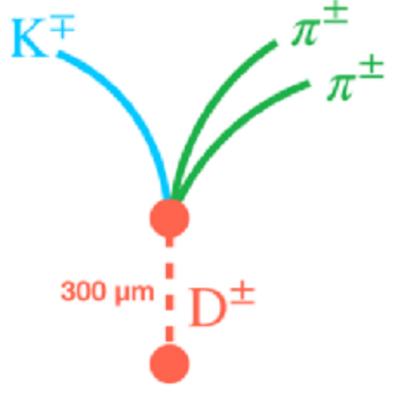
# Resolution improvement



ALI-PERF-564335



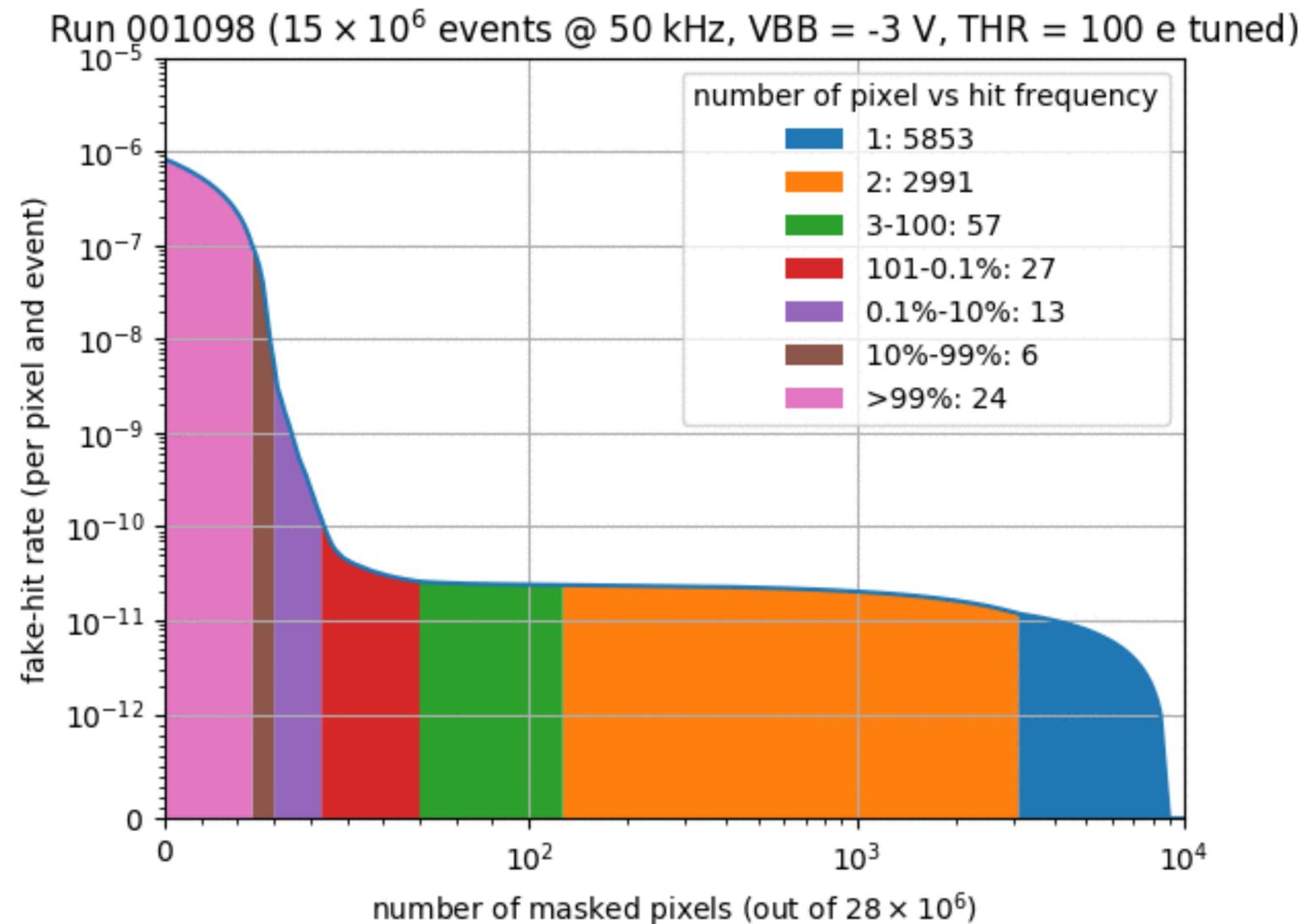
ALI-PERF-597787



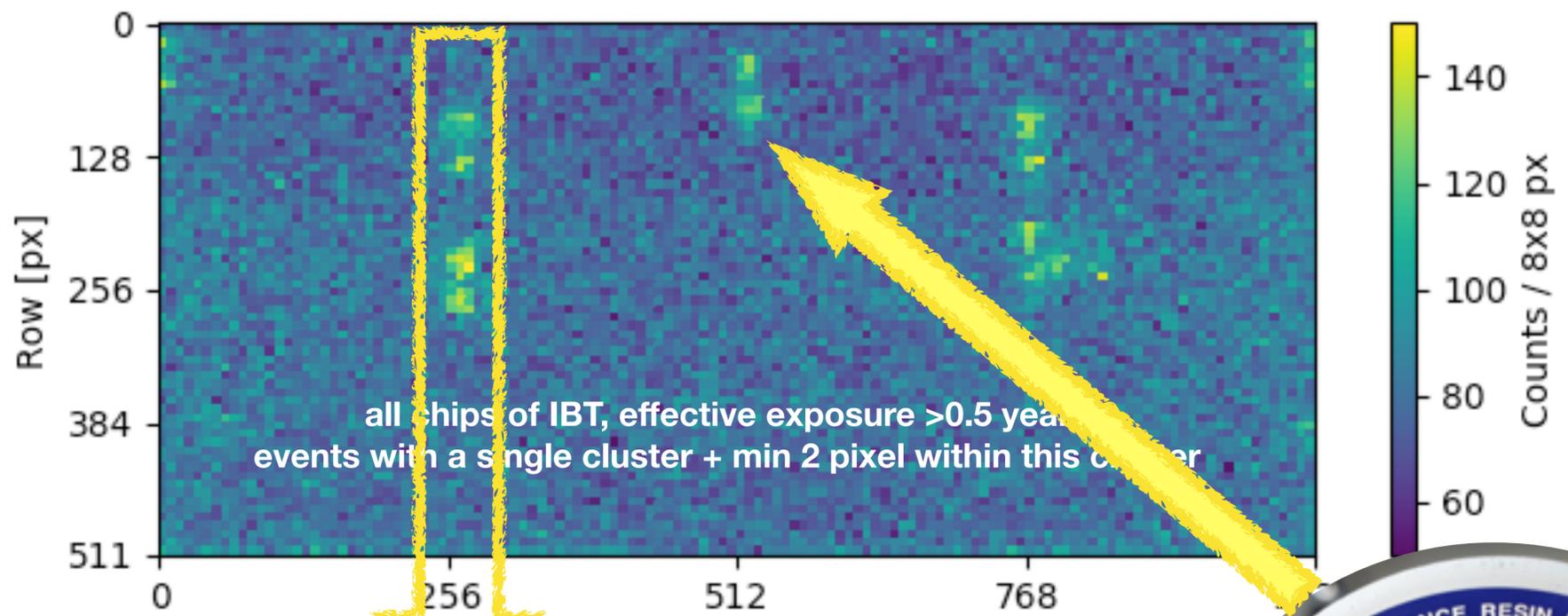
Improved impact parameter resolution for charged tracks and  $D^{\pm}$  mesons

# ALICE ITS2

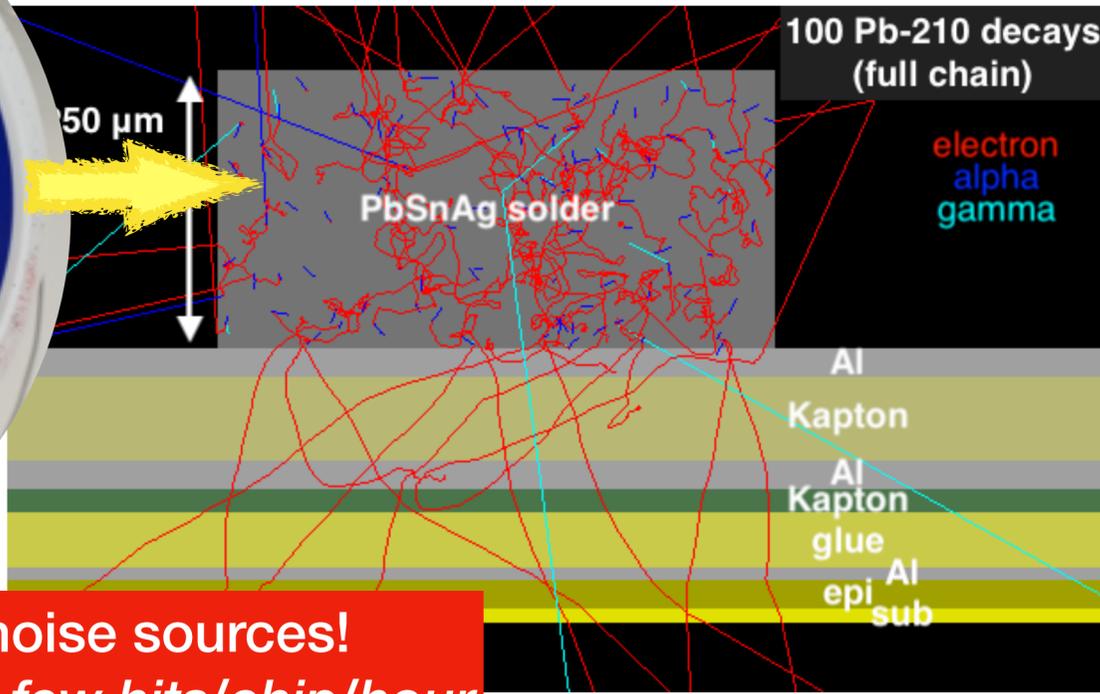
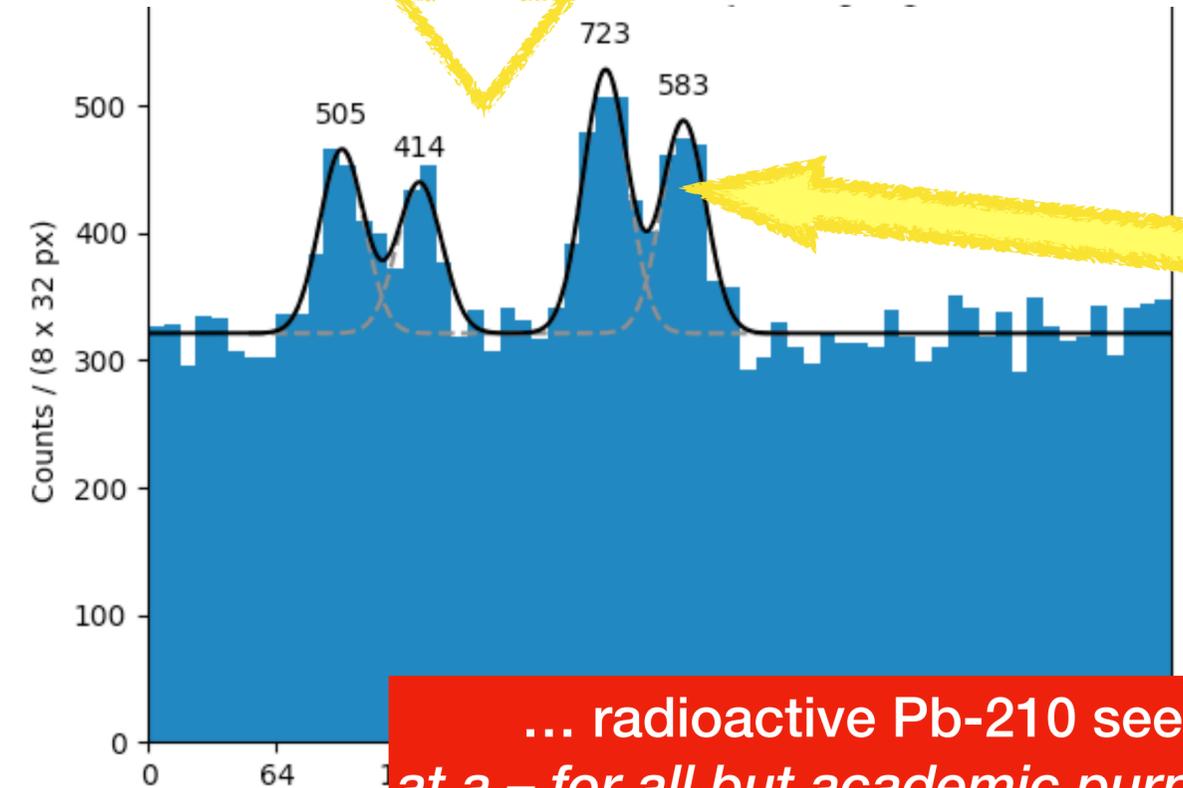
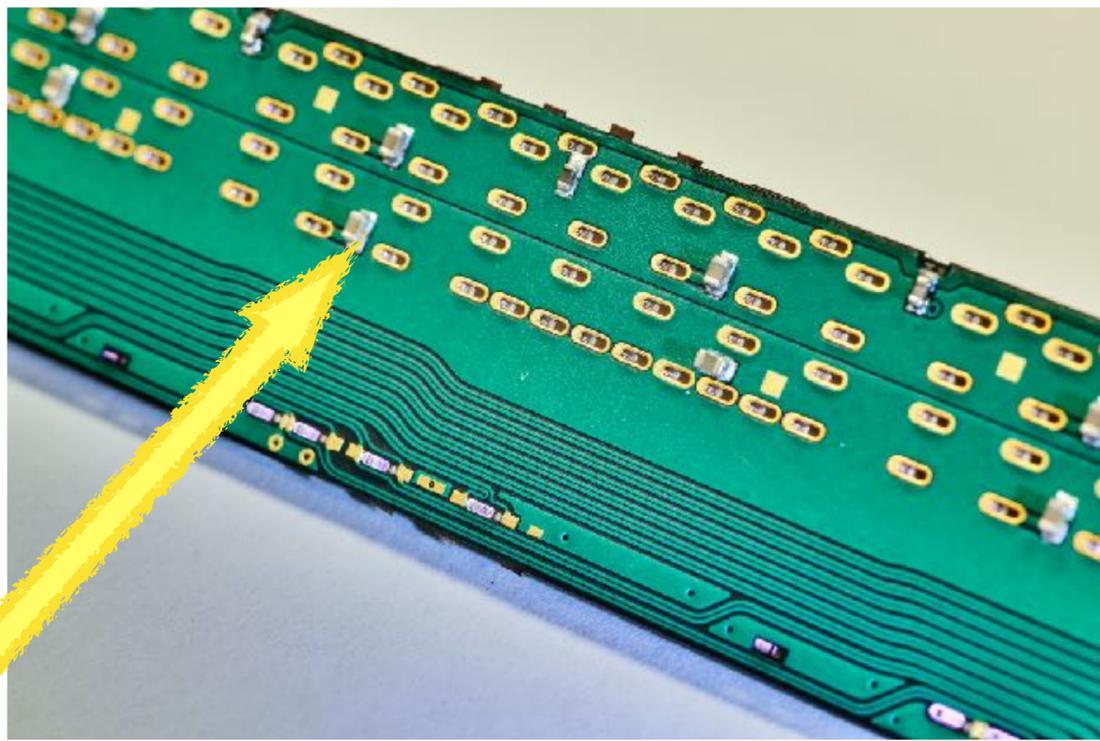
- ▶ This is the real rate measured on-detector, including final services
- ▶ Essentially, apart from a hand-full pixels per chip, the detector is **noise-free**
- ▶ Biggest contributor is natural radiation (which is *not* excluded here)
- ▶ Indeed, mitigation of Random Telegraph Signal noise (RTS noise / RTN) was a major achievement in the APIDE R&D



# ITS2 performance



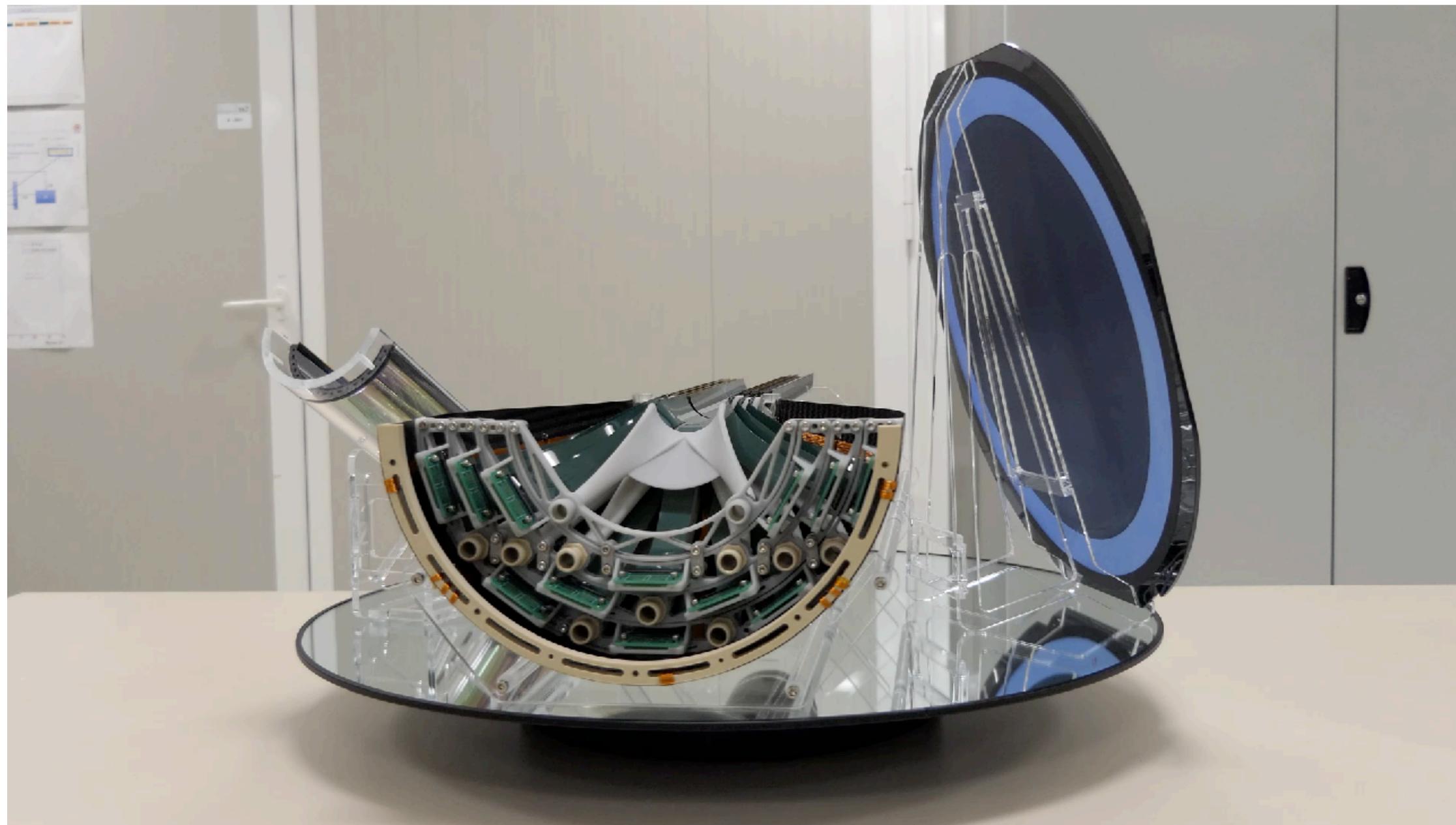
all chips of IBT, effective exposure >0.5 year  
events with a single cluster + min 2 pixel within this cluster



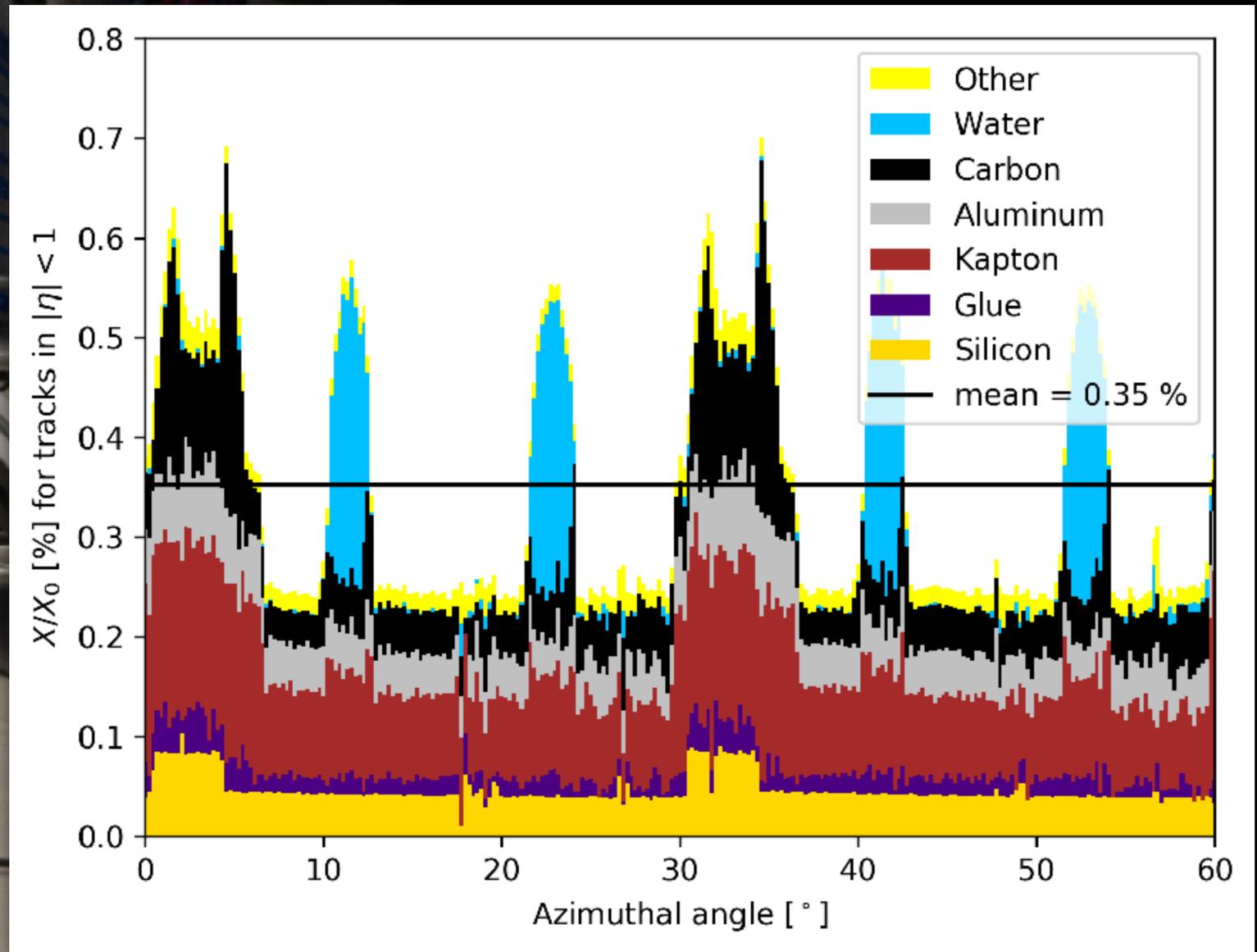
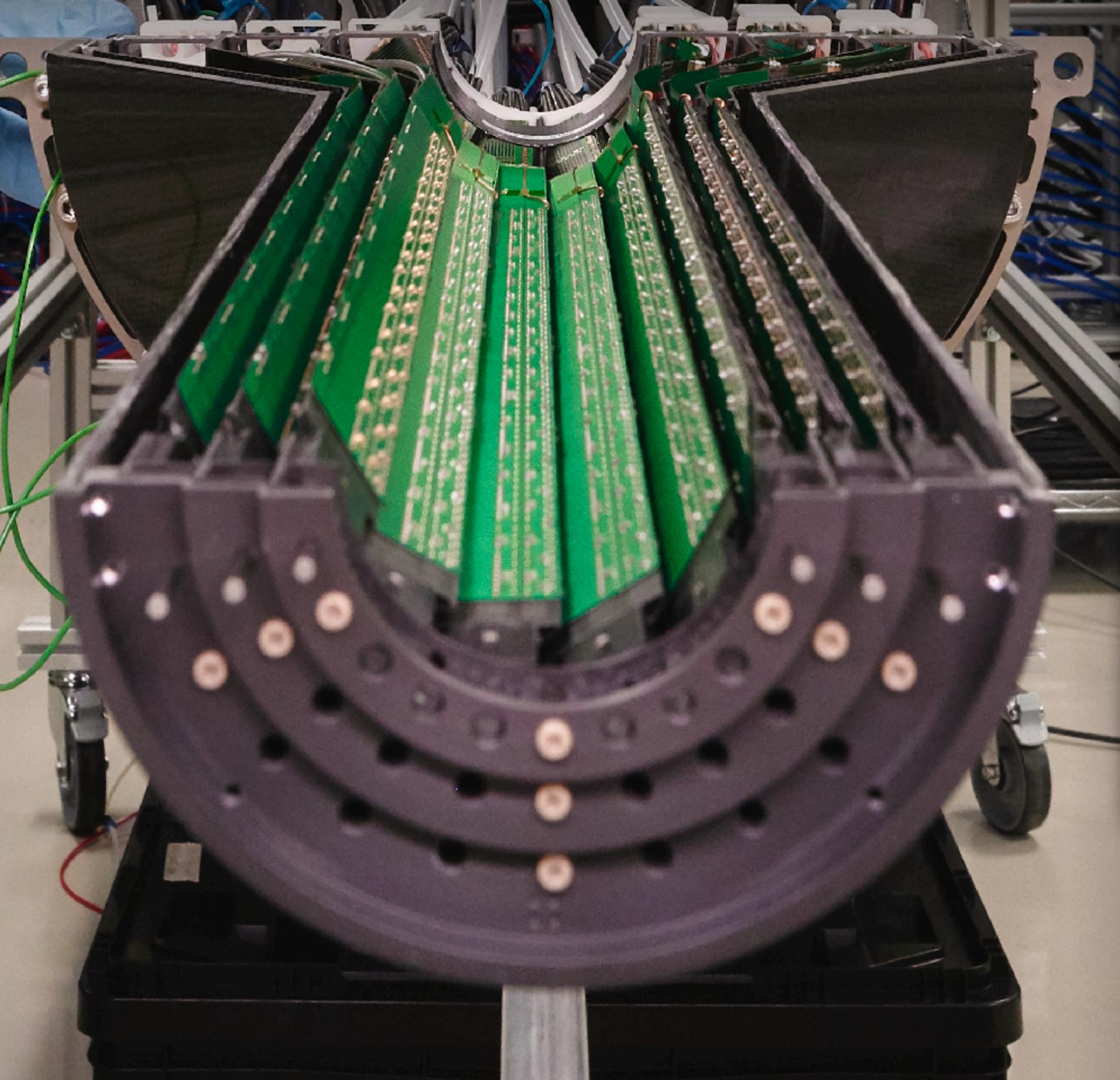
... radioactive Pb-210 seems to be one of the main real noise sources!  
at a – for all but academic purposes – negligible rate of totals few hits/chip/hour

[TDR: ALICE-TDR-021]

# ITS3



# ITS2 Inner Barrel

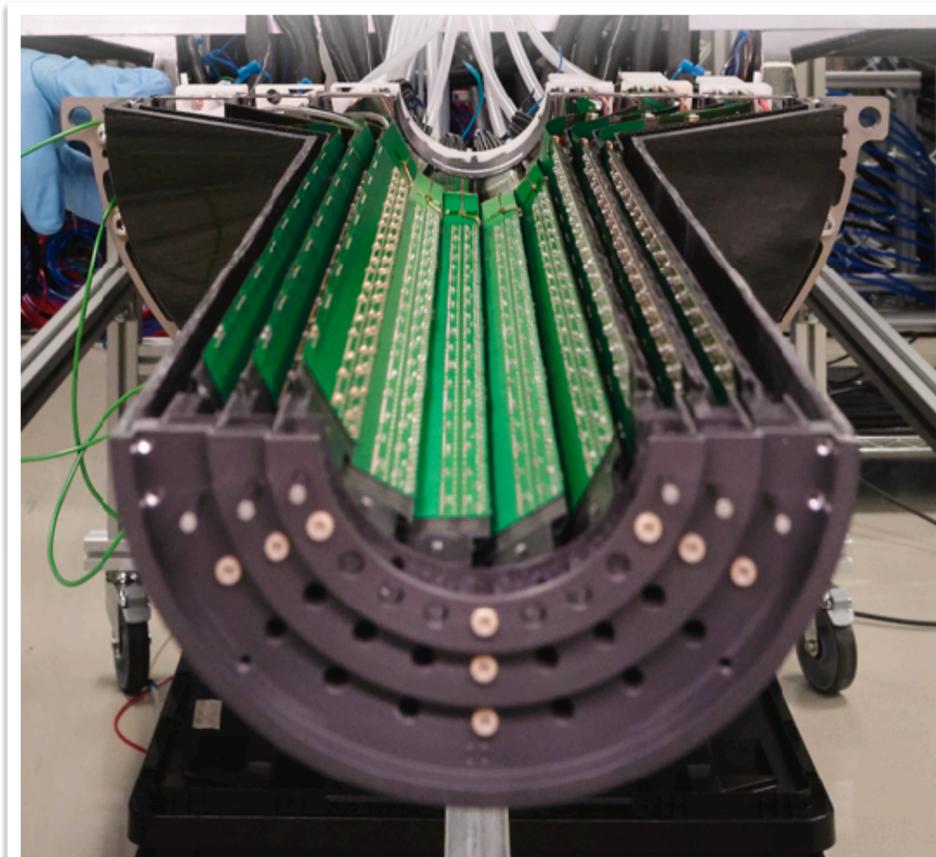


Very light detector (0.35%  $X_0$ )

Yet, dominated by support structures

# ALICE ITS3

conceptual idea



Only 1/7th of the material budget!

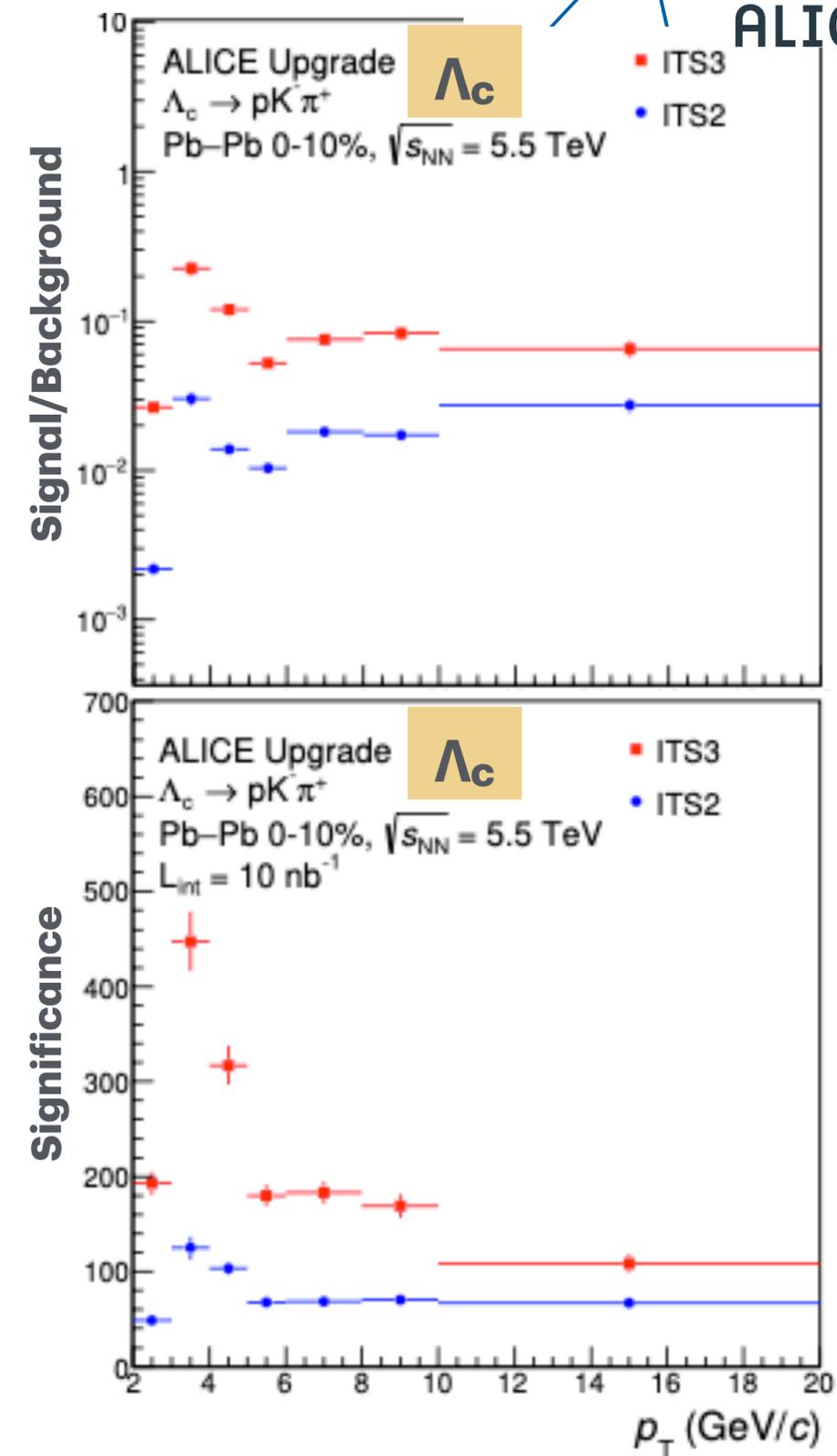
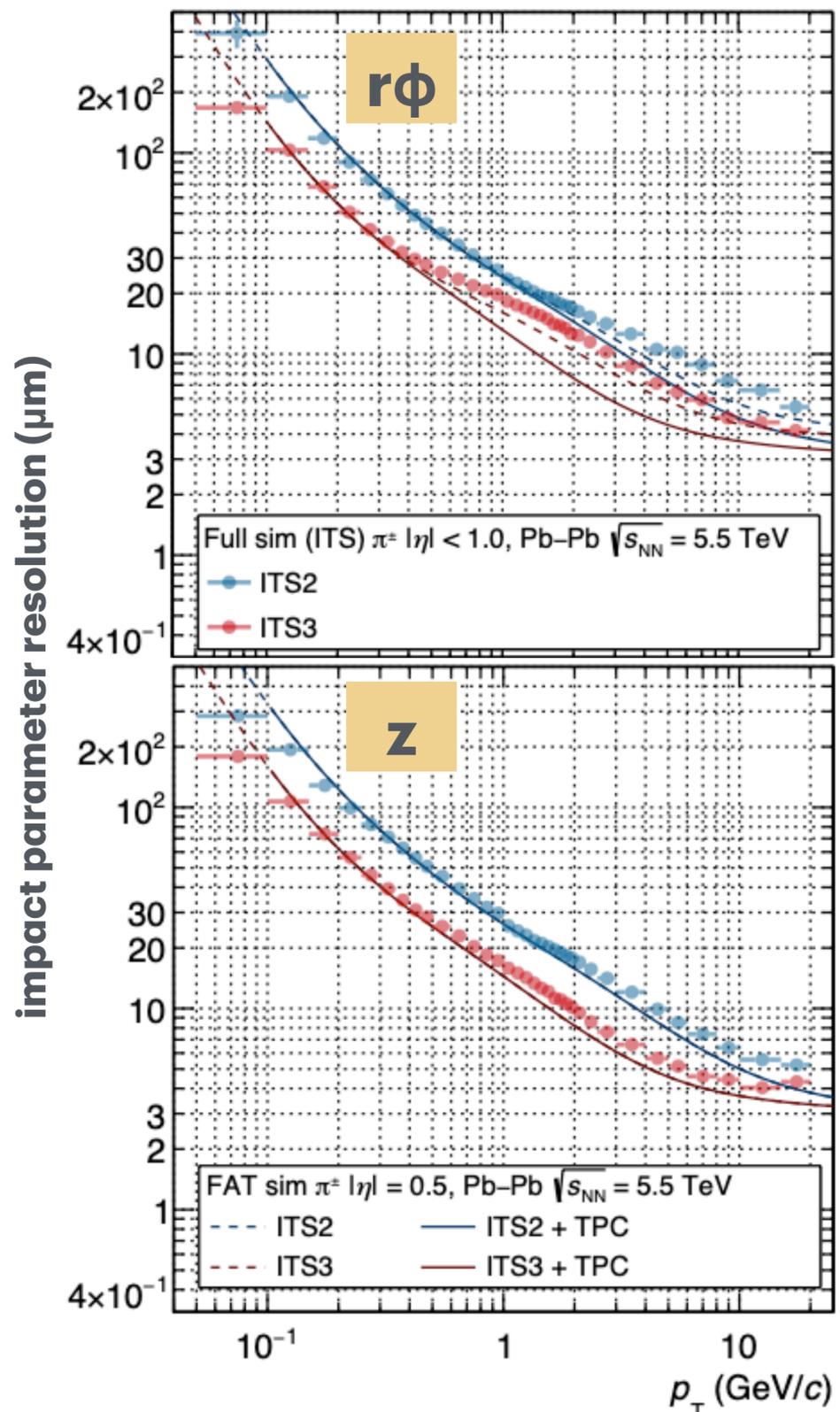
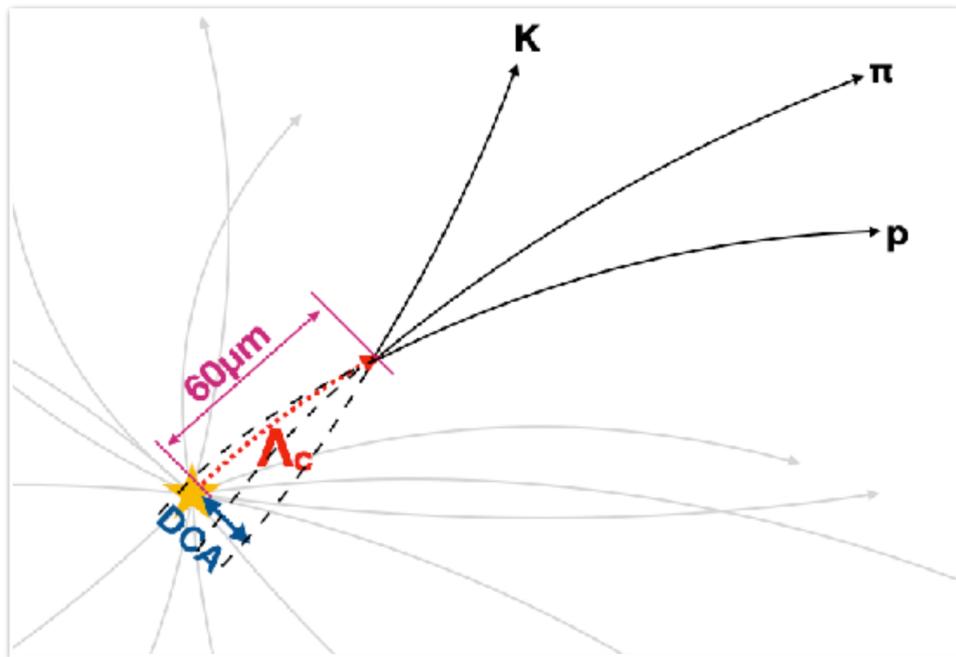
- ▶ Replacing the barrels by real half-cylinders (of **bent, thin** silicon)
- ▶ Rely on **wafer-scale sensors** (1 sensor per half-layer) in **65 nm** technology
- ▶ **Minimized material budget** → large improvement of vertexing precision and physics yield (“**ideal detector**”)

# Projected performance boost

- ▶ Improvement of pointing resolution by:
  - drastic reduction of **material budget** (0.3 → 0.07% X0/layer)
  - being **closer** to the interaction point (24 → 19 mm)
  - thinner and smaller **beam pipe** (700 → 500 μm; 18 → 16 mm)

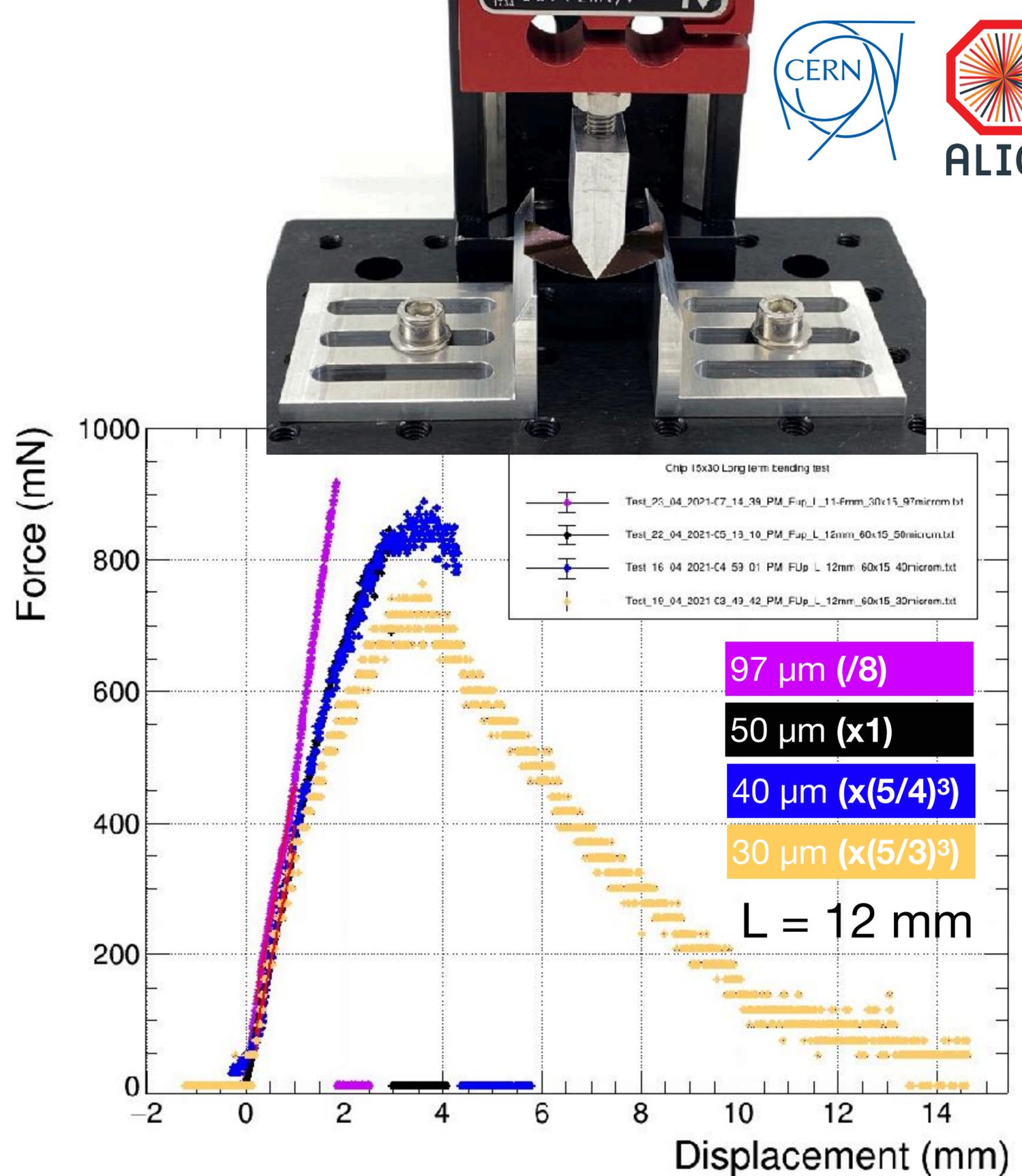
- ▶ Directly boosts the ALICE core physics program:
  - low momenta
  - secondary vertex reconstruction

- ▶ E.g.  $\Lambda_c$  S/B improves by factor 10, significance by factor 4



# Flexibility of silicon

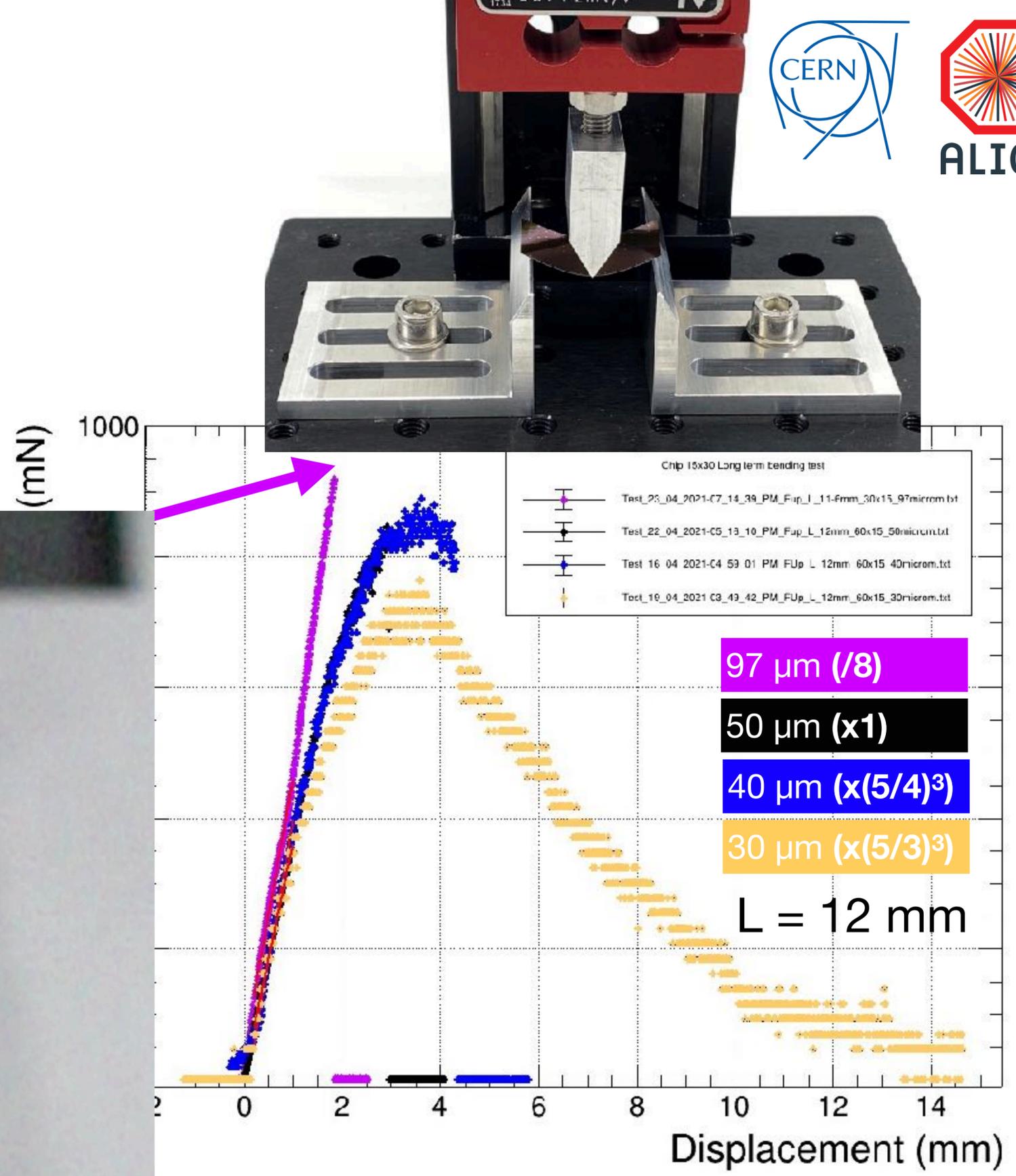
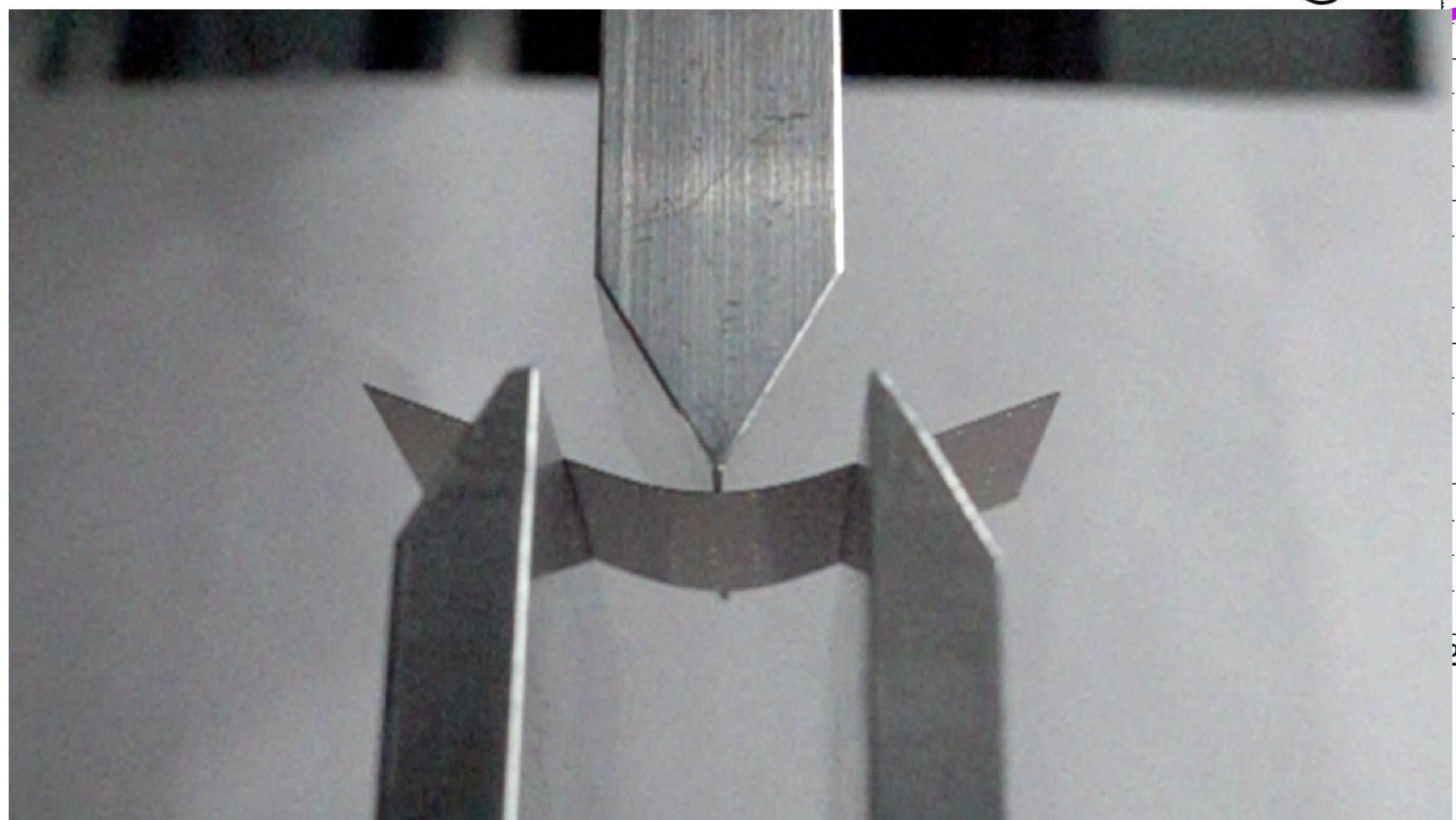
- ▶ **Monolithic Active Pixel Sensors** are quite flexible
- ▶ Bending force scales as  $(\text{thickness})^{-3}$ 
  - large benefit from thinner sensors



# Flexibility of silicon



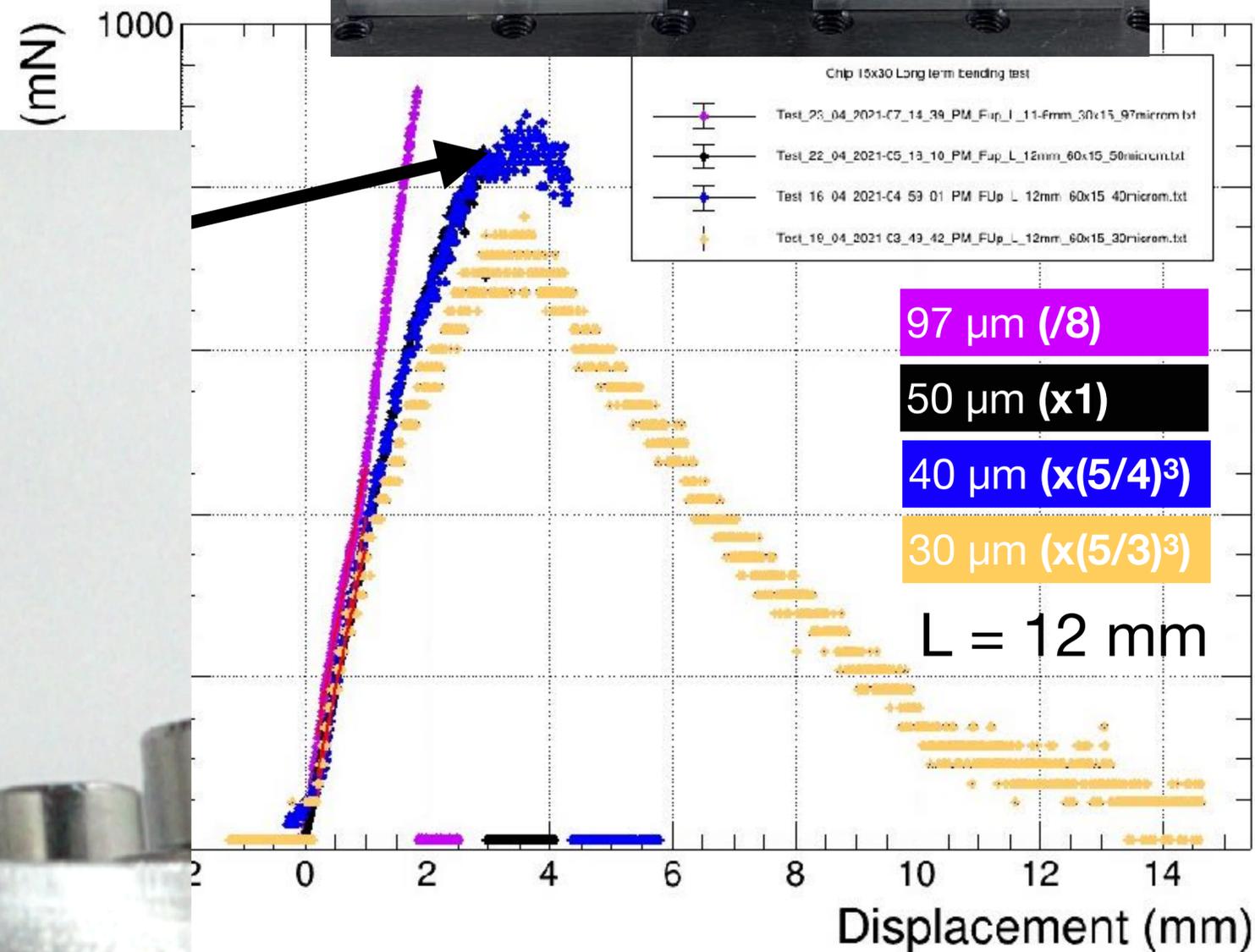
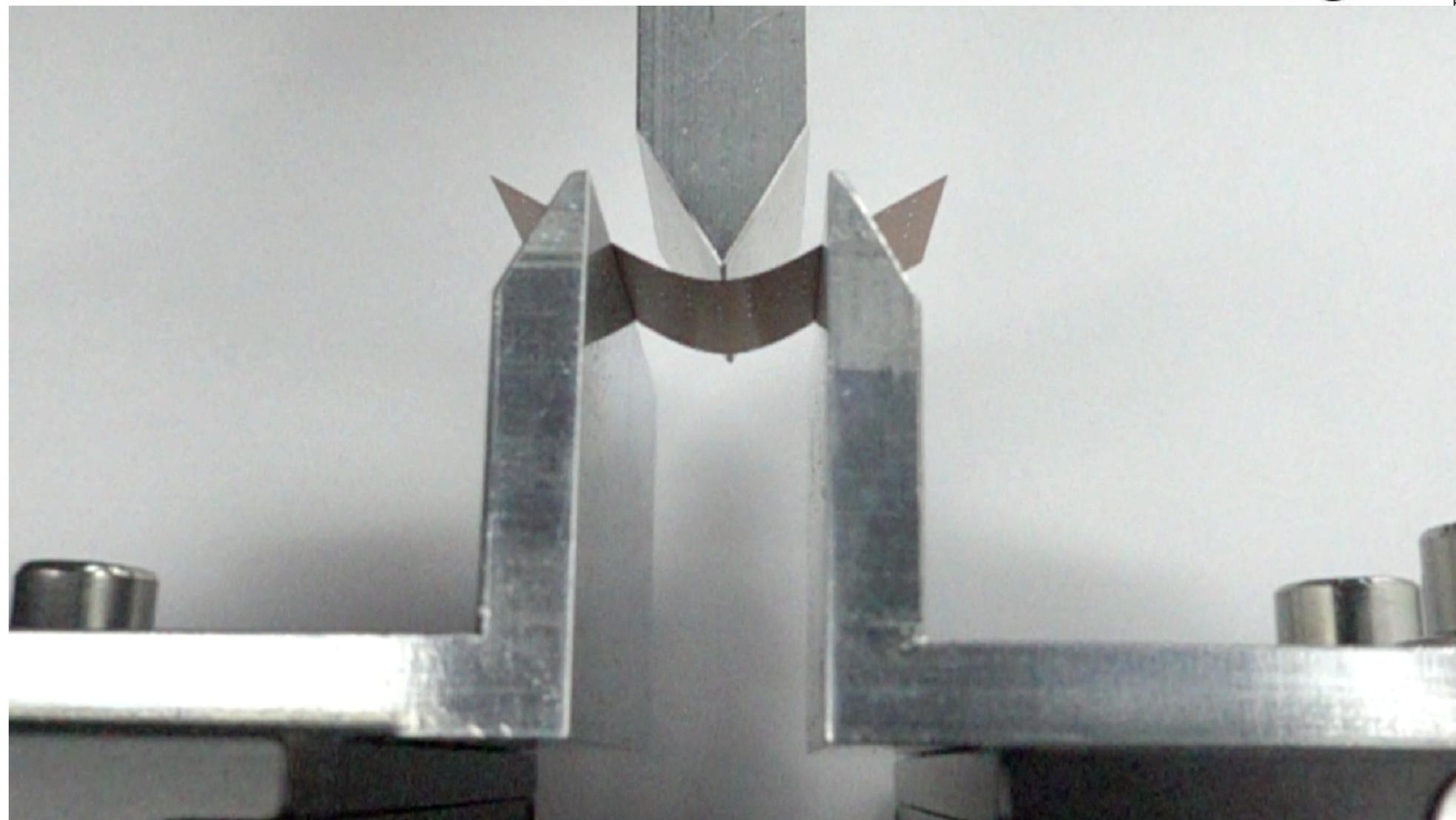
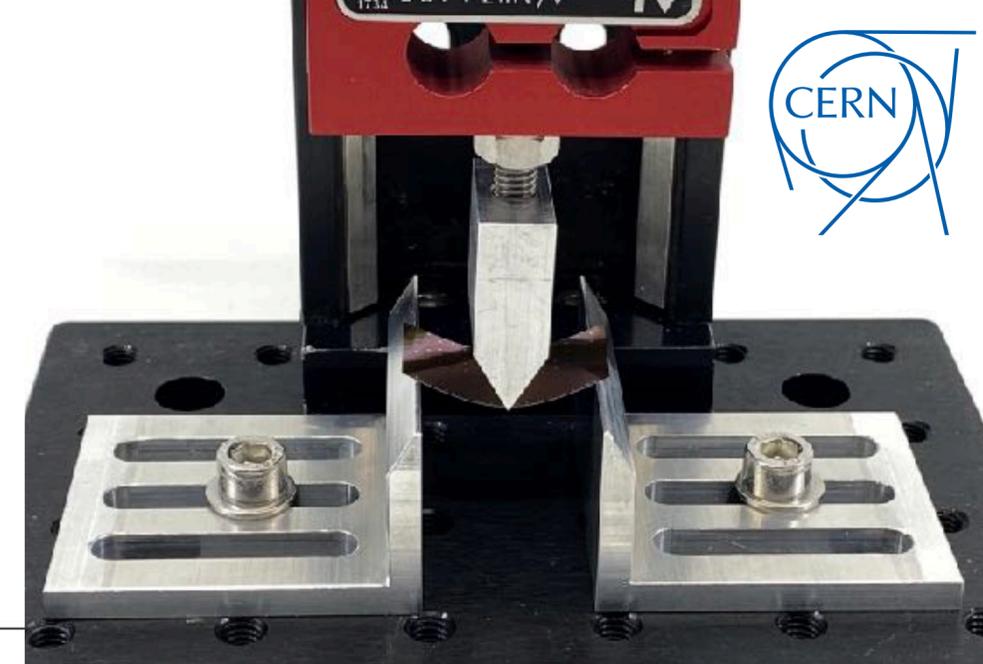
- ▶ **Monolithic Active Pixel Sensors** are quite flexible
- ▶ Bending force scales as (thickness)<sup>-3</sup>
  - large benefit from thinner sensors



# Flexibility of silicon



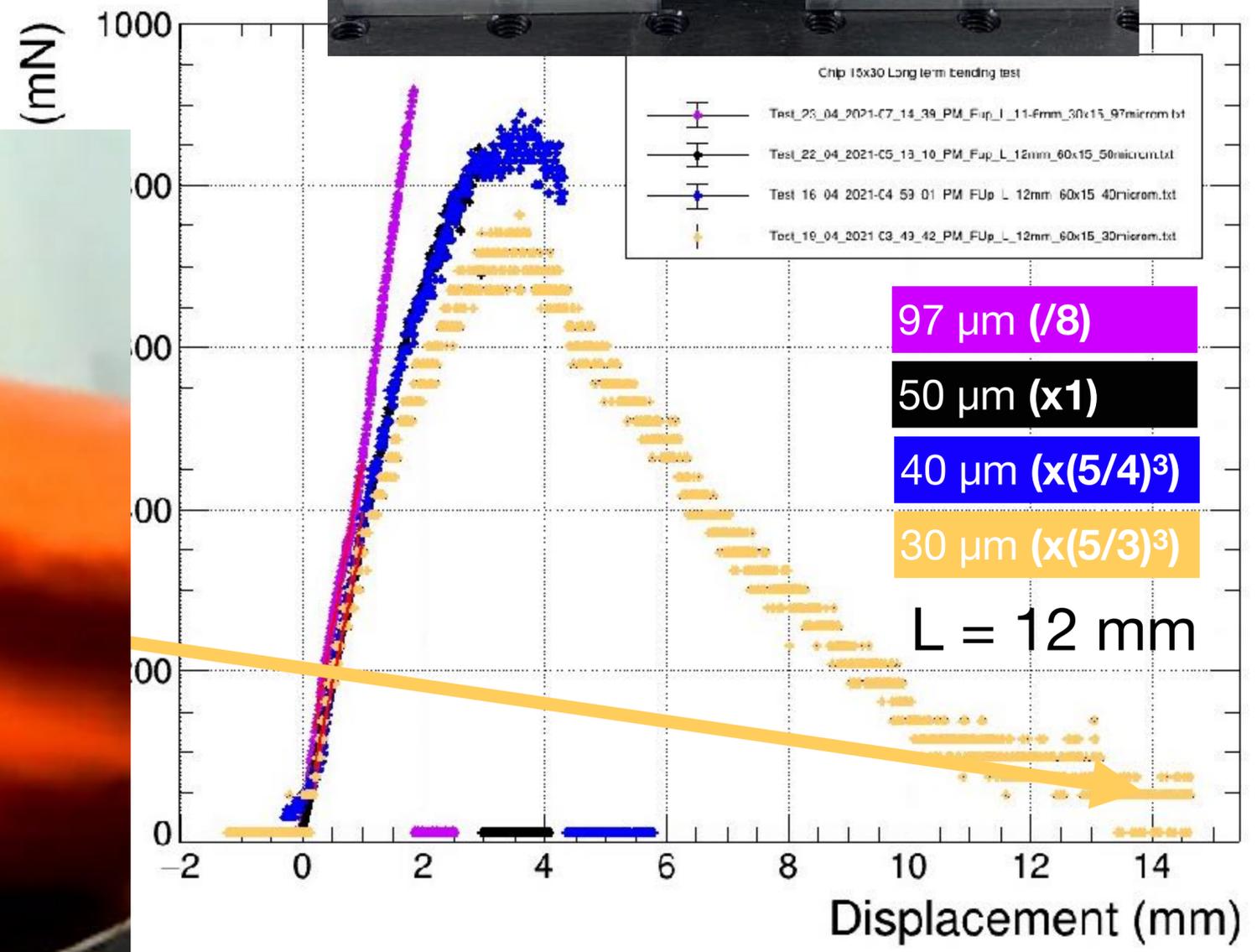
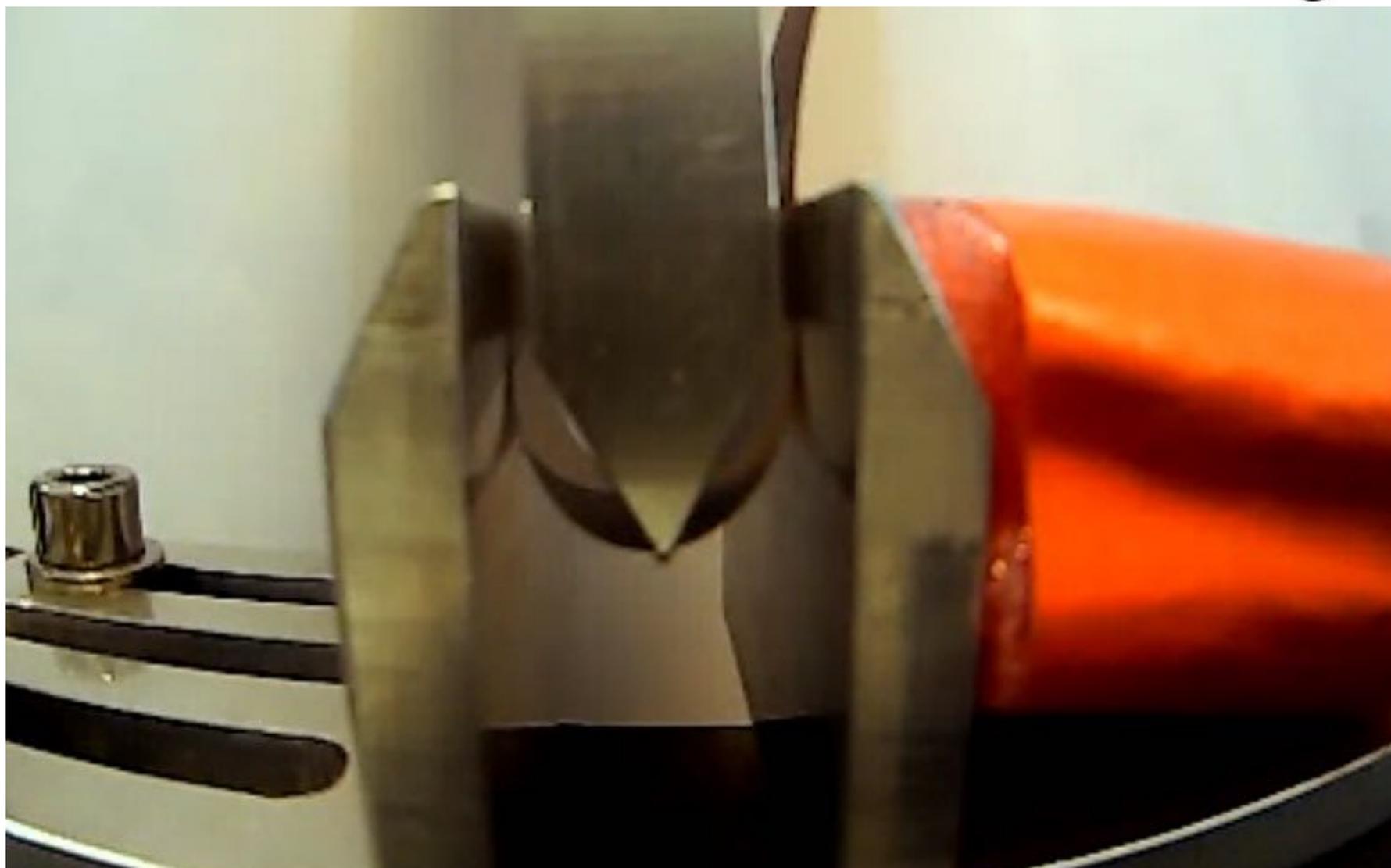
- ▶ **Monolithic Active Pixel Sensors** are quite flexible
- ▶ Bending force scales as (thickness)<sup>-3</sup>
  - large benefit from thinner sensors



# Flexibility of silicon



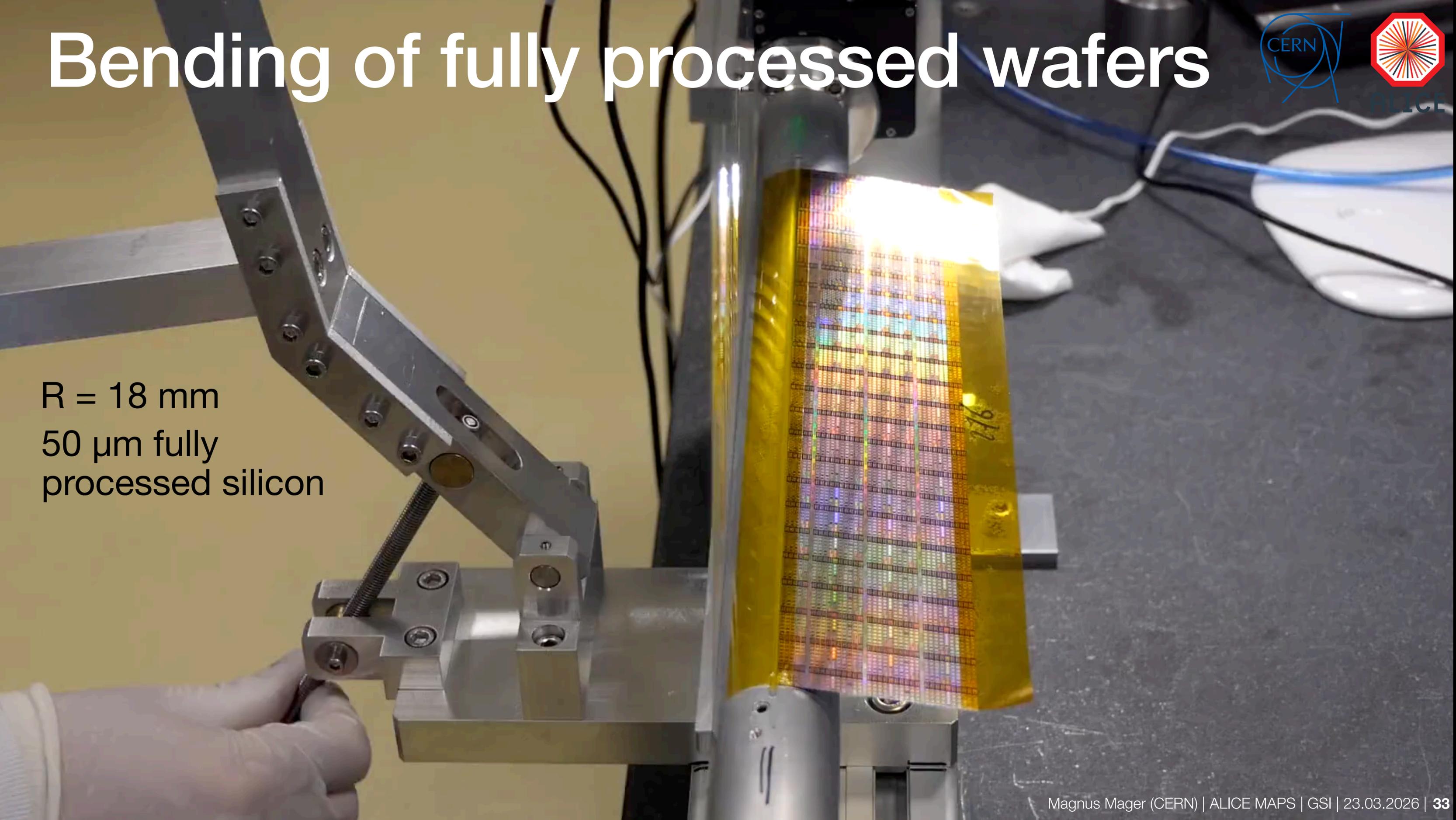
- ▶ **Monolithic Active Pixel Sensors** are quite flexible
- ▶ Bending force scales as (thickness)<sup>-3</sup>
  - large benefit from thinner sensors



# Bending of fully processed wafers

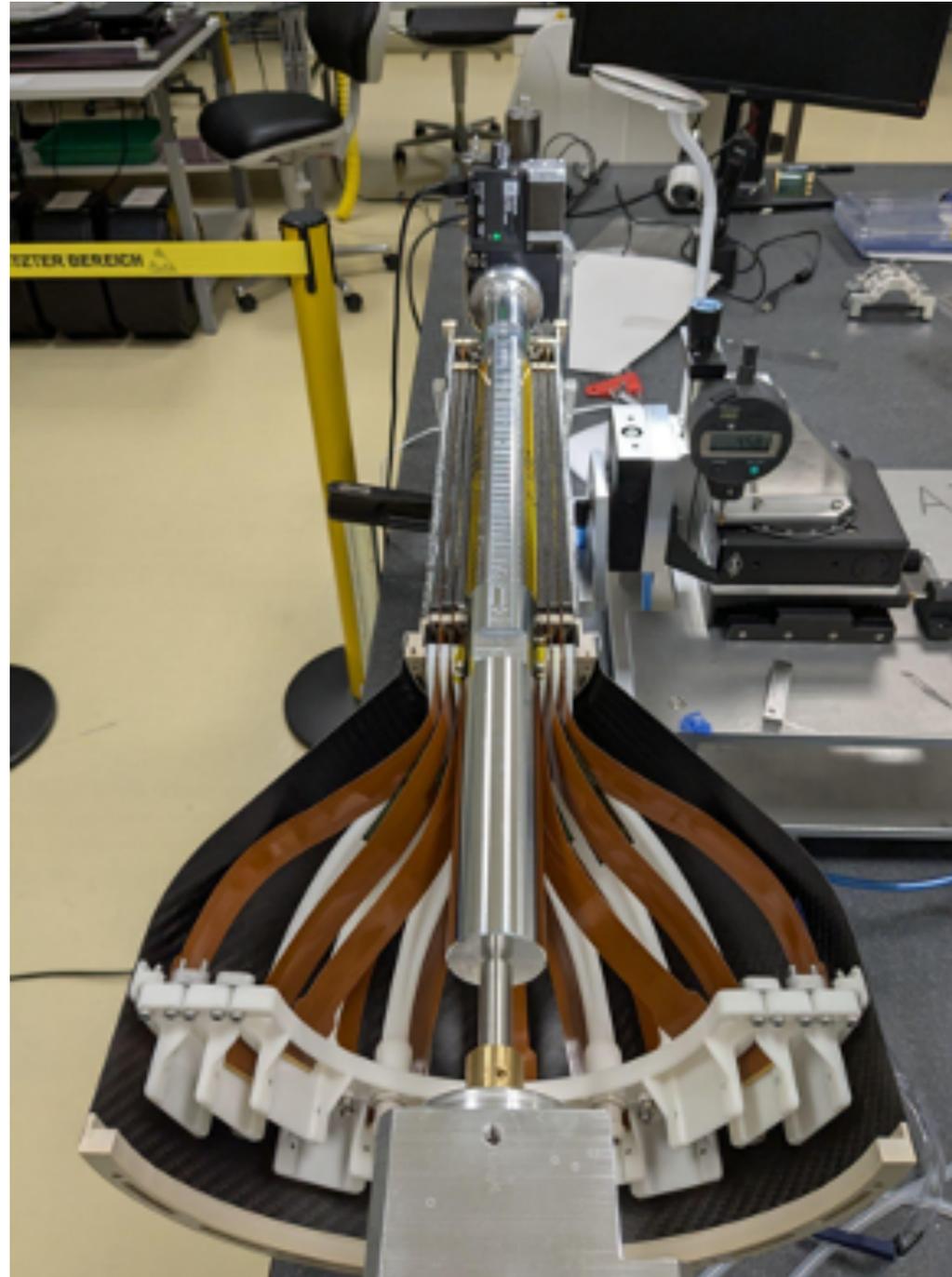
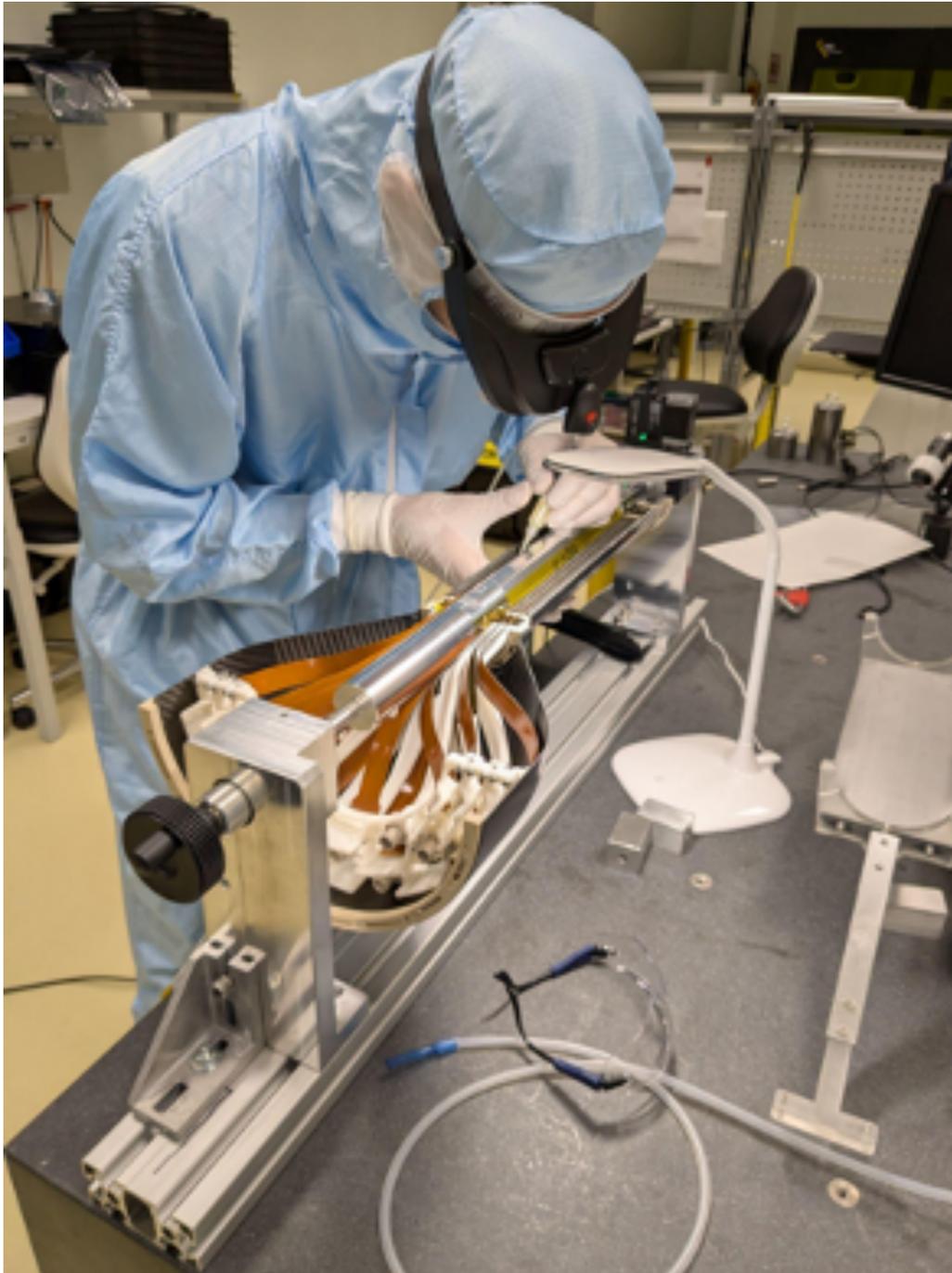


R = 18 mm  
50  $\mu\text{m}$  fully  
processed silicon

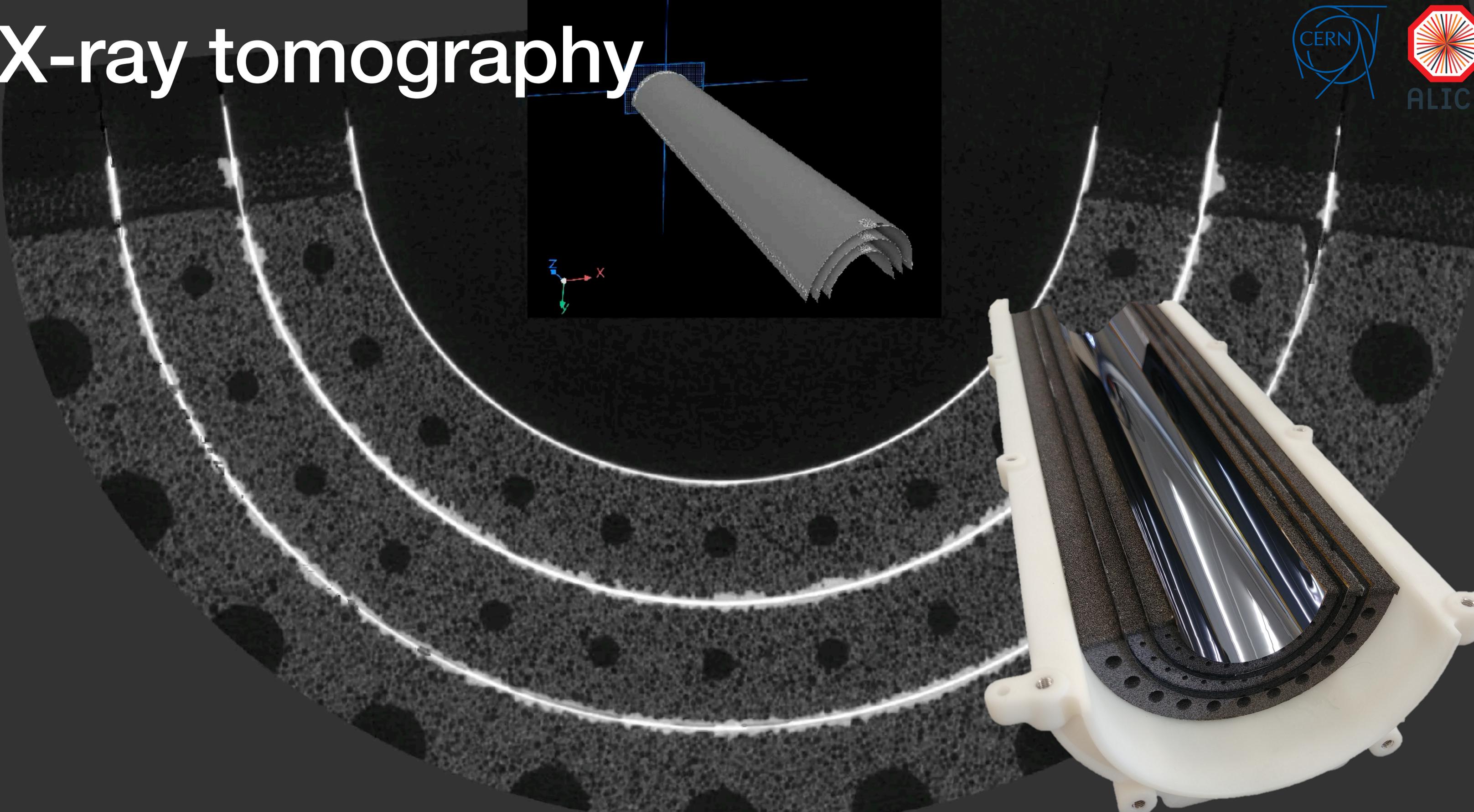


# Engineering Models

including services



# X-ray tomography



# Next technology node: 180 nm → 65 nm



## ► Key benefits:

- smaller features/transistors: higher integration density
- smaller pitches
- lower power consumption
- larger wafers

## ► ALICE ITS3 together with CERN EP R&D

- leverages on experience with 180 nm (ALPIDE)
- excellent links to foundry

## ► Works excellently!



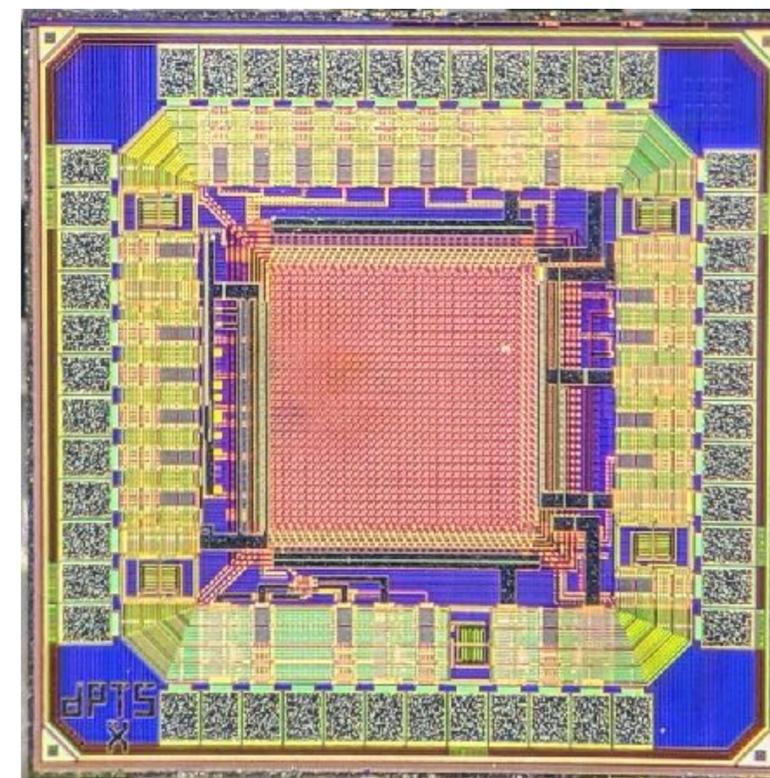
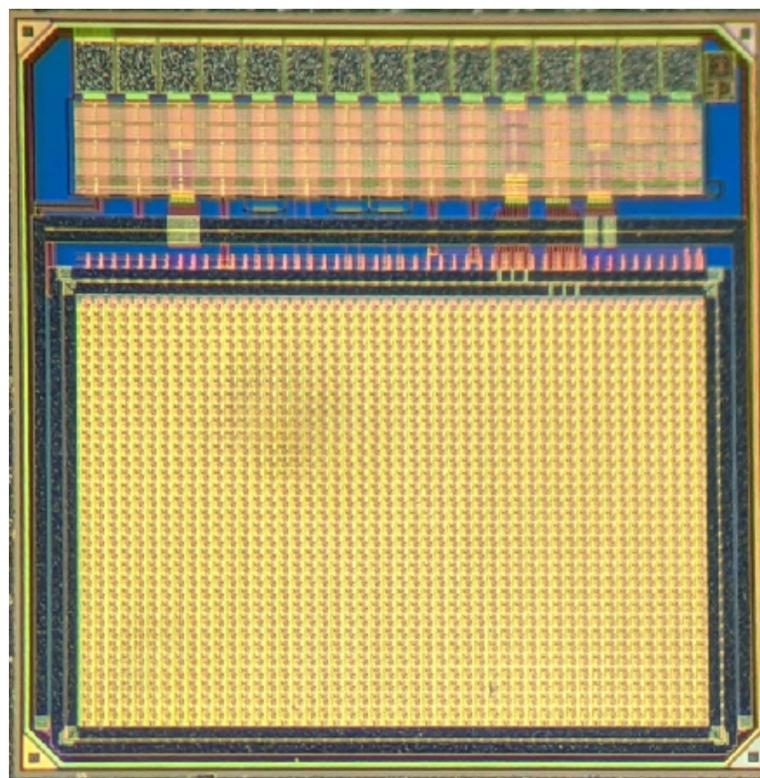
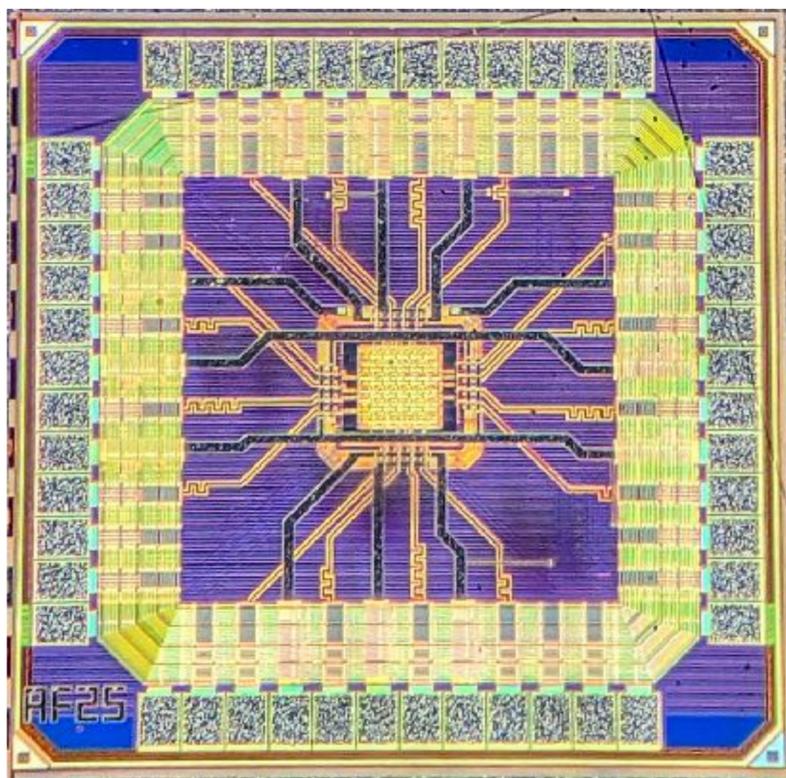
# 65 nm technology qualification

## APTS

## CE65

## DPTS

1.5 mm



- ▶ **matrix:** 6x6 pixels
- ▶ **readout:** direct analog readout of central 4x4
- ▶ **pitch:** 10, 15, 20, 25  $\mu\text{m}$
- ▶ **total:** 34 variants

- ▶ **matrix:** 64x32, 48x32 pixels
- ▶ **readout:** rolling shutter analog
- ▶ **pitch:** 15, 25  $\mu\text{m}$
- ▶ **total:** 4 variants

- ▶ **matrix:** 32x32 pixels
- ▶ **readout:** async. digital with ToT
- ▶ **pitch:** 15  $\mu\text{m}$
- ▶ **total:** 3 variants

[[doi:10.1016/j.nima.2024.169896](https://doi.org/10.1016/j.nima.2024.169896)]

[[doi:10.1016/j.nima.2024.170034](https://doi.org/10.1016/j.nima.2024.170034)]

[[doi:10.48550/arXiv.2512.13339](https://doi.org/10.48550/arXiv.2512.13339)]

[[doi:10.1016/j.nima.2022.167213](https://doi.org/10.1016/j.nima.2022.167213)]

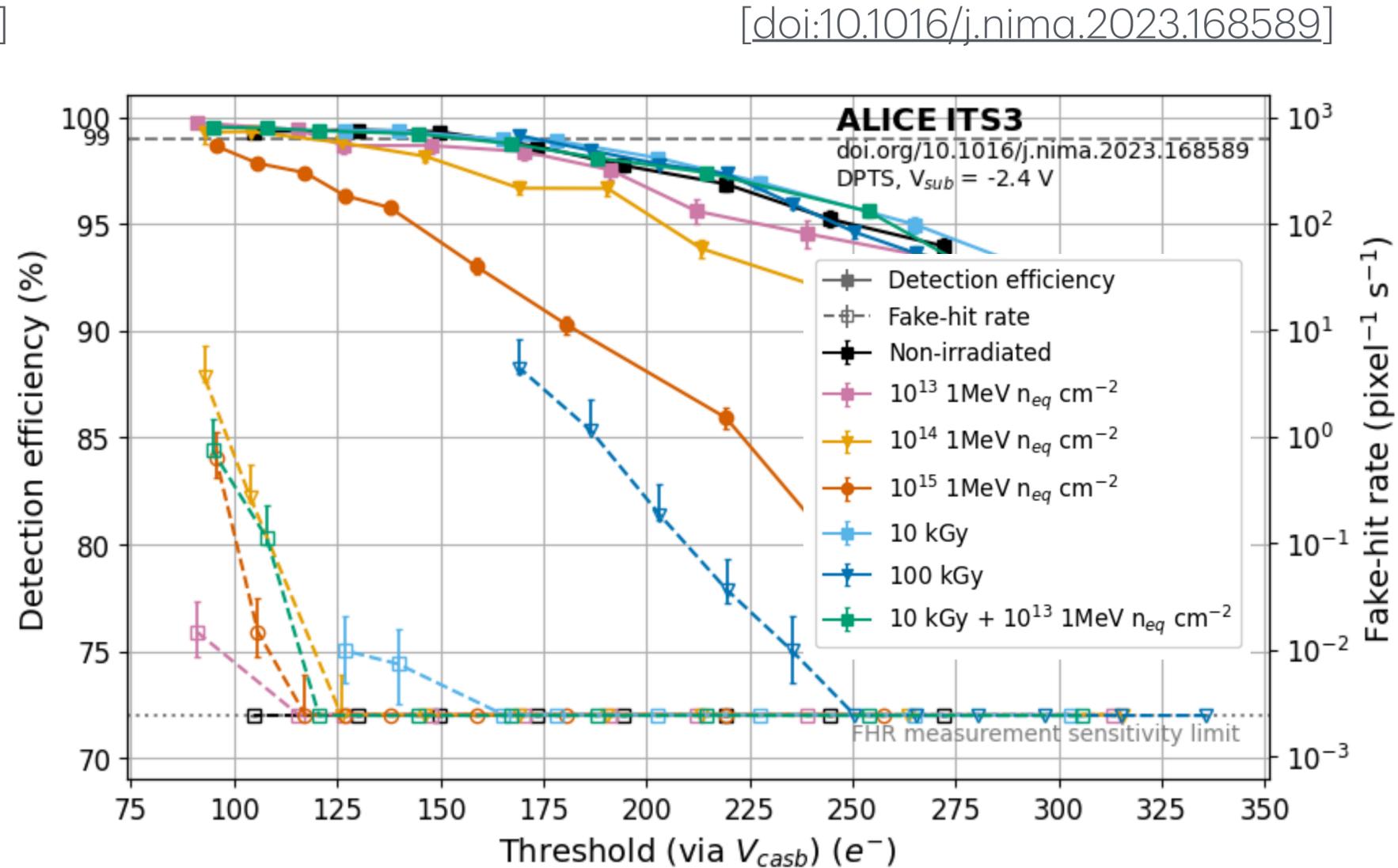
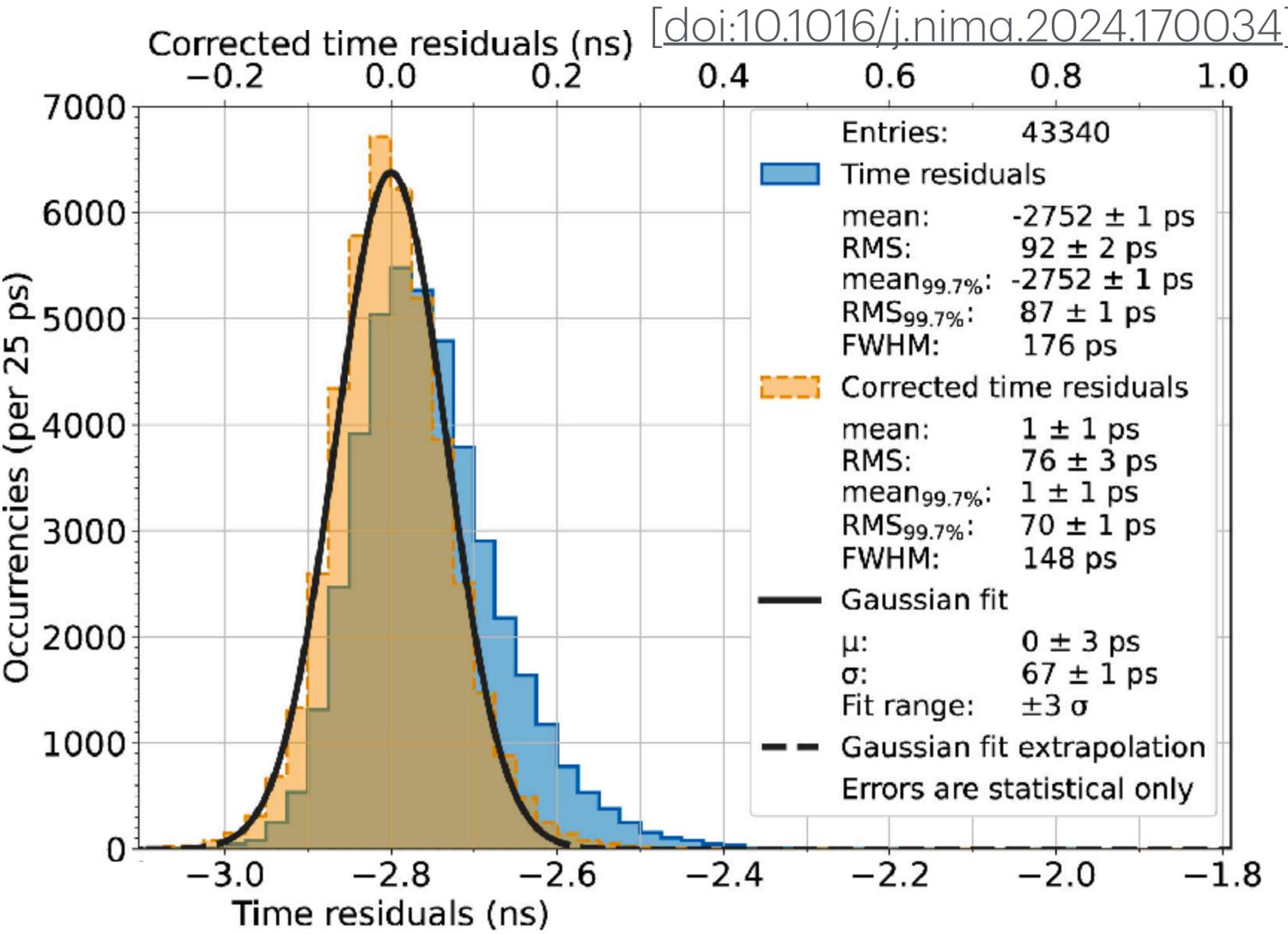
[[doi:10.1088/1748-0221/20/03/C03033](https://doi.org/10.1088/1748-0221/20/03/C03033)]

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[[doi:10.48550/arXiv.2505.05867](https://doi.org/10.48550/arXiv.2505.05867)]

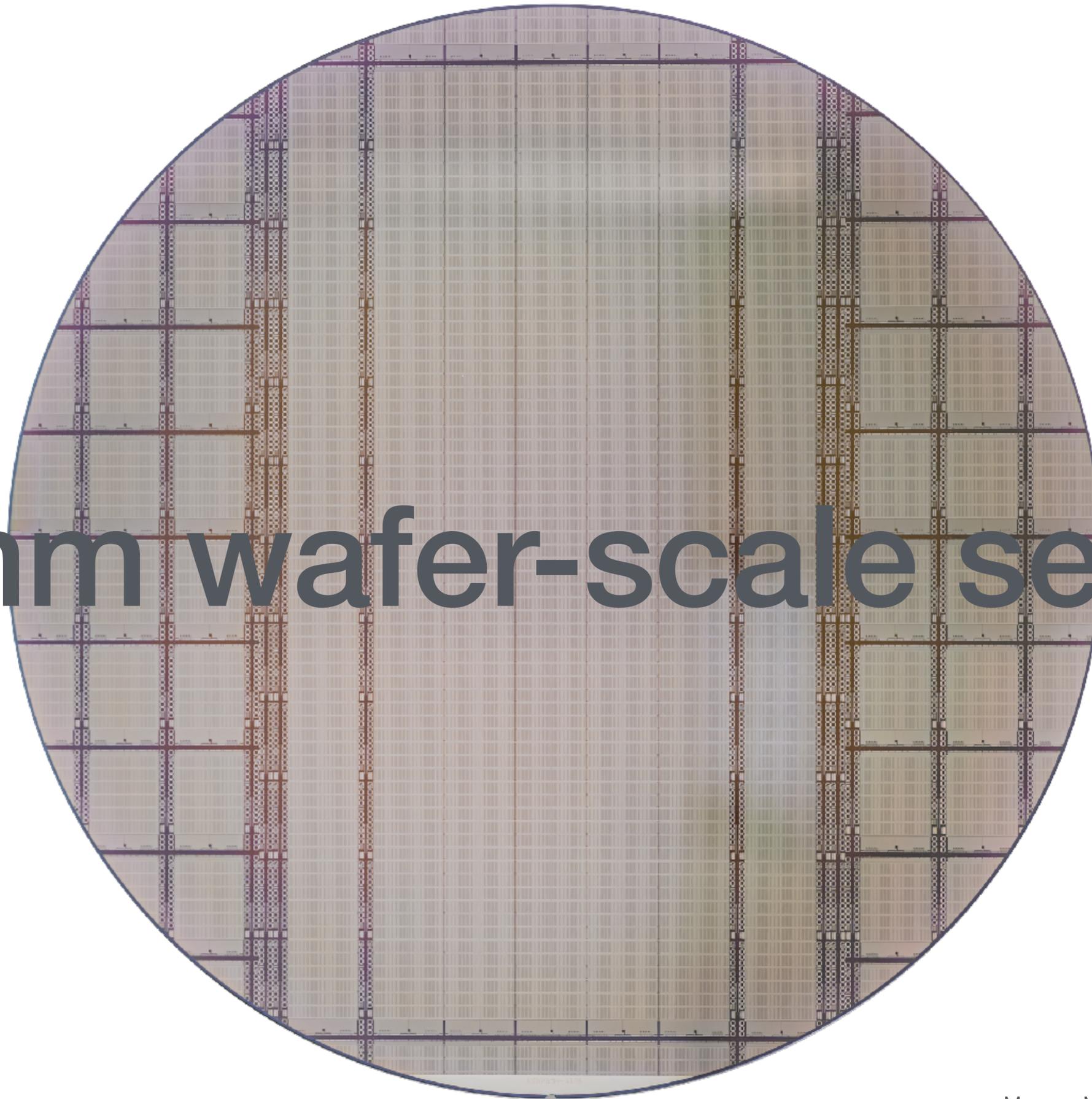
# 65 nm technology qualification

- ▶ Intrinsic time resolutions of 67 ps for 10 μm pixels
- ▶ >99% detection efficiency even after  $10^{15}$  NIEL for 15 μm pixels at room temperature



Excellent performances of the 65 nm technology have been established experimentally

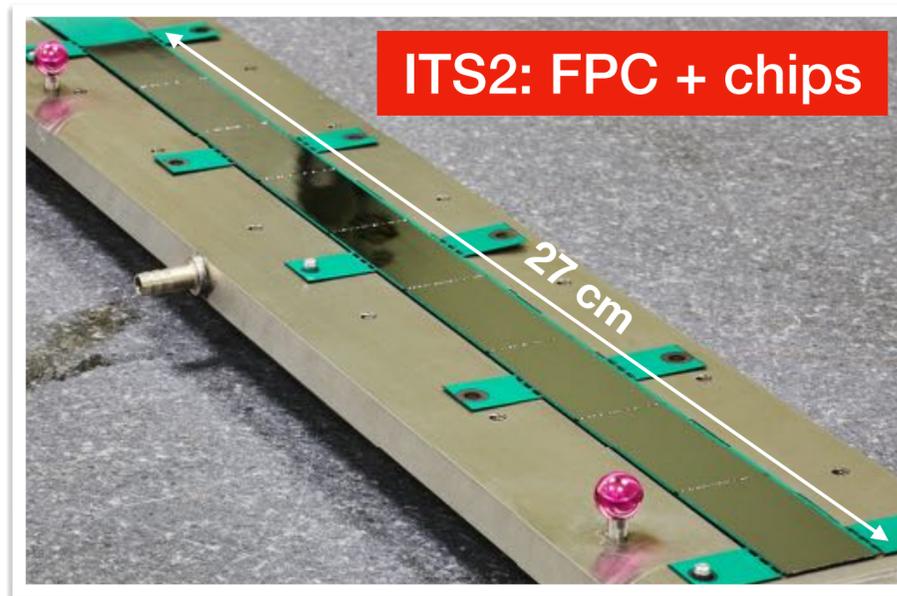
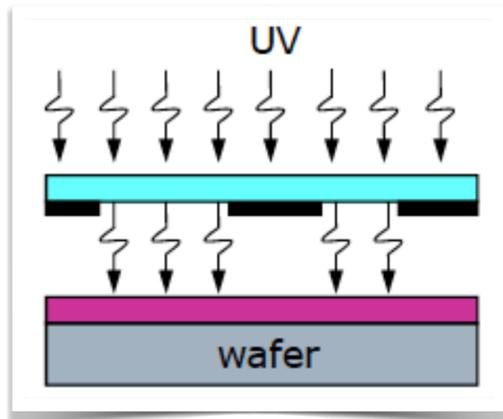
# 300 mm wafer-scale sensors



# Wafer-scale sensors

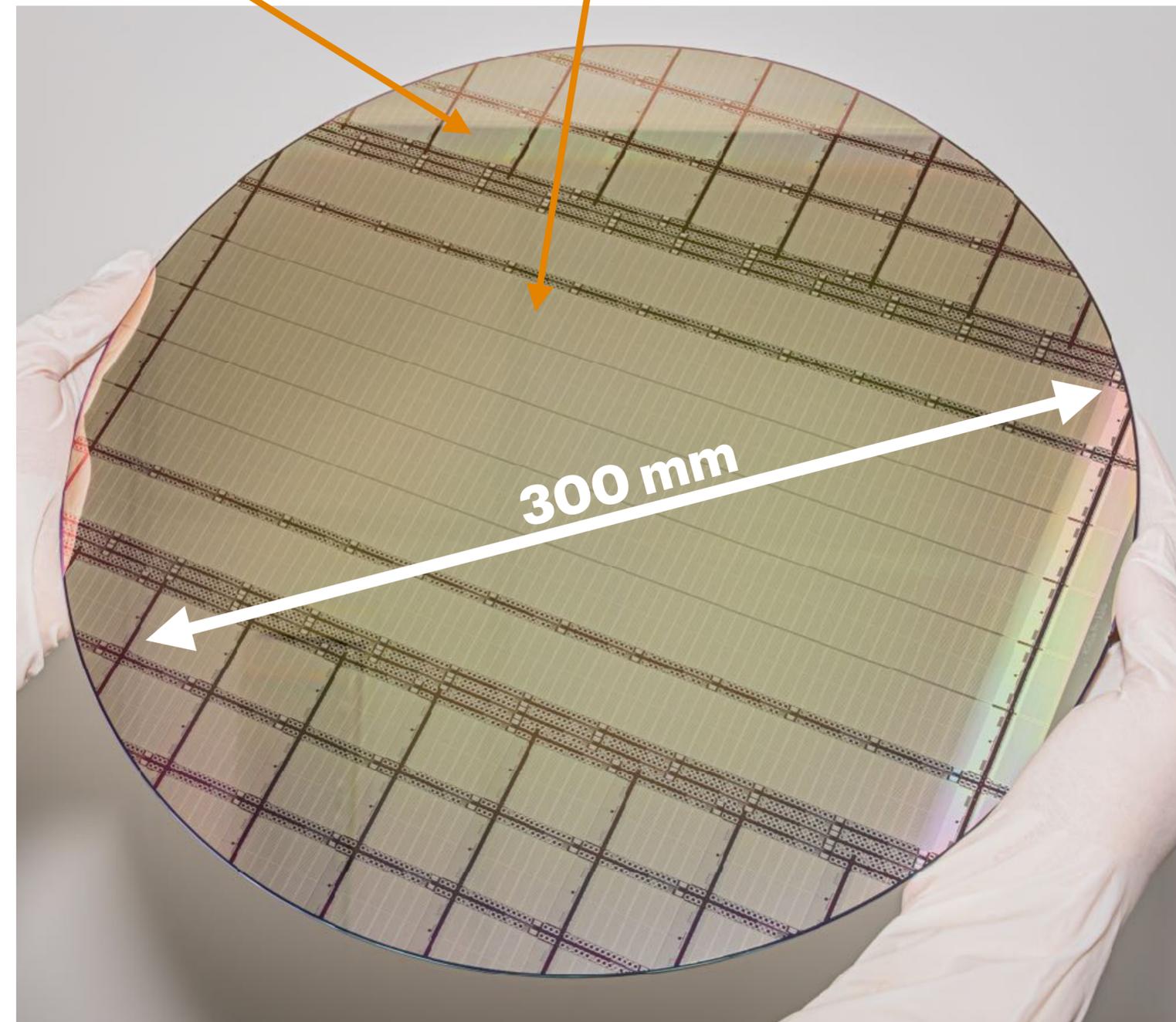
## concept

- ▶ **Previous** chip sizes are  $O(1-3 \text{ by } 1-3 \text{ cm}^2)$ 
  - dictated by mask size
  - masks are exposed once for each chip
  - chips diced out and qualified/selected
  - interconnection on circuit boards (“modules”)
- ▶ **Wafer-scale** “chips”/sensors: stitching of exposures
  - same mask exposed in a precisely aligned fashion
  - design is made periodic (metal lines stitch together)
  - *chip is a module*



single units

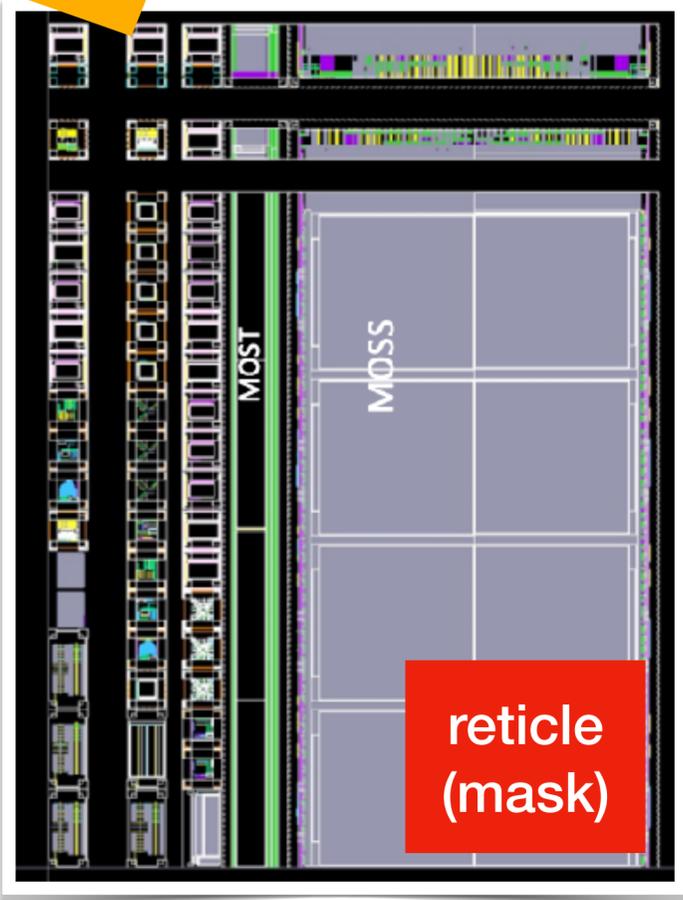
12 units stitched



# Stitching

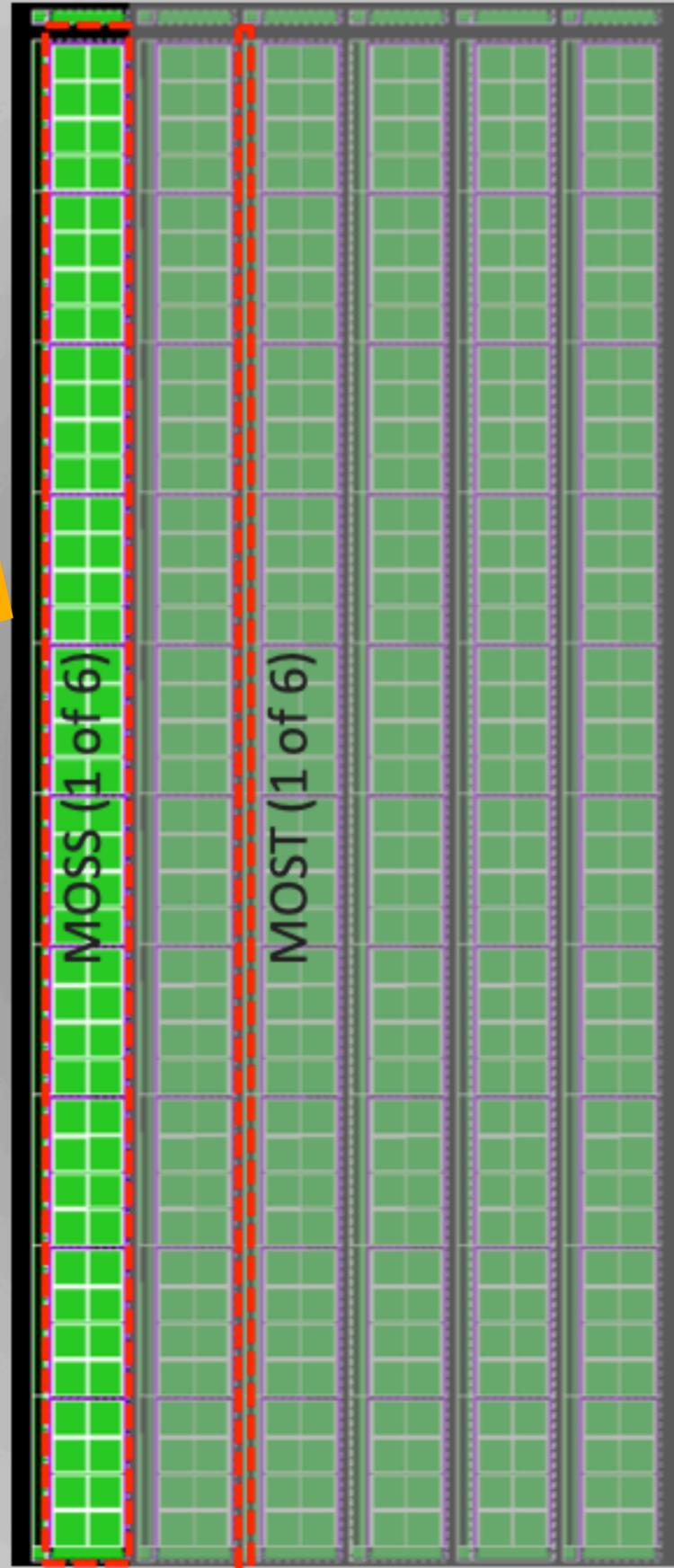
rough principle

what we "design"



what we want to fabricate

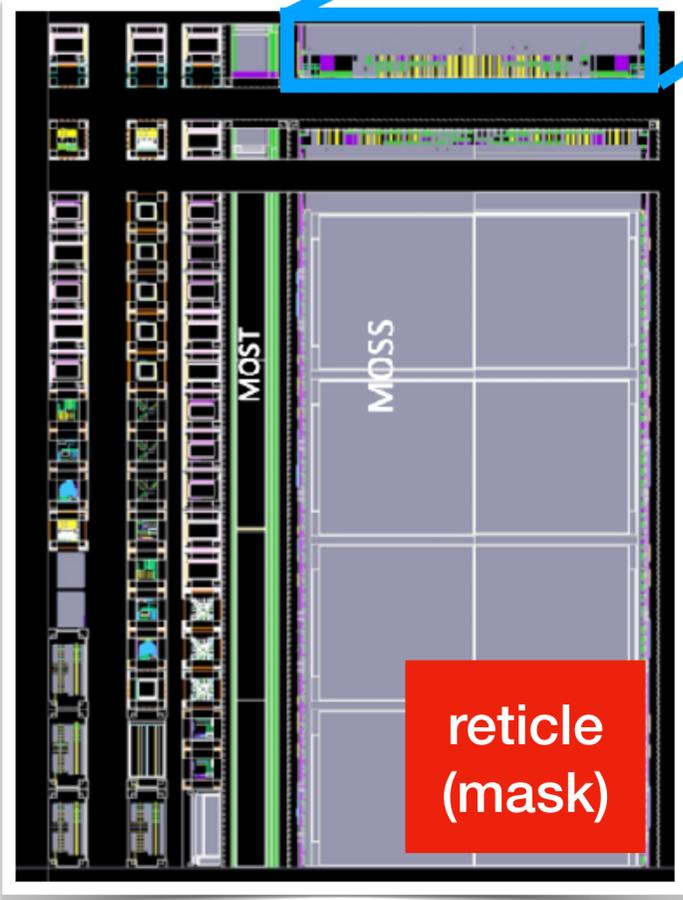
wafer (ø=300 mm)



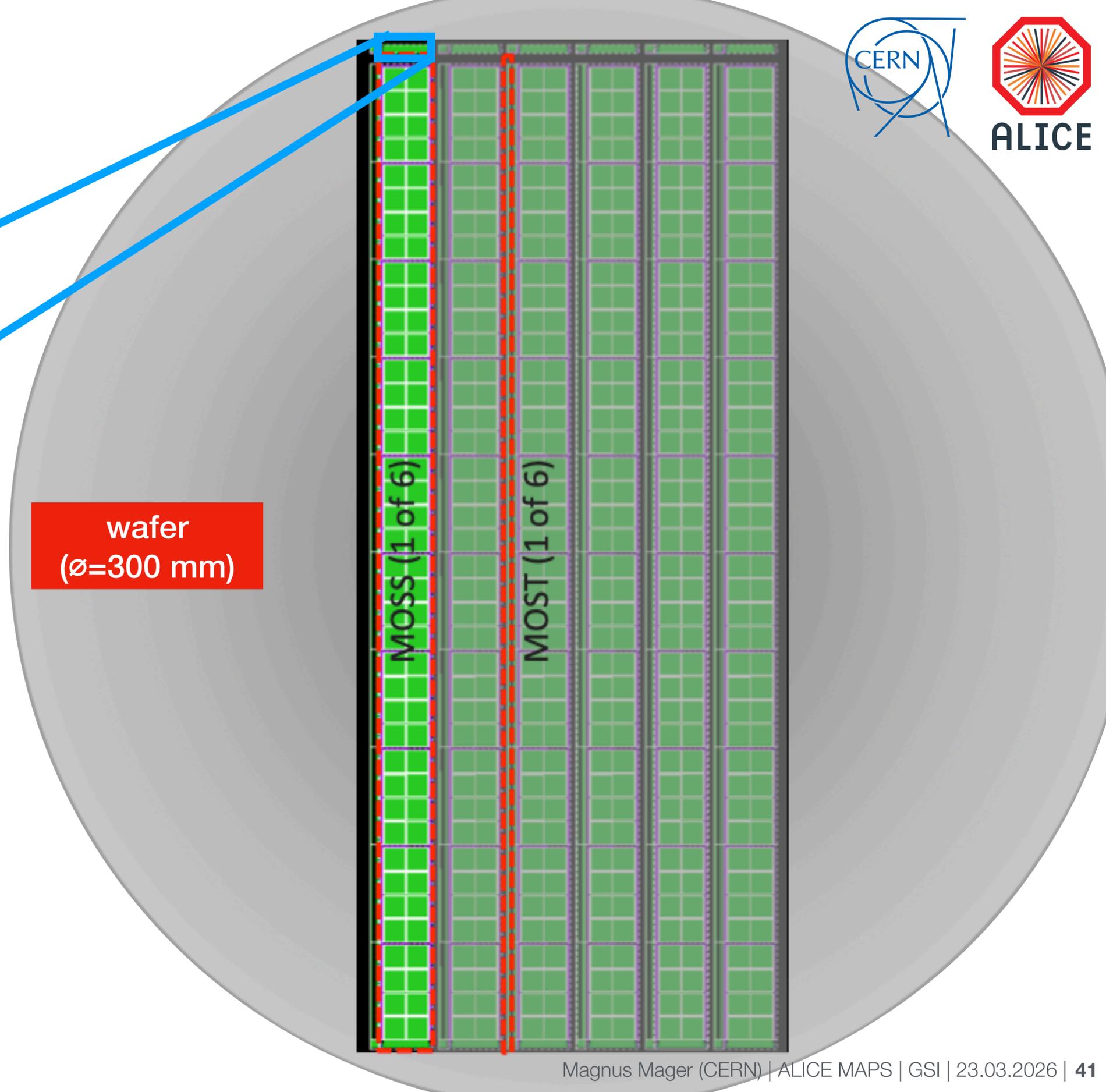
# Stitching

rough principle

► top part



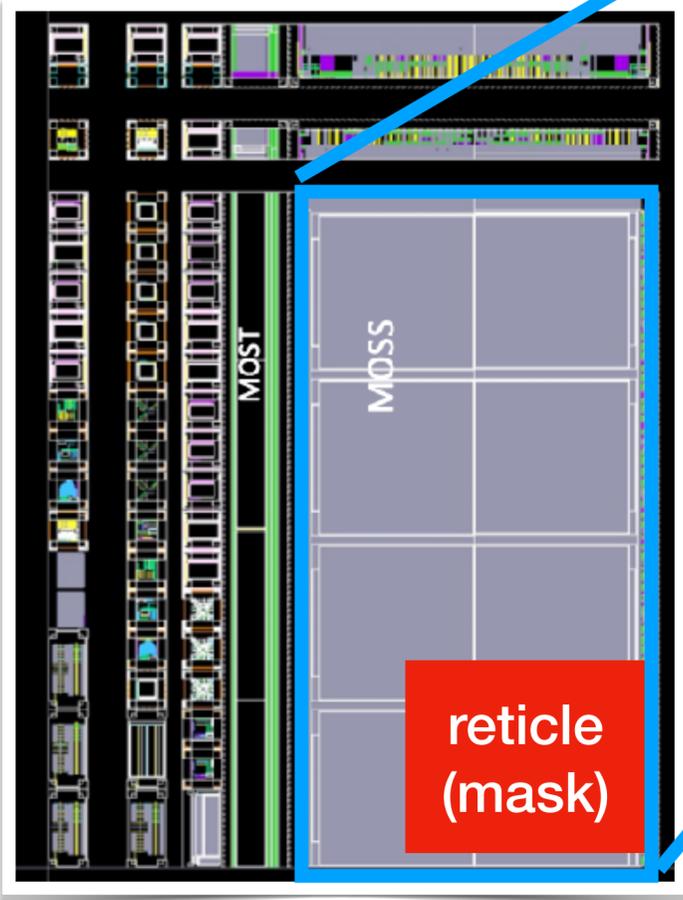
wafer (ø=300 mm)



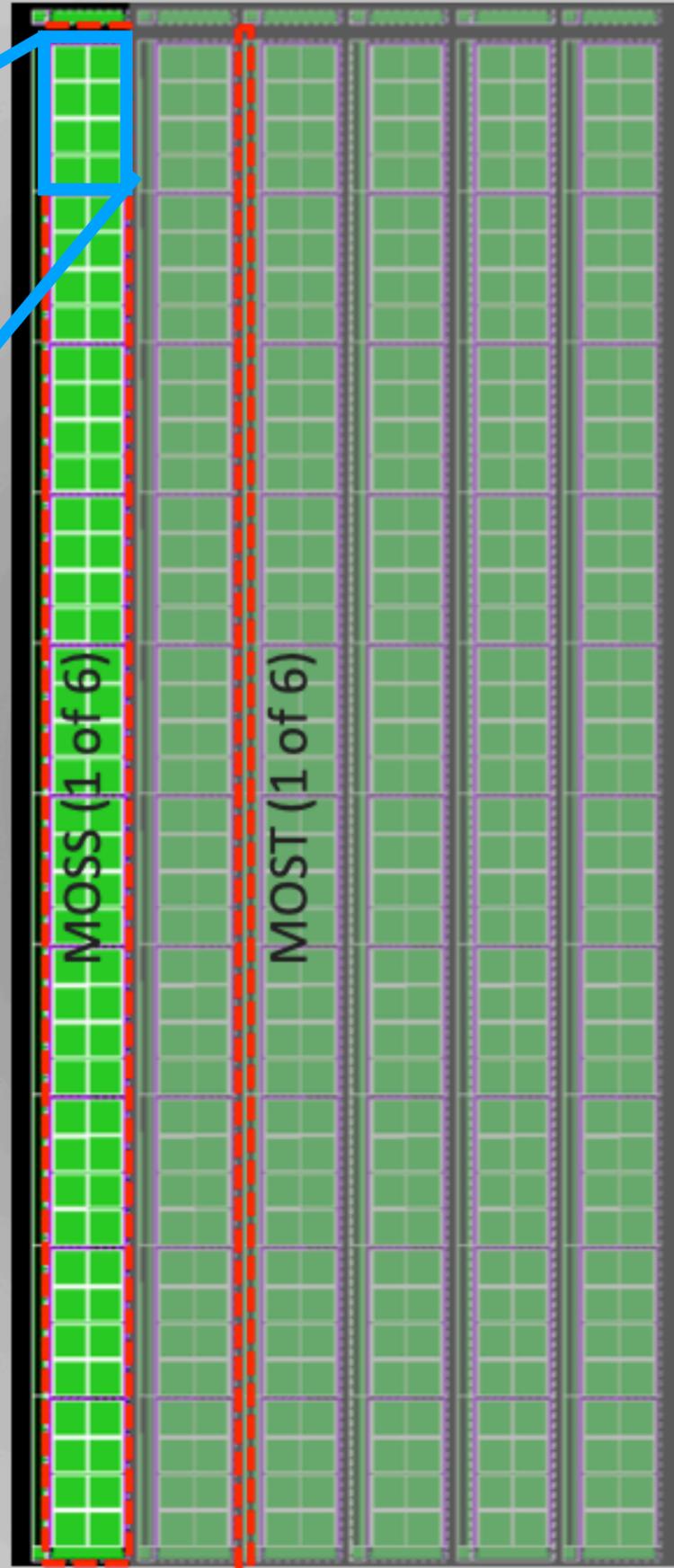
# Stitching

rough principle

► central part (1)



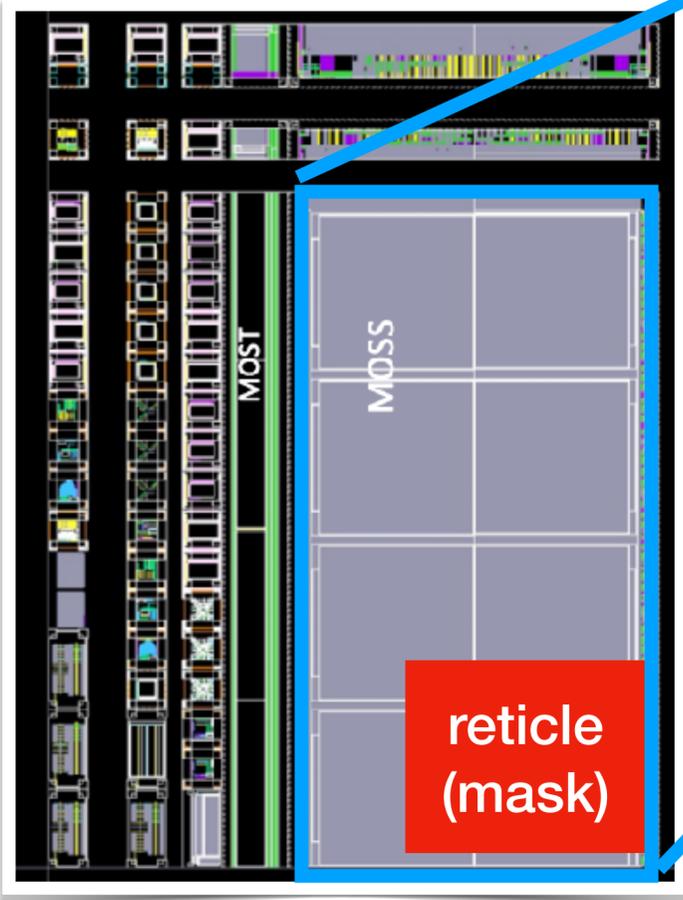
wafer (ϕ=300 mm)



# Stitching

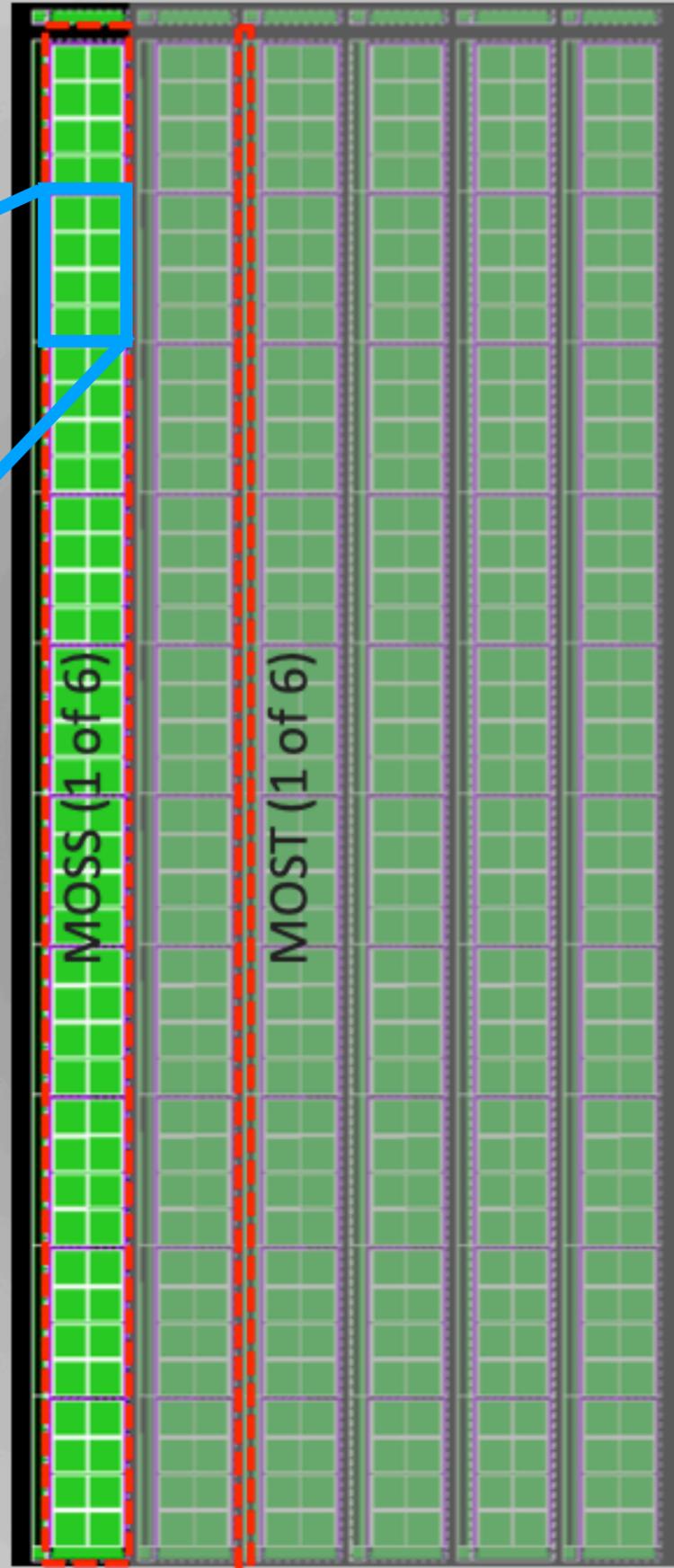
rough principle

- ▶ central part (2)



reticle  
(mask)

wafer  
( $\phi=300$  mm)



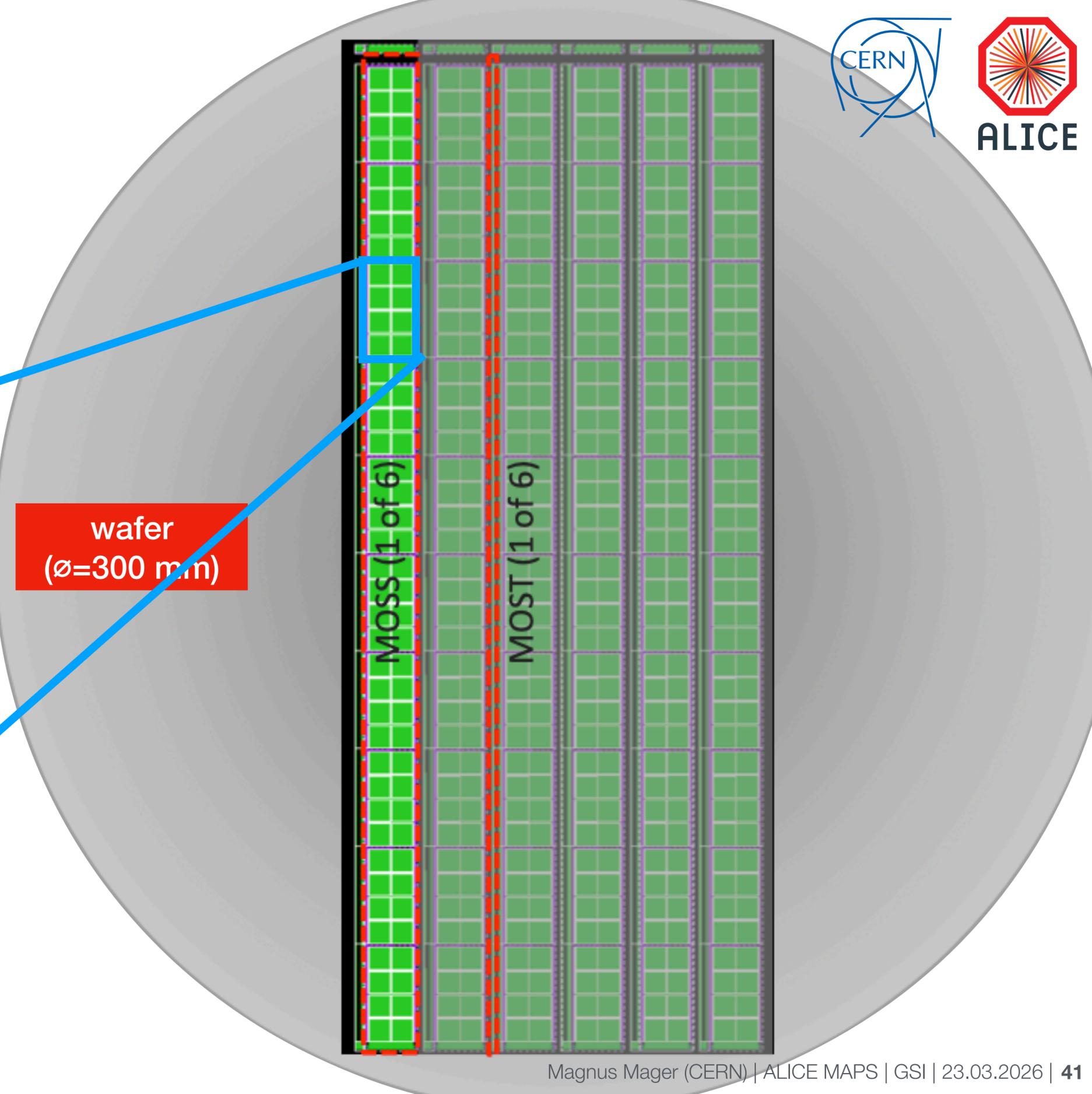
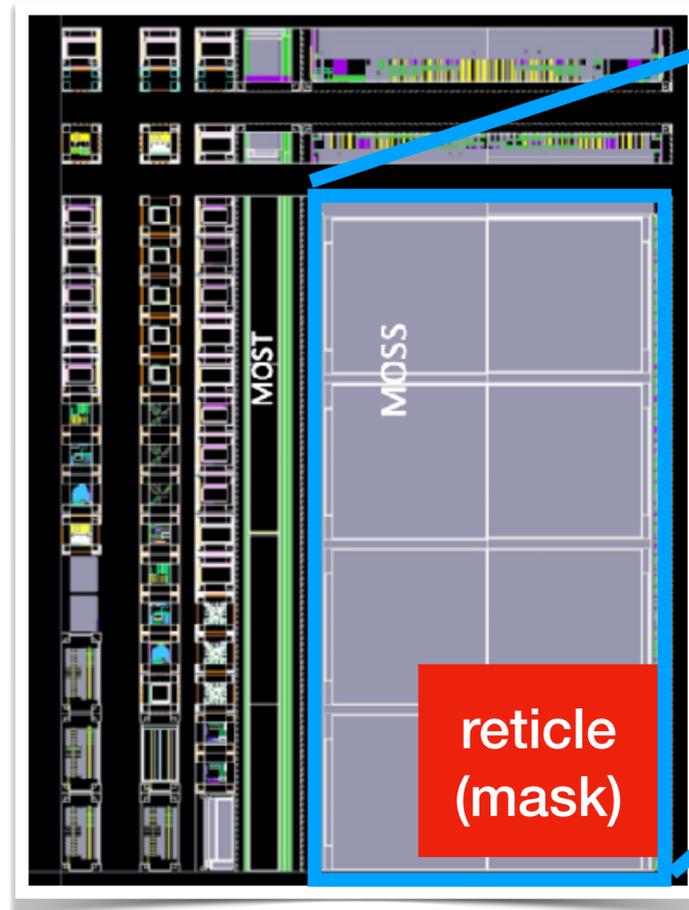
# Stitching

rough principle



ALICE

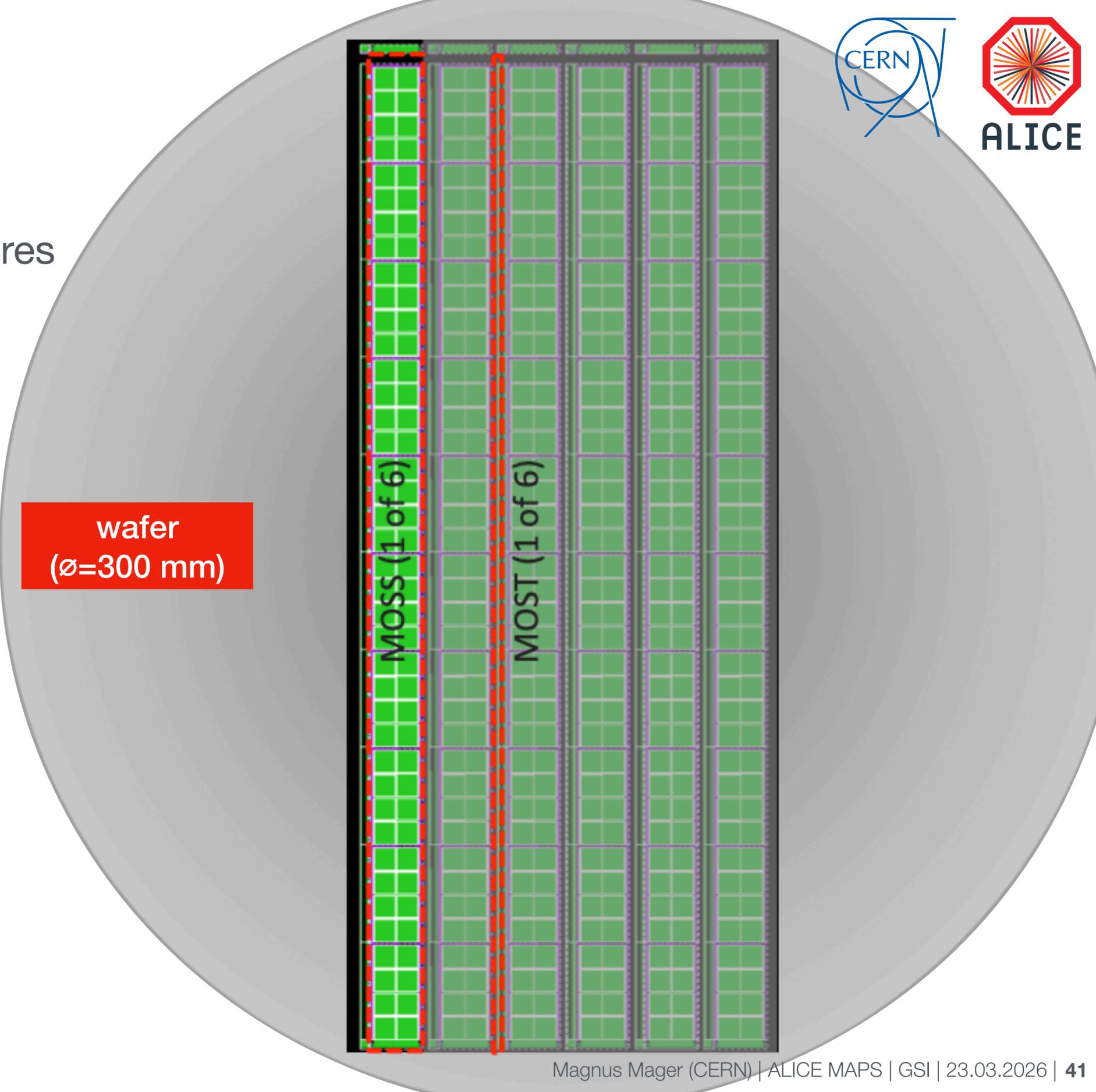
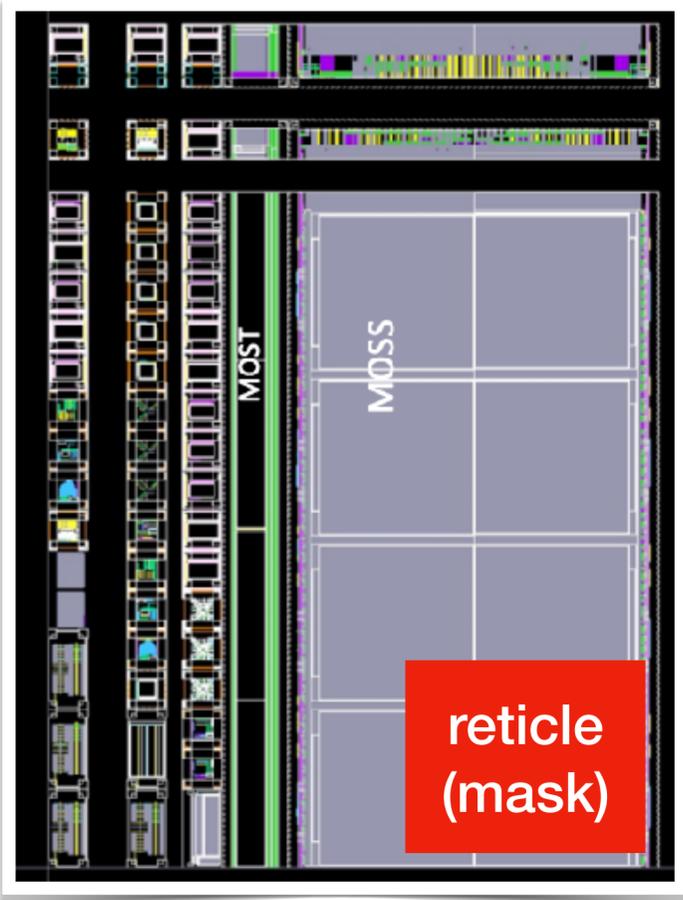
- ▶ central part (3)



# Stitching

rough principle

- ▶ final chip is the concatenation of all exposures



# ITS3 chip development roadmap

past

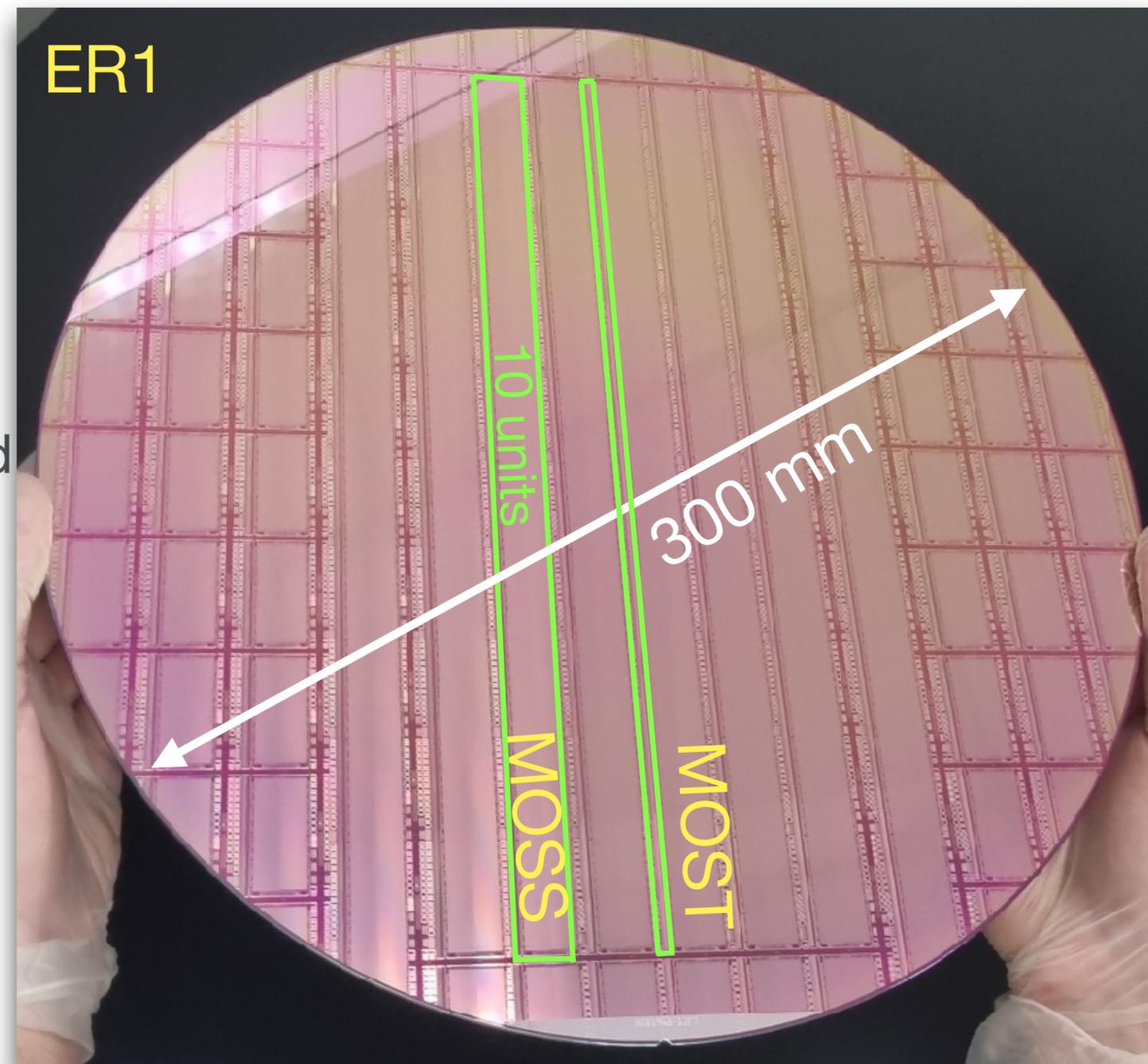
- ▶ **MLR1: first MAPS in TPSCo 65nm (2021)**
  - successfully qualified the 65nm process for particle detectors

present

- ▶ **ER1: first stitched MAPS (2023)**
  - large design “exercise”
  - **“MOSS”**: 14 x 259 mm, 6.72 MPixel (22.5 x 22.5 and 18 x 18  $\mu\text{m}^2$ ): conservative design, different pitches
  - **“MOST”**: 2.5 x 259 mm, 0.9 MPixel (18 x 18  $\mu\text{m}^2$ ): more dense design

future

- ▶ **ER2: “MOSAIX” (2025)**
  - full-scale, fully functional prototype
  - *currently being tested*
- ▶ **ER3: ITS3 sensor production (2026)**

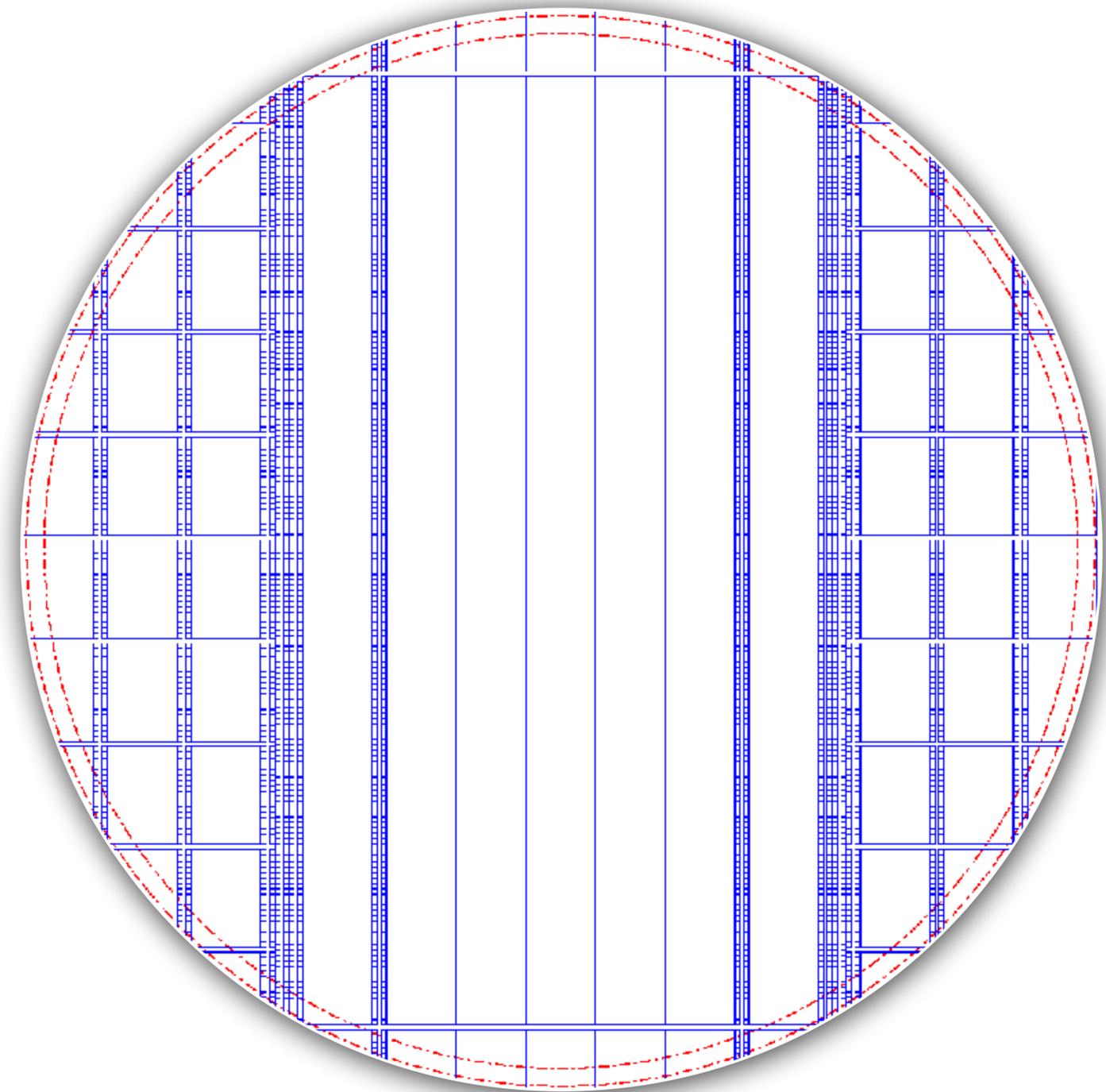
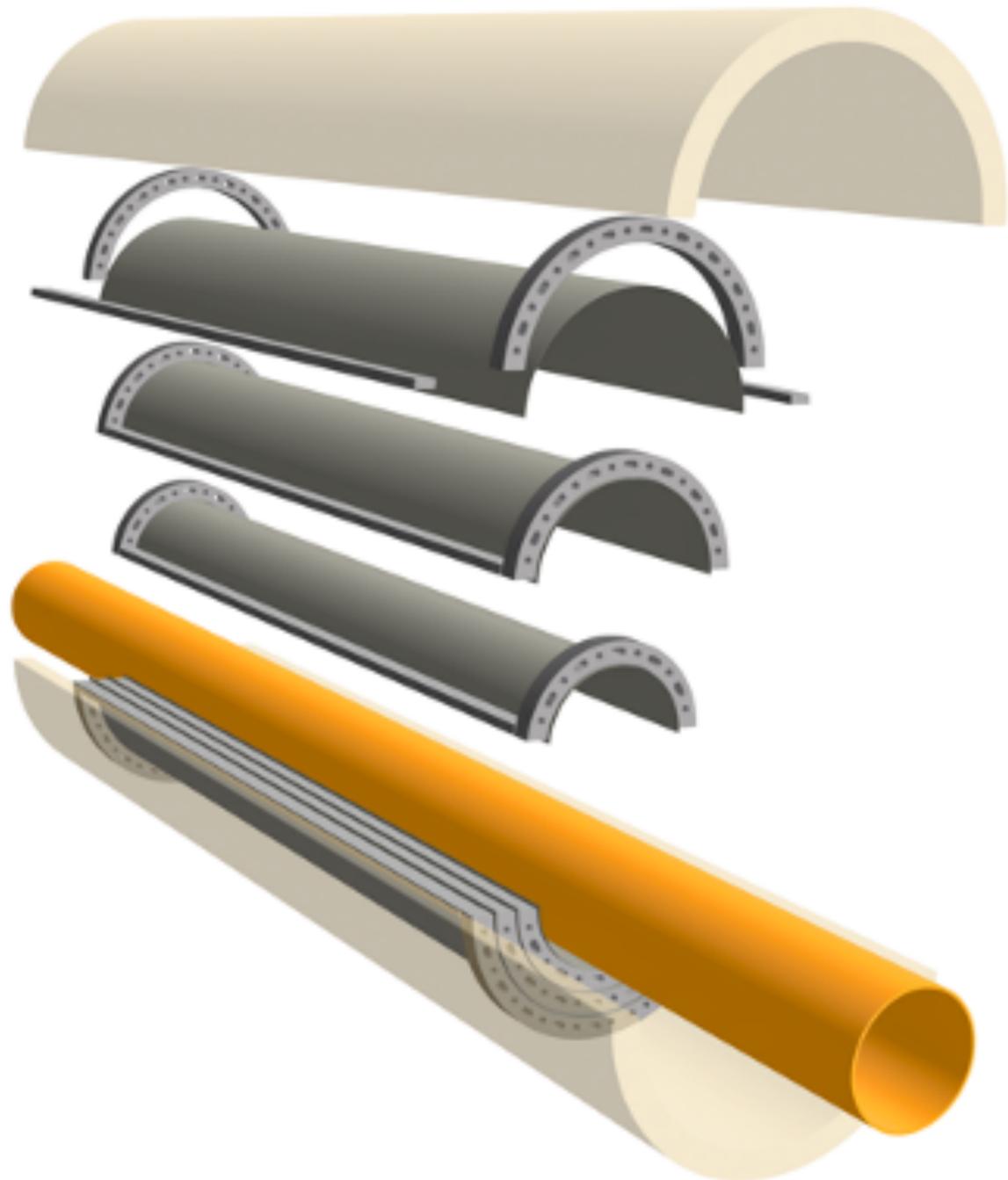


# ER2: MOSAIX

the full-scale prototype



ER2 wafer layout

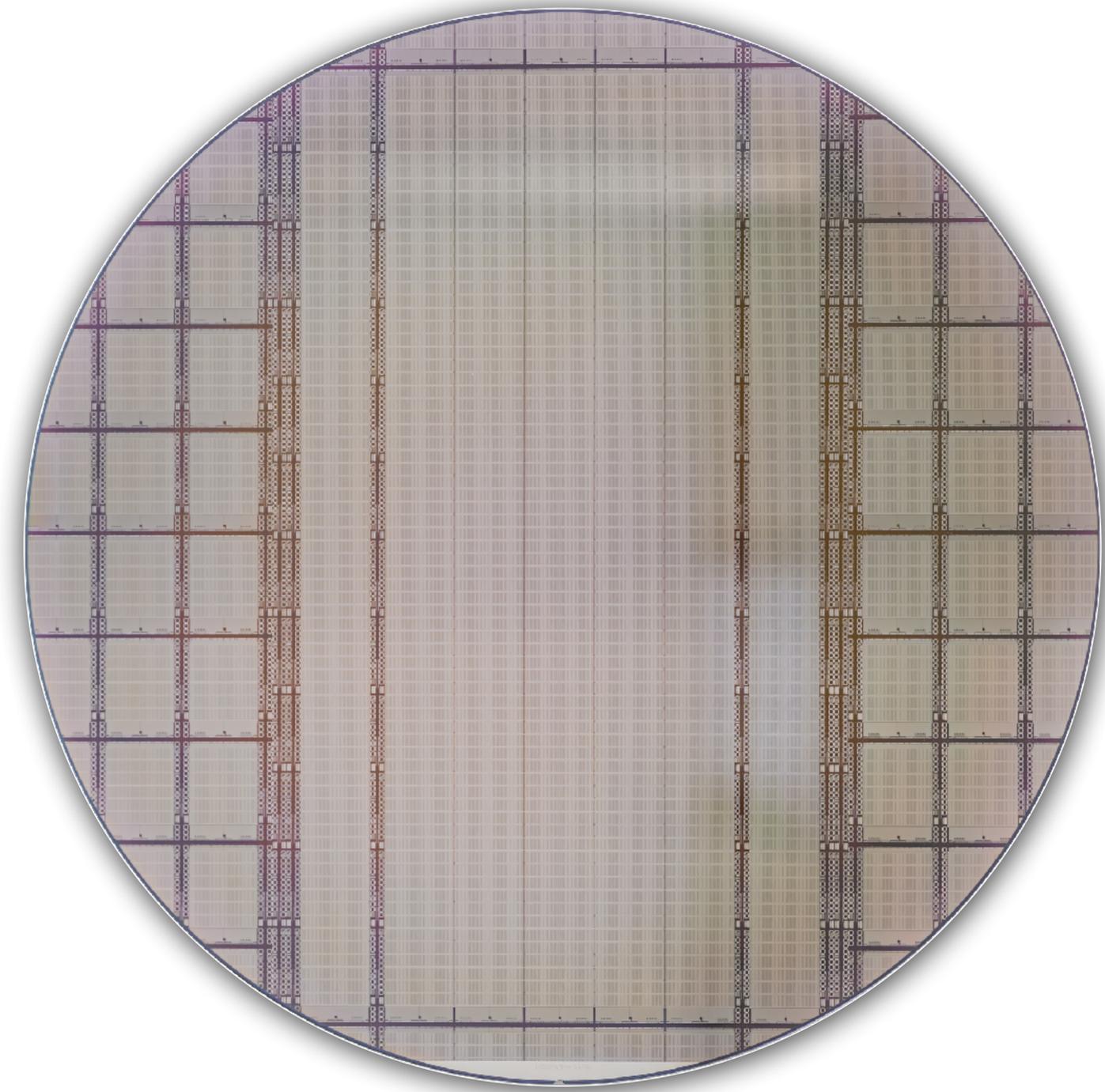
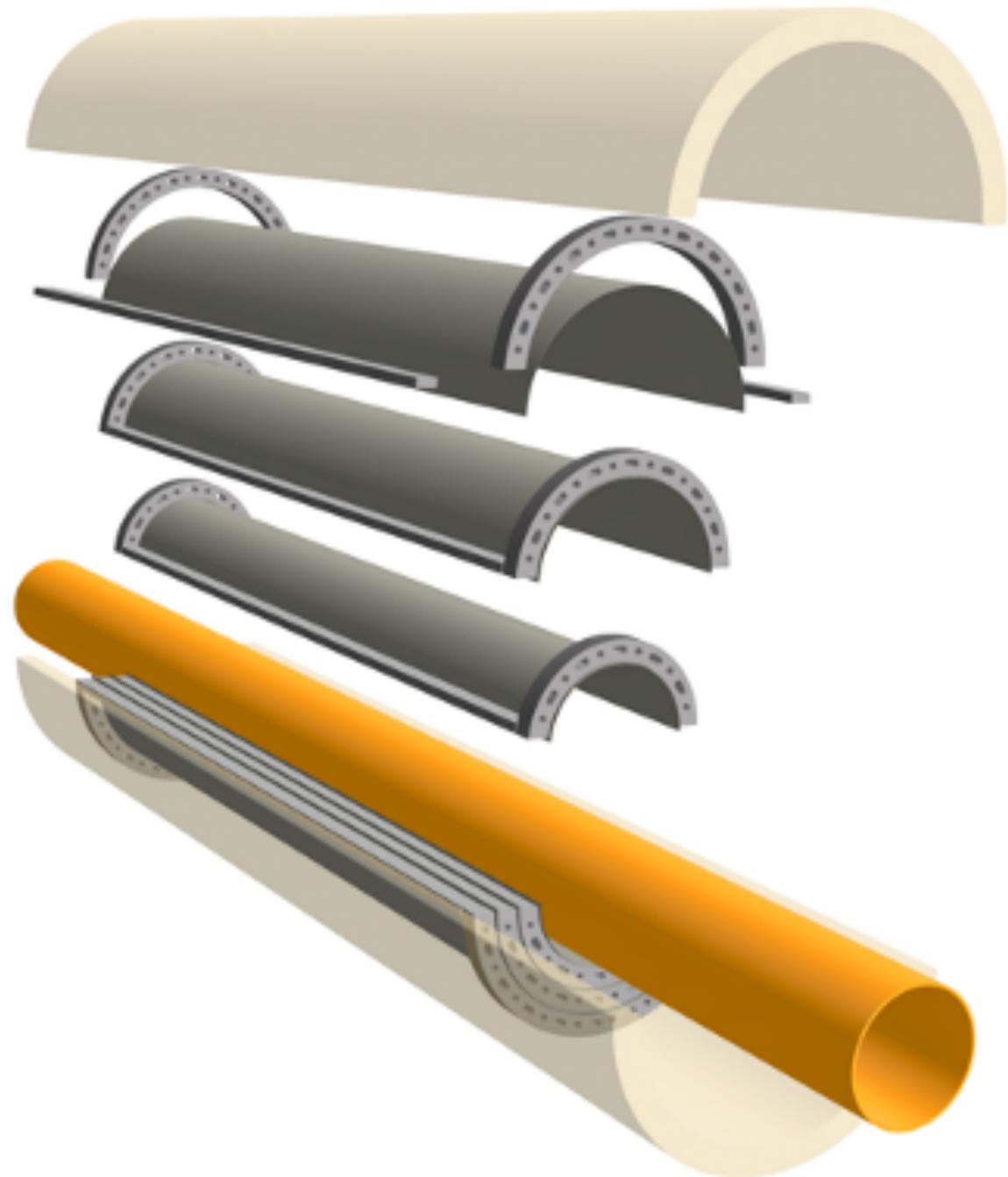


# ER2: MOSAIX

the full-scale prototype



ER2 wafer layout



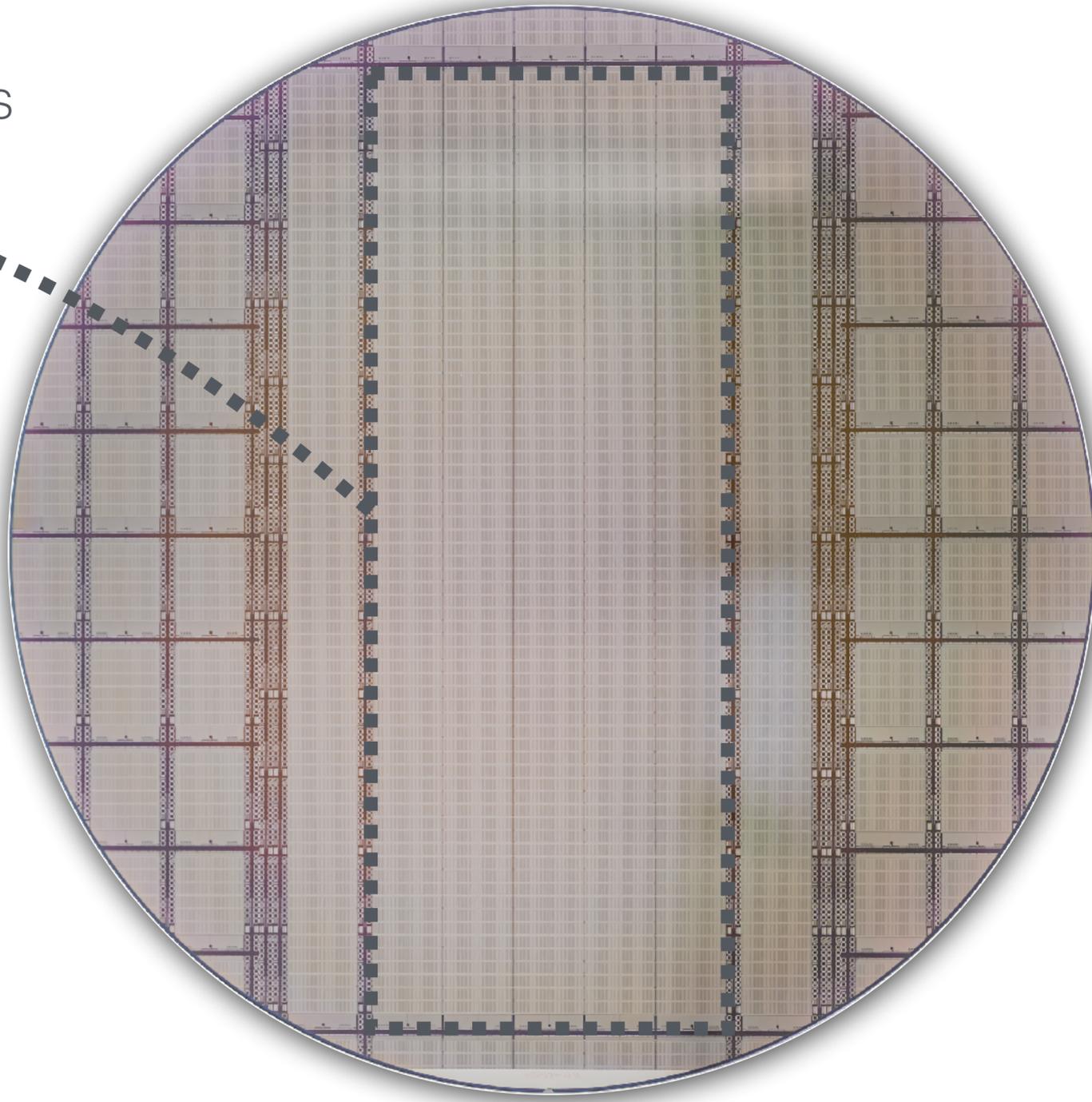
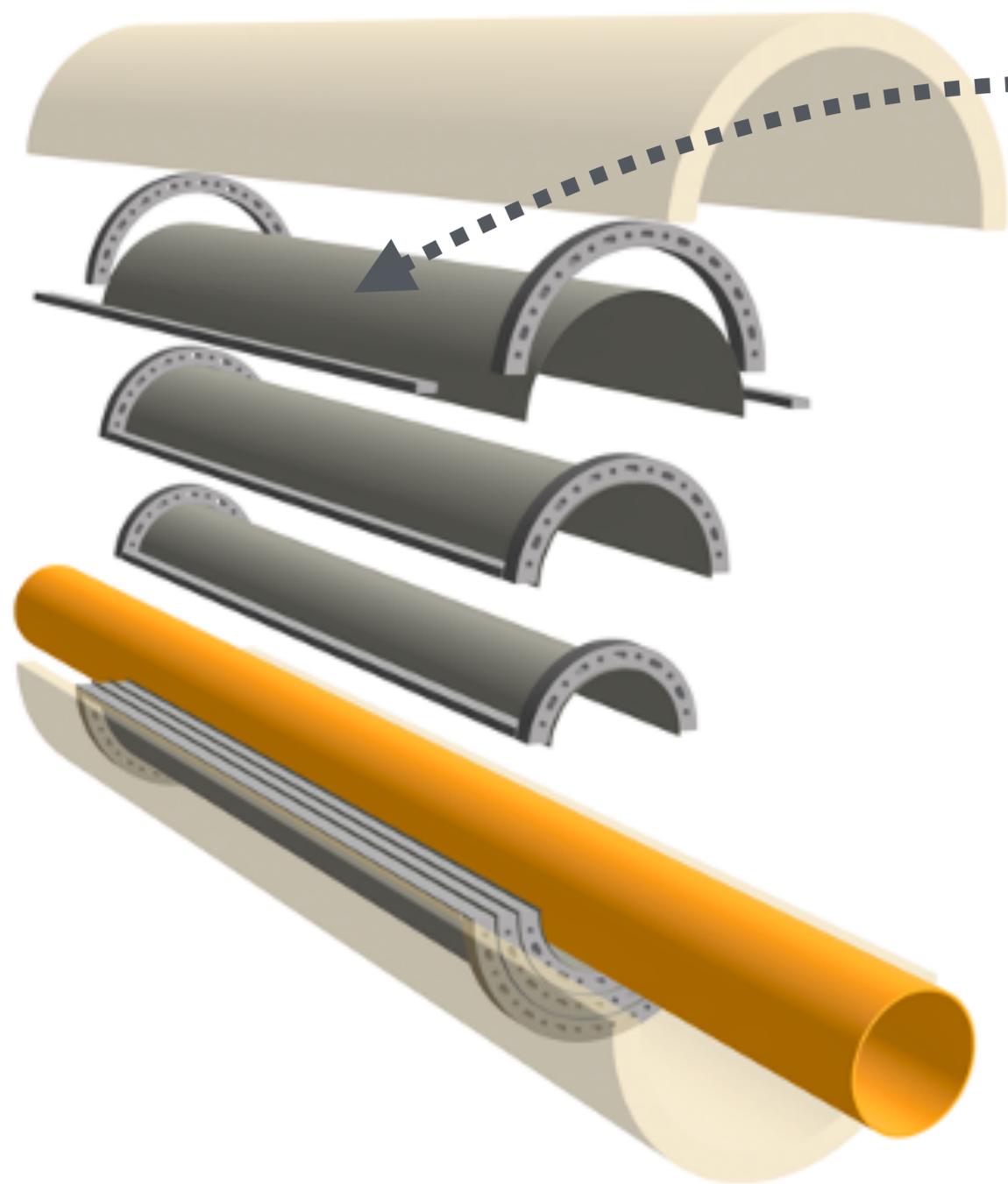
# ER2: MOSAIX

the full-scale prototype



ER2 wafer layout

**Layer 2:** 5 segments

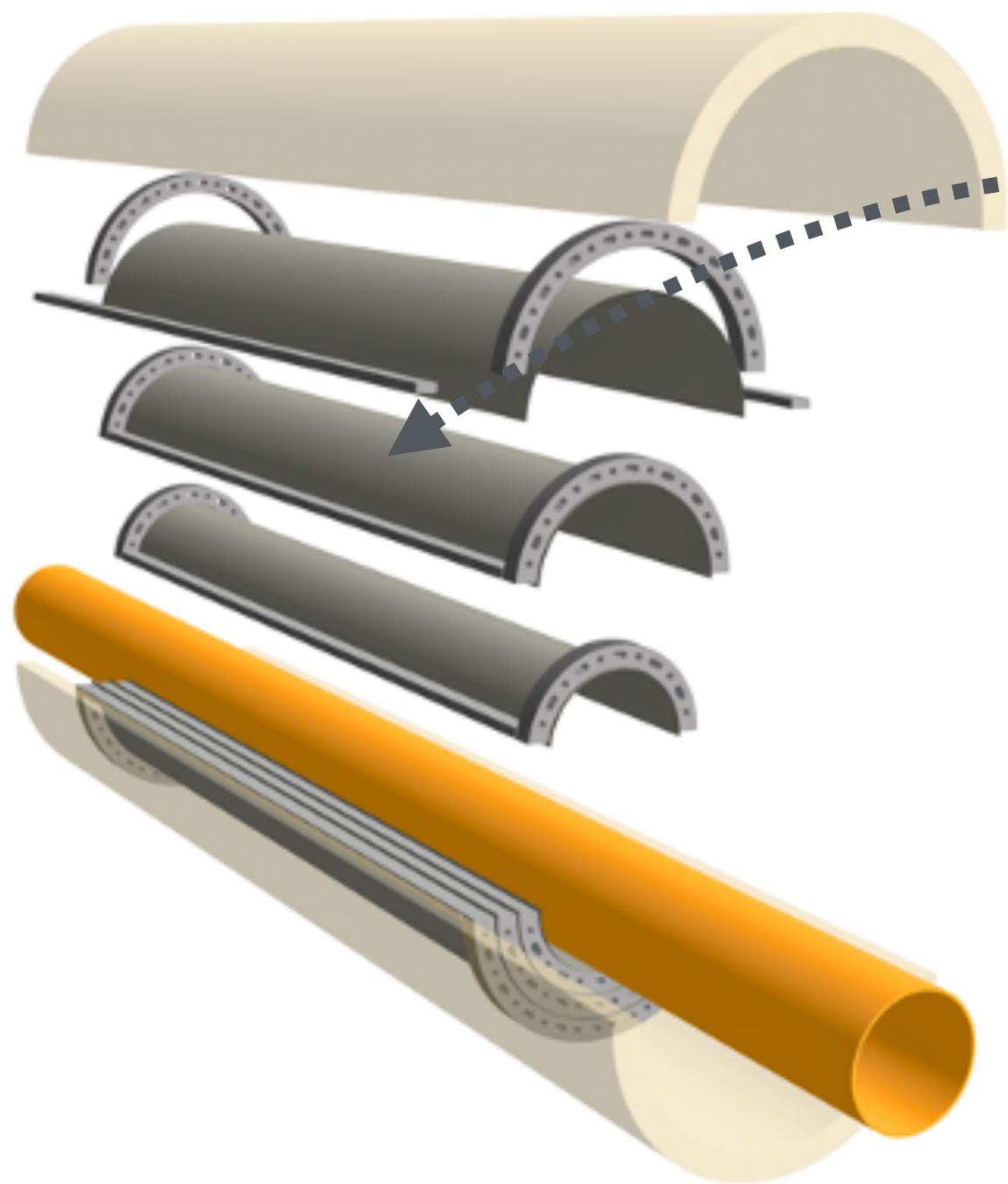


# ER2: MOSAIX

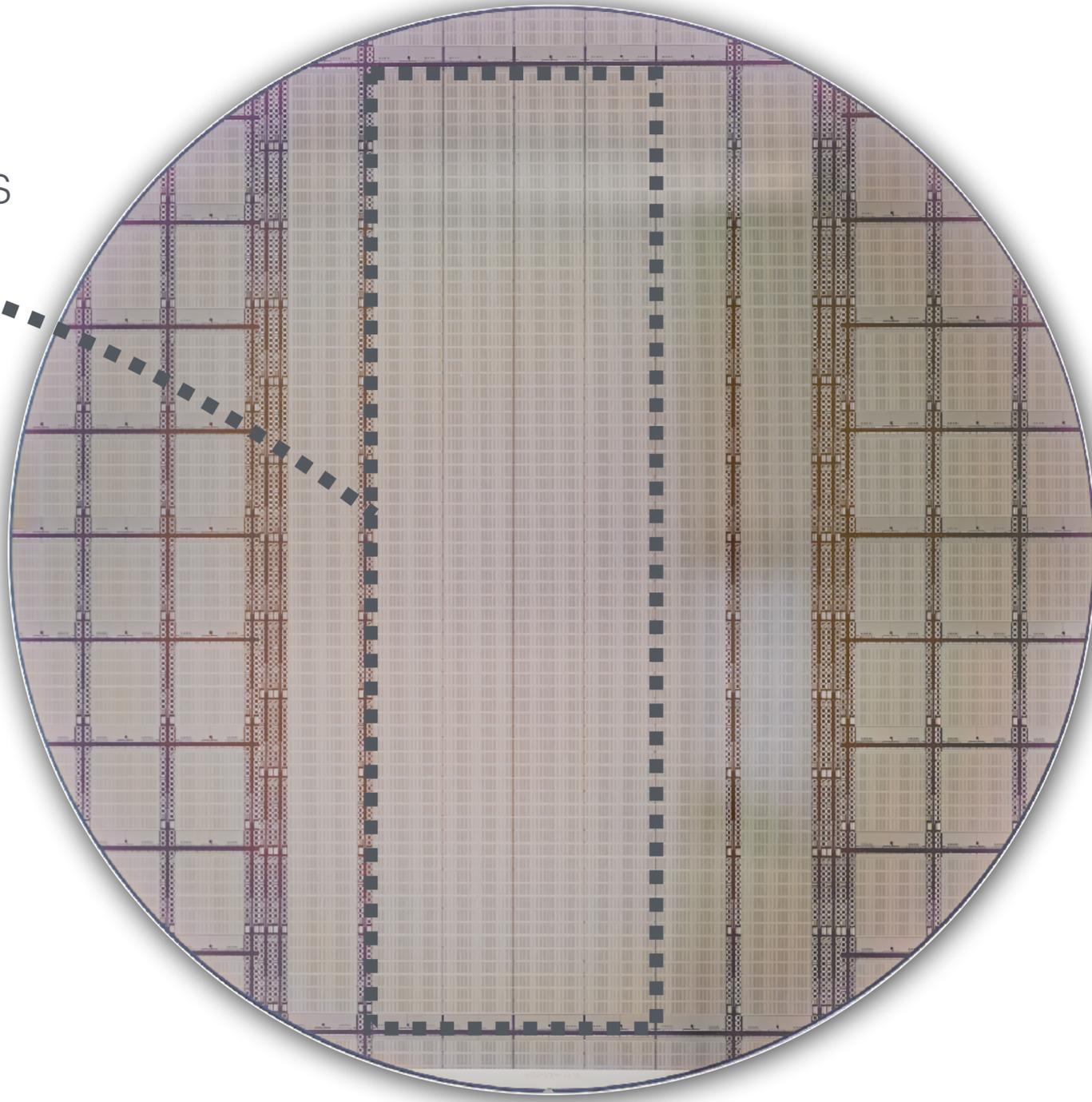
the full-scale prototype



ER2 wafer layout



**Layer 1:** 4 segments

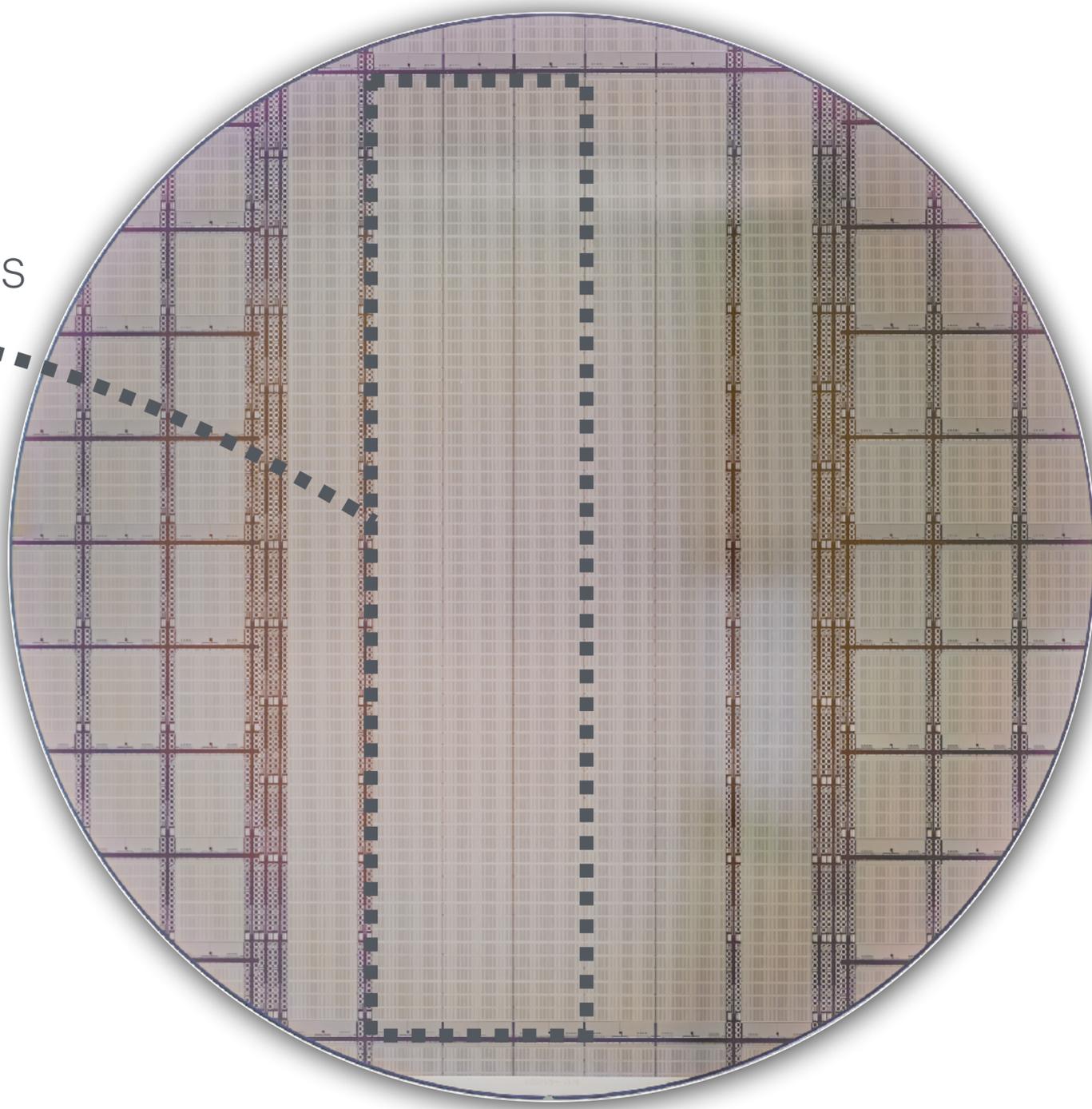
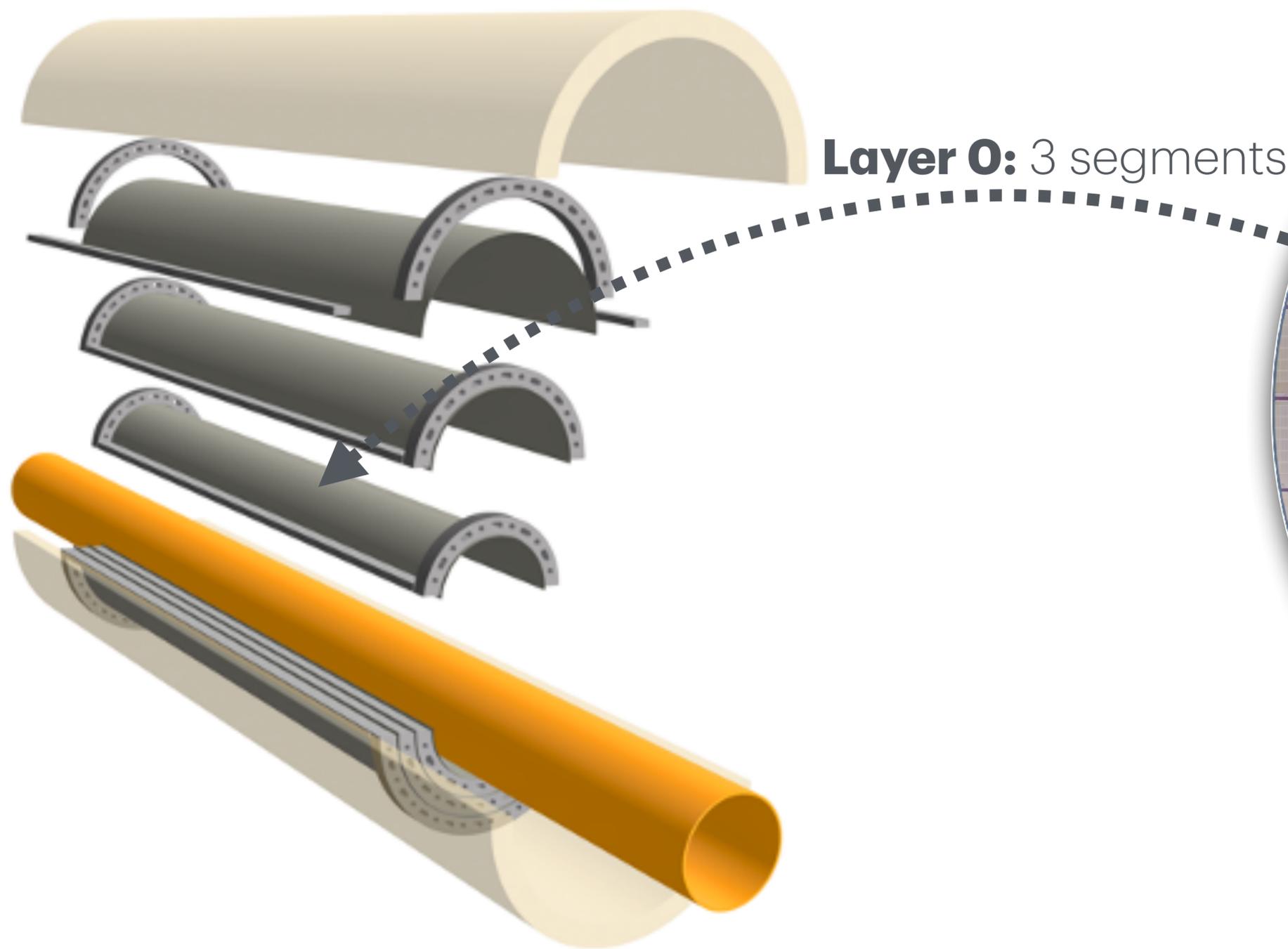


# ER2: MOSAIX

the full-scale prototype



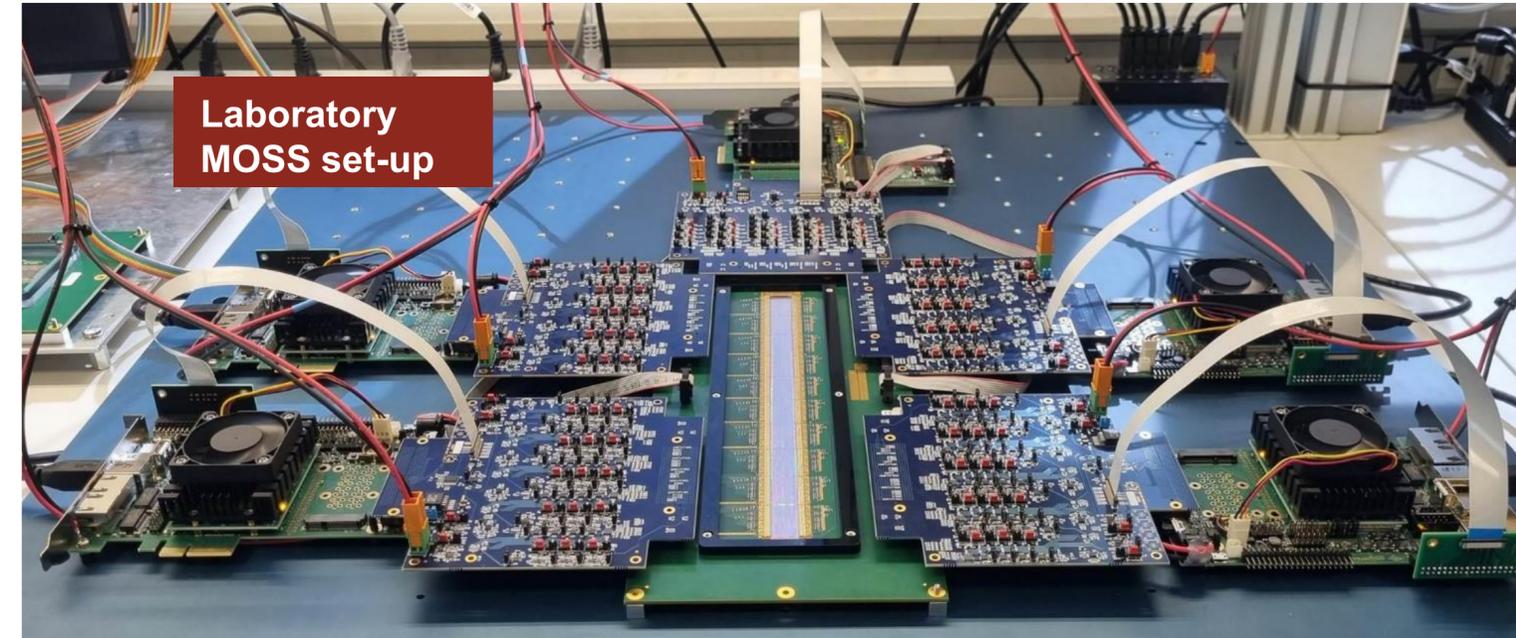
ER2 wafer layout



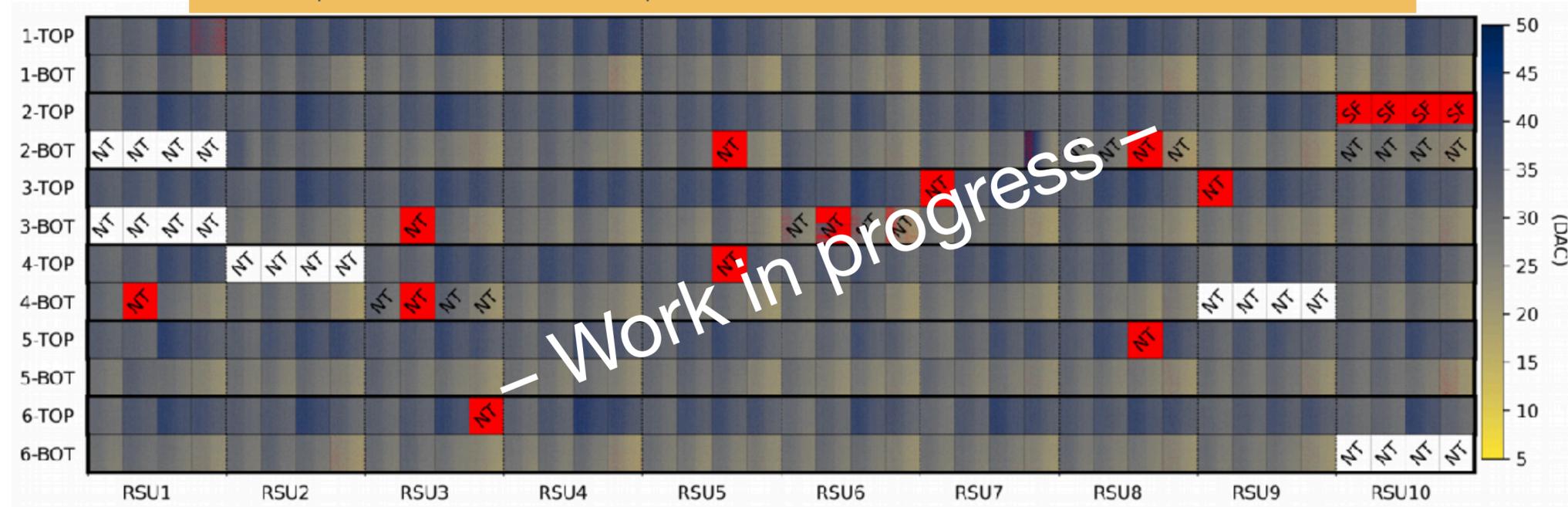
# ER1: MOSS

## understanding of yield

- ▶ **Detailed understanding** of yield is gained with first prototypes
- ▶ **Mitigation** strategy based on:
  - hardening critical circuitry
  - fine-grained isolation of eventually malfunctioning blocks
- ▶ **Very encouraging** results
  - extrapolated functional yield >98%



Example threshold map of 40 MPixel over 10x26 cm of silicon

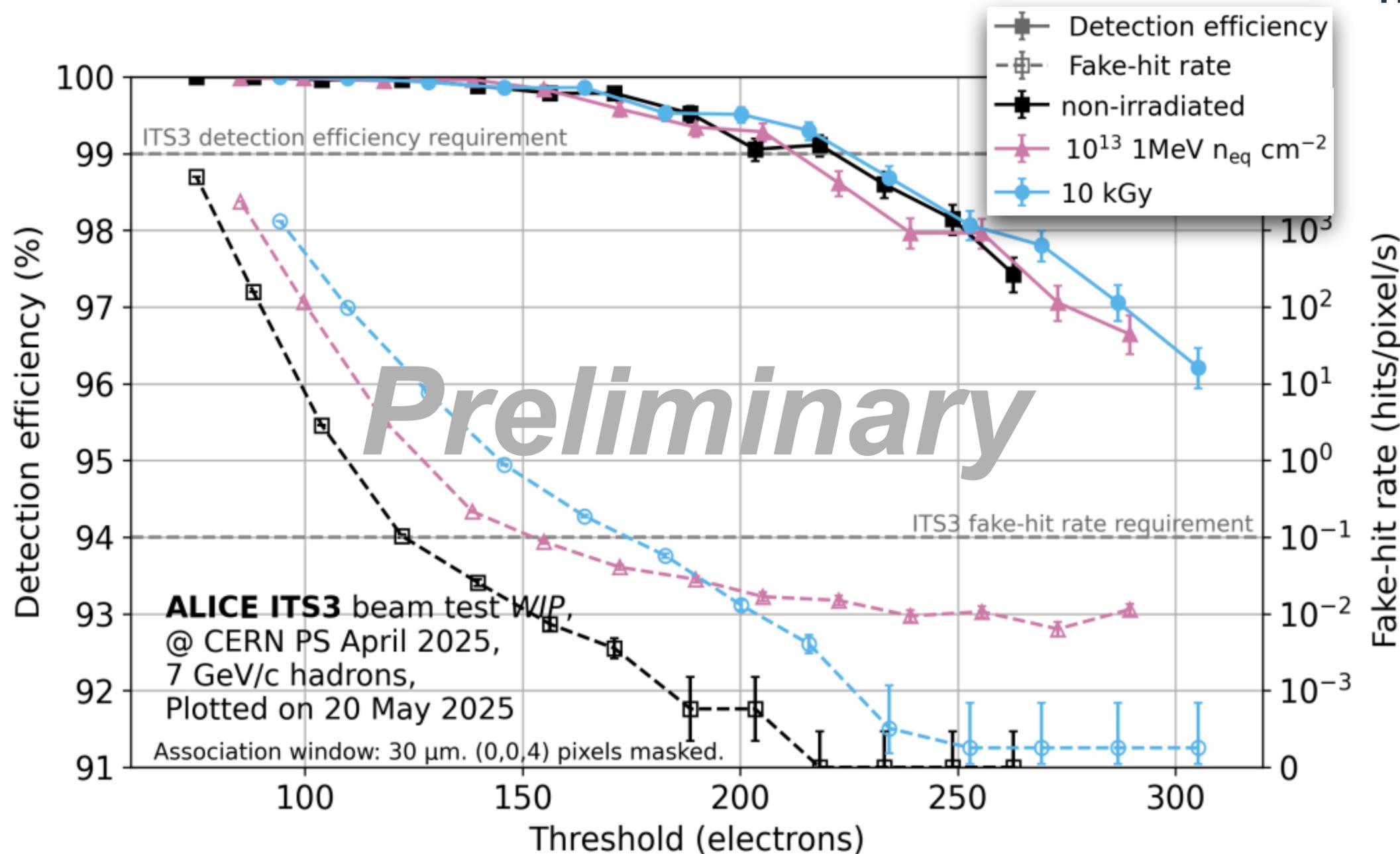
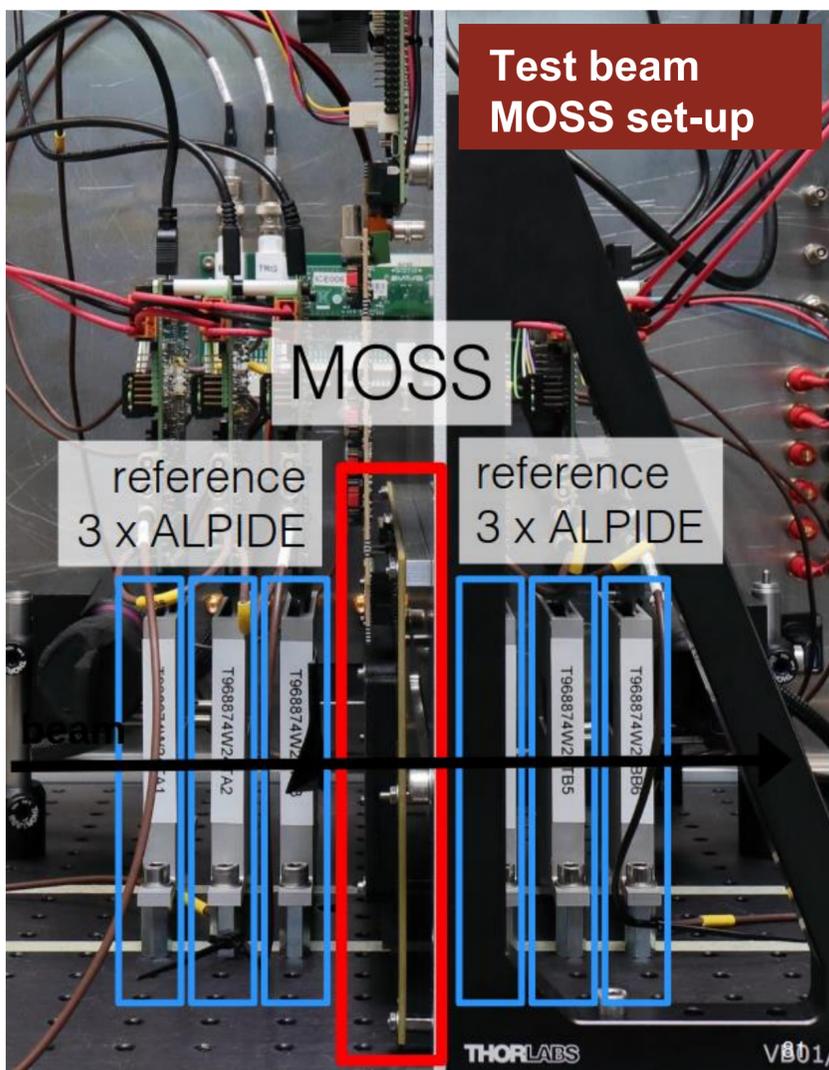


[doi:10.1016/j.nima.2026.171297]

[doi:10.1109/TNS.2026.3671605]

# ER1: MOSS

operation in beam tests



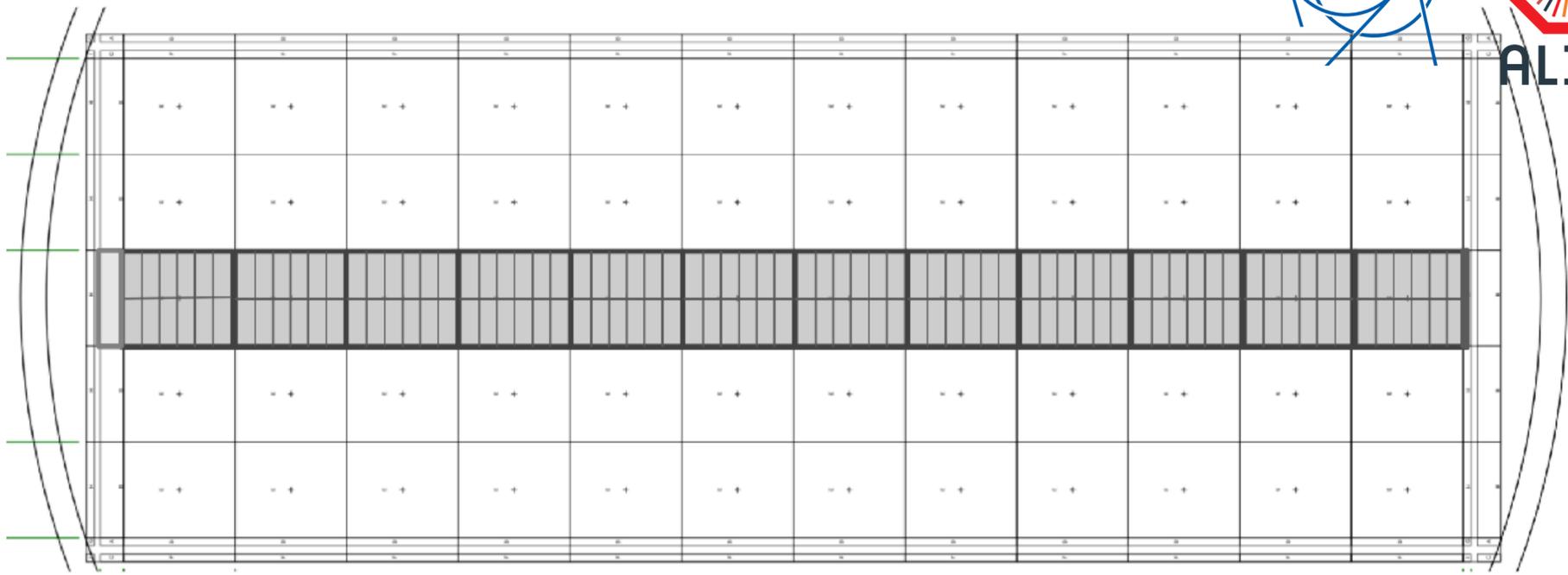
► Prototypes **work well** in beam tests

► **Operational margin** (efficiency >99% and fake-hit rate <10<sup>-6</sup>) is maintained at ALICE radiation levels

# ER2: MOSAIX

## architecture

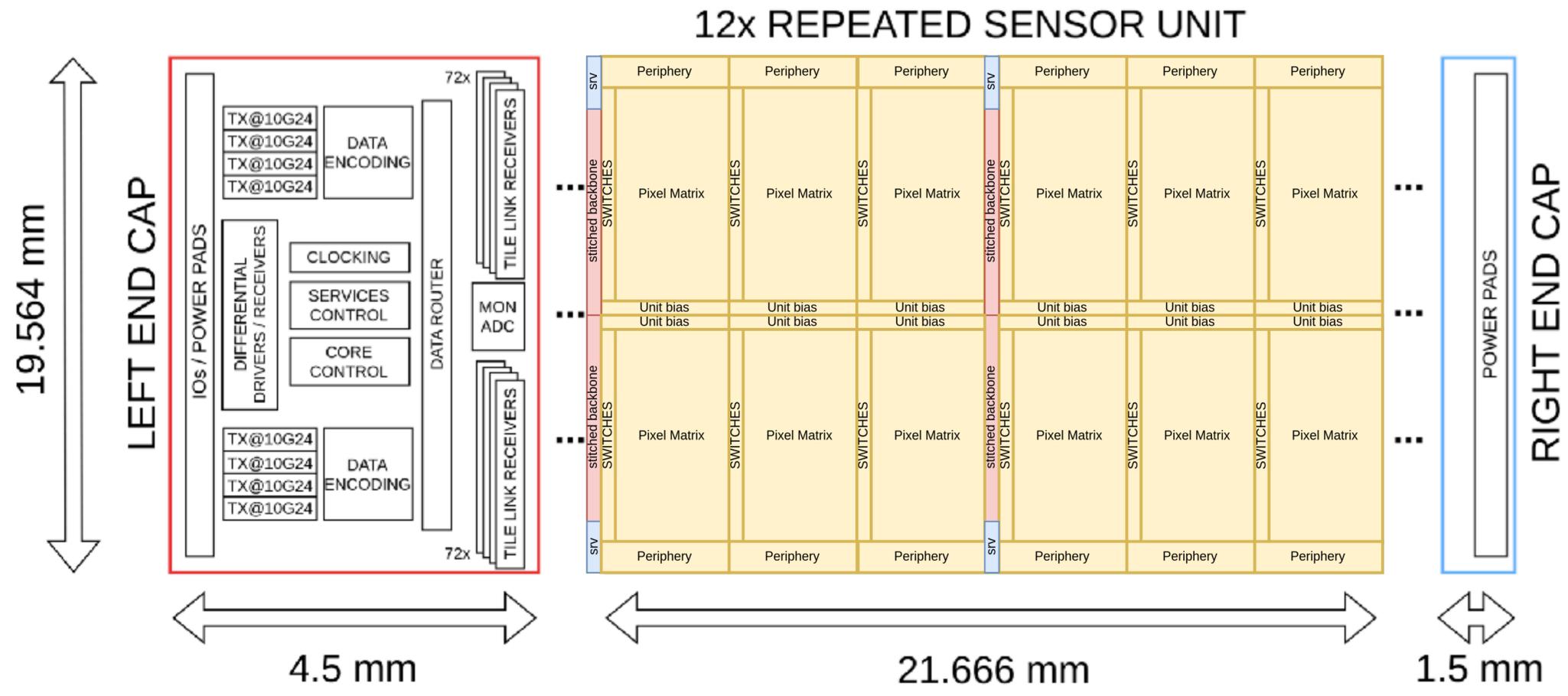
- ▶ Same size and full functionality of final chip
  - “module on a chip”
  - including data/event management and high-speed links



- ▶ High-granularity power network
  - 144 units can individually be switched off in case of malfunctioning

- ▶ 12 different pixel/matrix variants to fine tune operational margins
  - pitch:  $20.8 \times 22.8 \mu\text{m}^2$

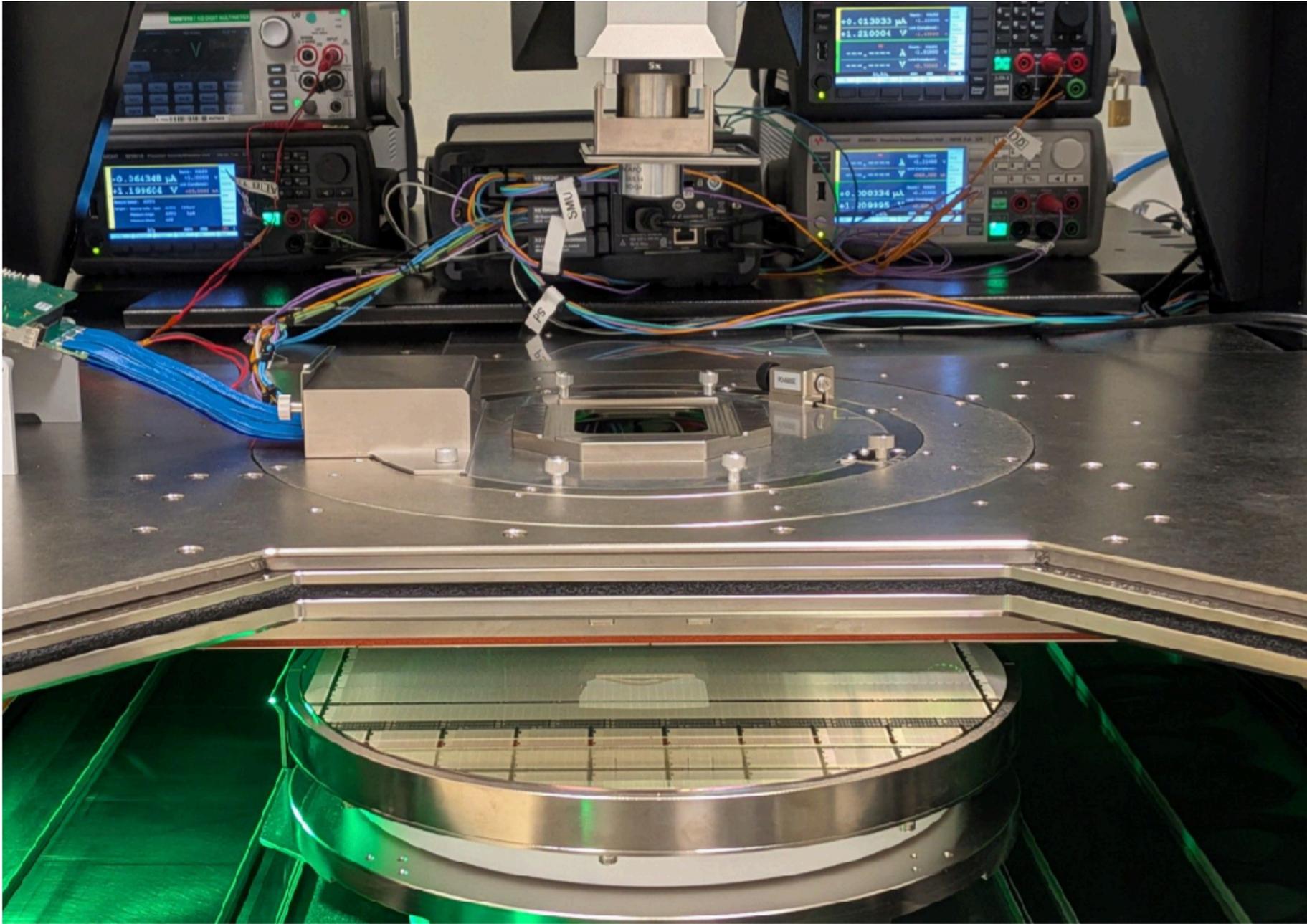
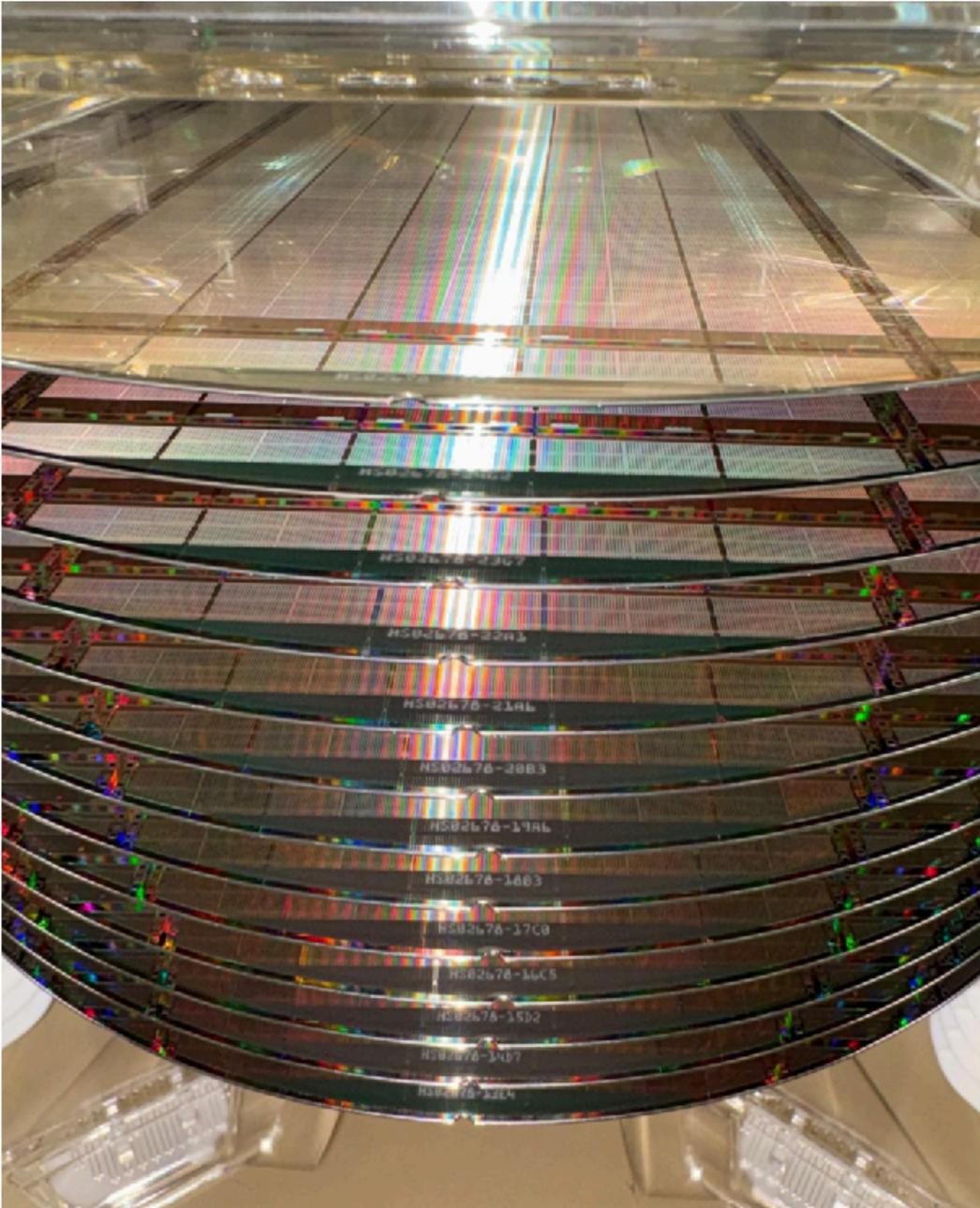
▶ Wafers back from production!



# ER2 tests



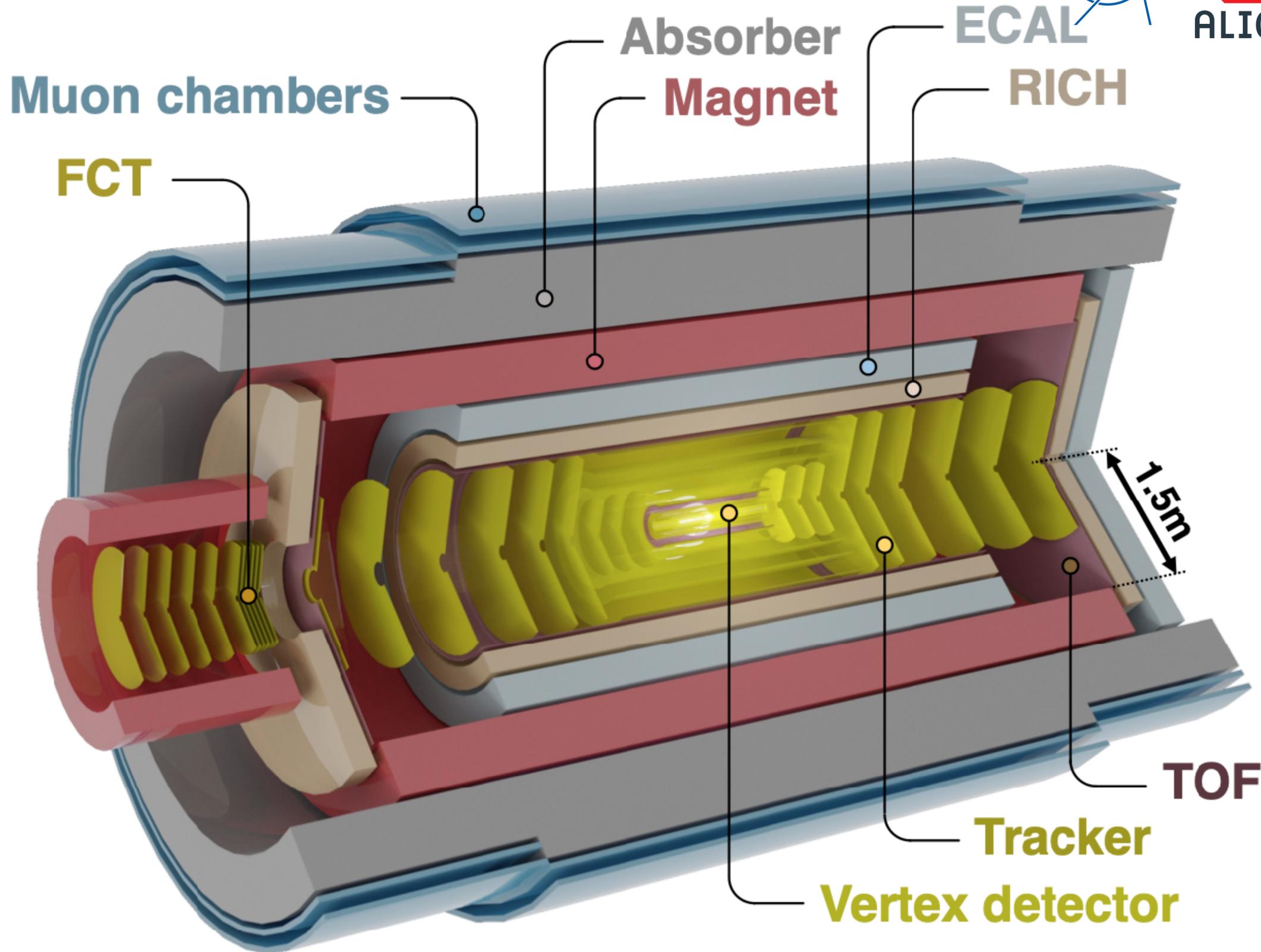
▶ are ongoing ;)





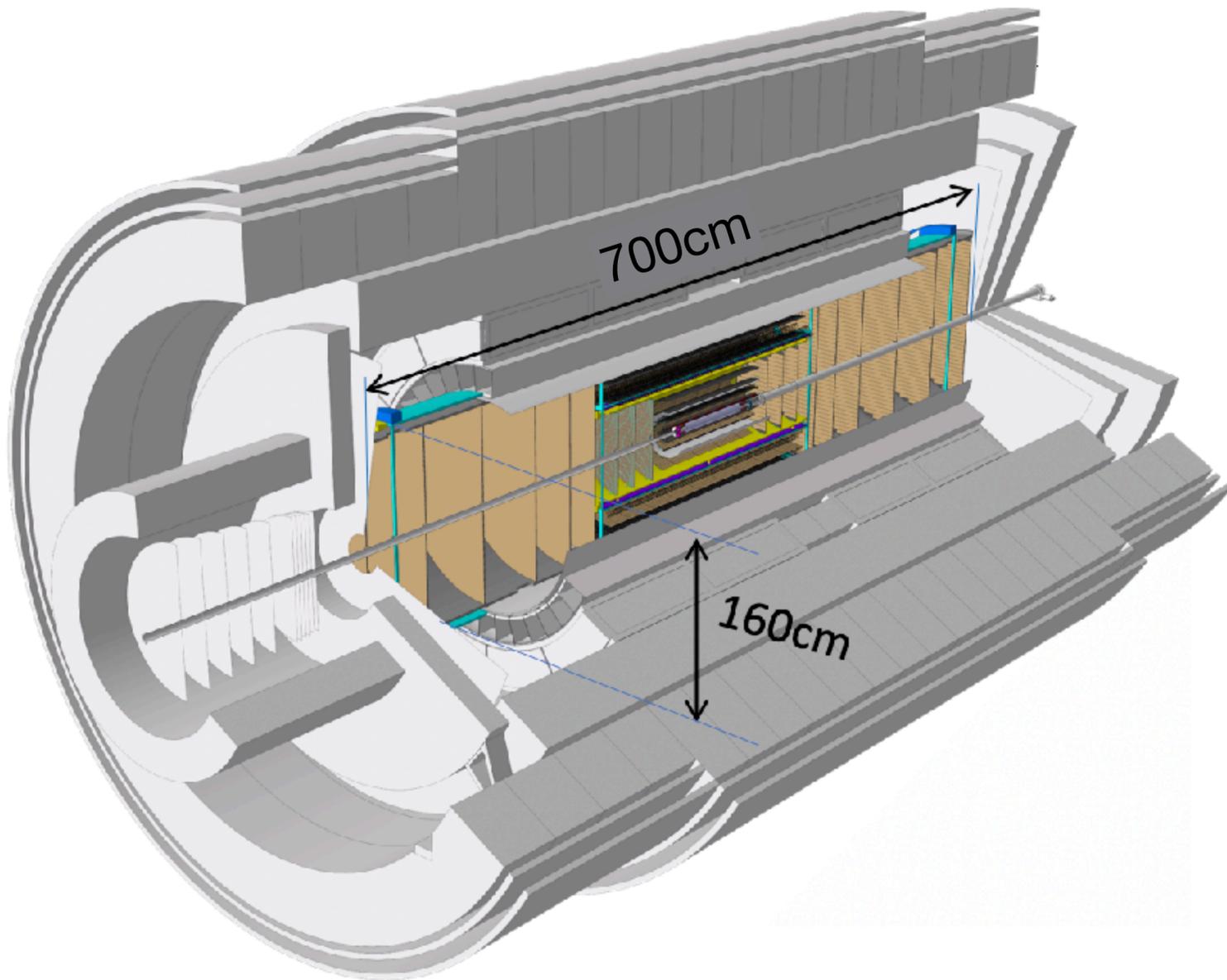
ALICE

# ALICE 3



# ALICE 3

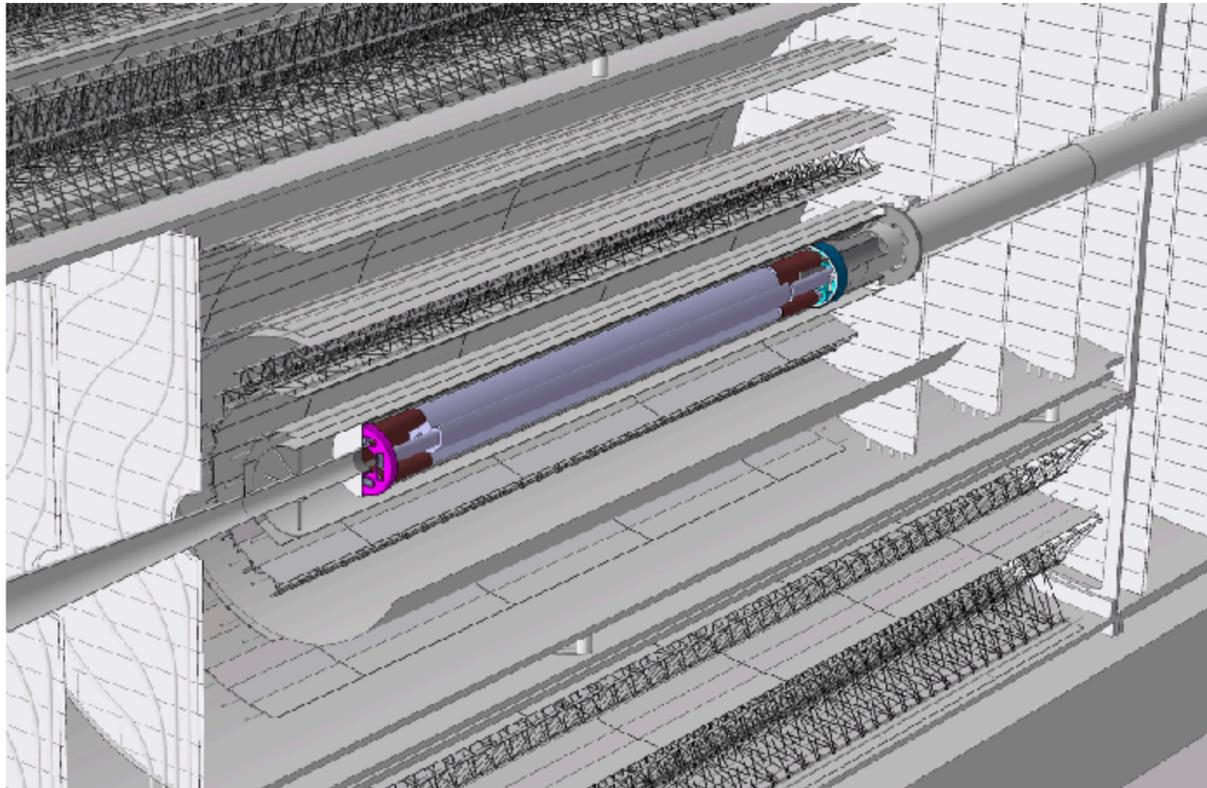
## Middle and Outer Layers



- ▶ **40-60 m<sup>2</sup> silicon pixel detector**
  - large coverage:  $\pm 4\eta$
  - high spatial resolution:  $\approx 10 \mu\text{m}$
  - very low material budget:  
 $X/X_0$  (total)  $\lesssim 10\%$
  - time resolution: **100 ns**
  - low power:  $\approx 20 \text{ mW/cm}^2$
- ▶ **Main R&D challenge:** its size
  - power consumption and distribution (both ways) are critical
  - module design for industrial production is necessary
- ▶ Relies on maturity, reliability and availability of a large quantity of MAPS
  - largely leverages from ITS2 and ITS3

# ALICE 3

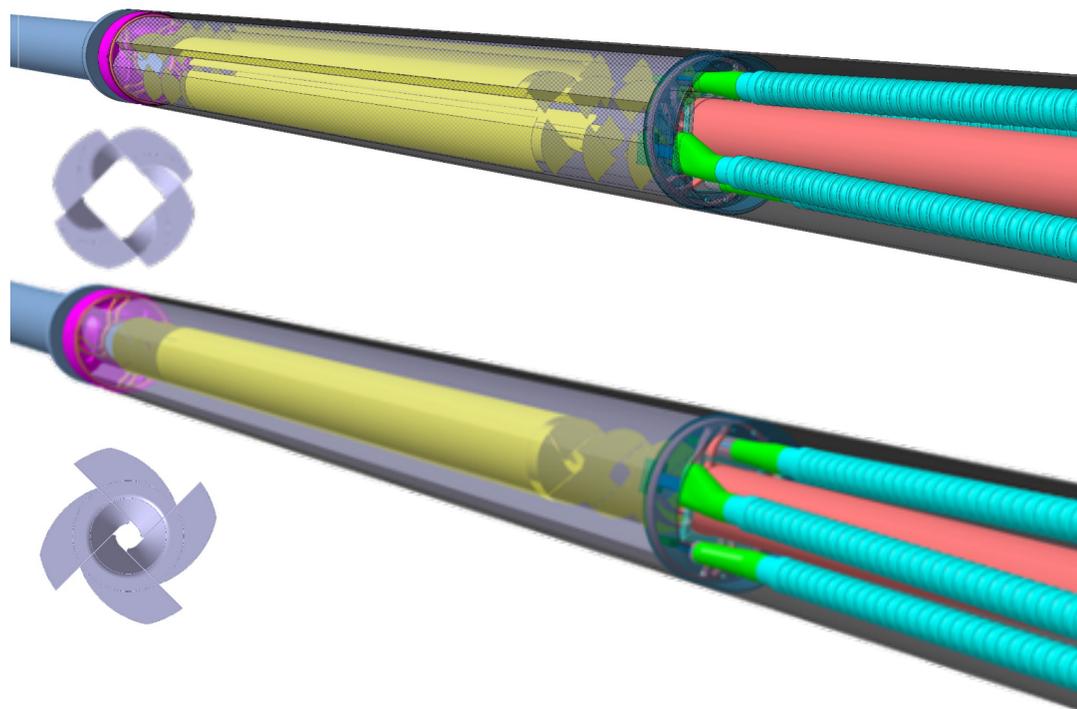
## Vertex Detector



- ▶ **Based on wafer-scale, ultra-thin, curved MAPS**
  - radial distance from interaction point: **5 mm** (inside beampipe, retractable configuration)
  - unprecedented spatial resolution:  $\approx 2.5 \mu\text{m}$
  - ... and material budget:  $\approx 0.1\% X_0/\text{layer}$
  - at radiation levels of:  $\approx 10^{16} \text{ 1MeV } n_{\text{eq}}/\text{cm}^2 + 300 \text{ Mrad}$
  - and hit rates up to: **94 MHz/cm<sup>2</sup>**

- ▶ Unprecedented performance figures
  - largely leverages on the ITS3 developments
  - pushes the technology on a number of fronts

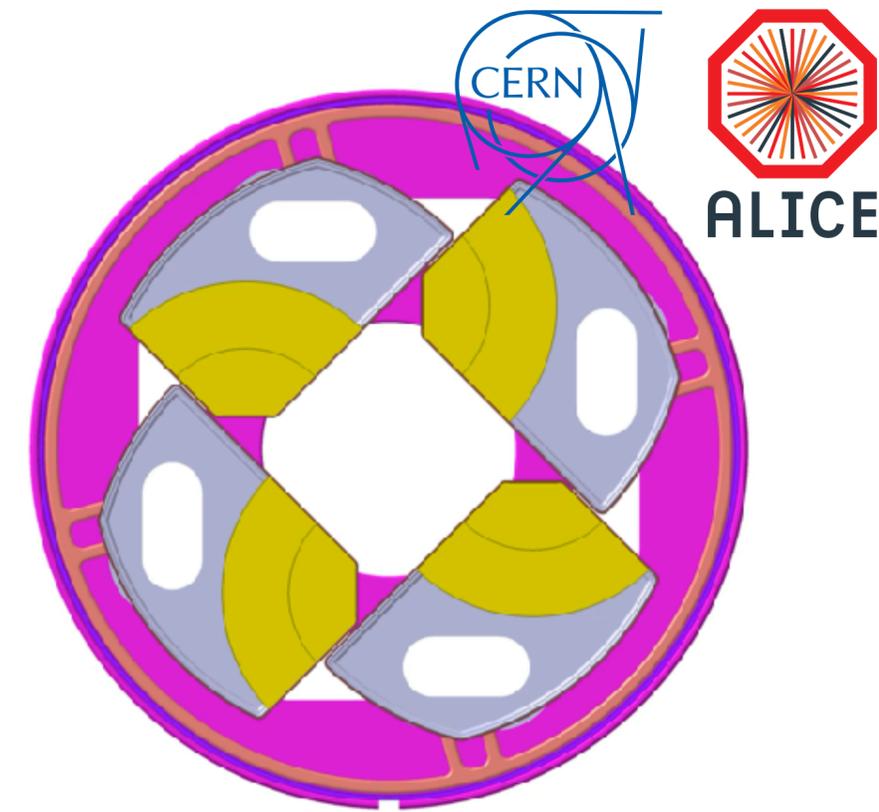
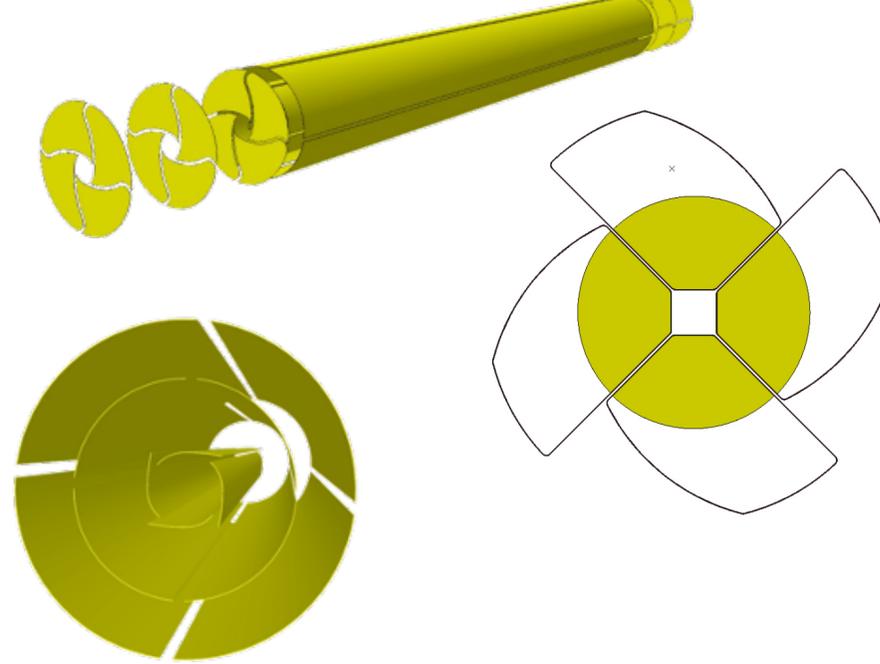
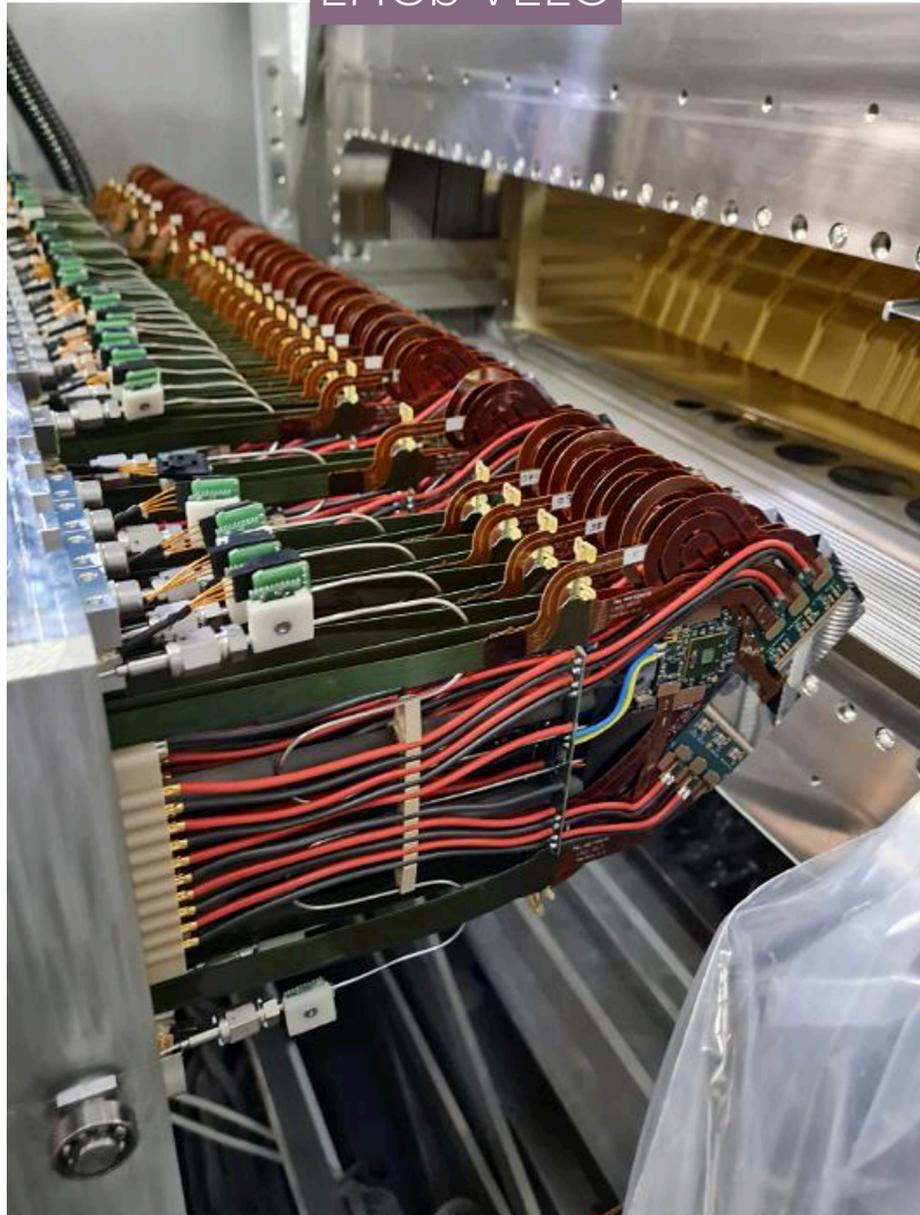
- ▶ **R&D has started**



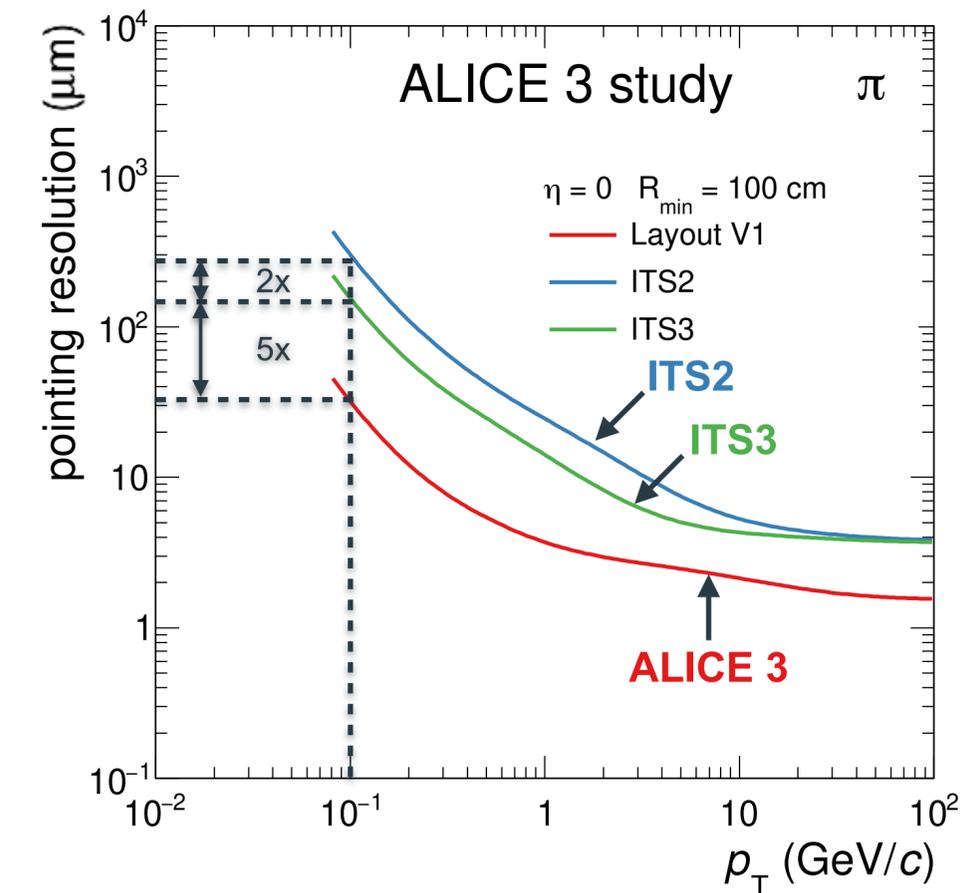
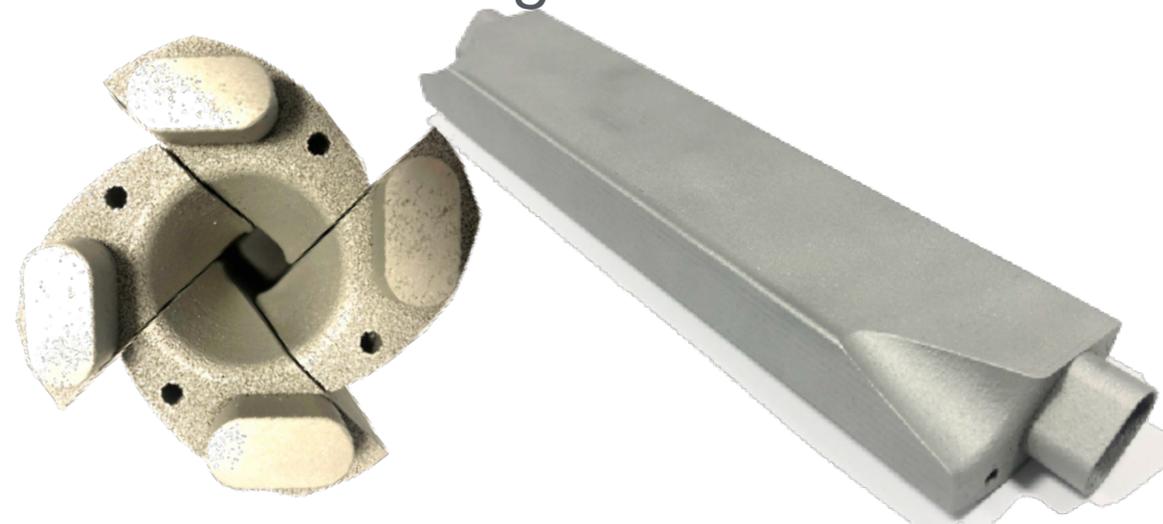
# ALICE 3

## in beam pipe: iris mechanics

LHCb VELO



- ▶ Ultimate tracking resolution obtained by minimizing the extrapolation length (lever arm) → **in beam pipe**
- ▶ Needs to be retracted during beam injection
  - Similar concept to LHCb VELO, but in barrel configuration



# Future sensor requirements



	Vertex Detector	Middle Layers	Outer Tracker	ITS3
Pixel size ( $\mu\text{m}^2$ )	$O(10 \times 10)$	$O(50 \times 50)$		$O(20 \times 20)$
Position resolution ( $\mu\text{m}$ )	2.5	10		5
Time resolution (ns RMS)	$O(100)$	$O(100)$		$O(1000)$
In-pixel hit rate - barrel / forward (Hz)	94	42 / 12	1 / 16	54
Fake-hit rate (/ pixel / event)	$< 10^{-7}$			
Power consumption (mW / $\text{cm}^2$ )	70	20		35
Particle hit density - barrel / forward (MHz / $\text{cm}^2$ )	94	0.6 / 0.6	0.06 / 0.6	8.5
Non-Ionising Energy Loss (1 MeV $n_{\text{eq}}$ / $\text{cm}^2$ )	$3 \times 10^{15}$	$4 \times 10^{13} / 4 \times 10^{13}$	$3 \times 10^{13} / 4 \times 10^{13}$	$4 \times 10^{12}$
Total Ionising Dose (Mrad)	110	3 / 3	0.5 / 3	0.4

- ▶ Challenging, but ITS3 provides a great starting point
  - indeed, a lot of ITS3 R&D supports the feasibility of several parameters

# MAPS for ALICE 3 tracker

## (working proposal)

- ▶ **Background:** attempt a unified approach to the sensor development, even if requirements differ for different parts of the detector
- ▶ **Common design approach:** modular pixel matrix unit ( $1 \times 1 \text{ cm}^2$ ), identical layout and circuits for all layers
- ▶ **Two variants:**
  - 10  $\mu\text{m}$  pitch for the Vertex Detector (VD), driven by spatial resolution
  - 20  $\mu\text{m}$  (or larger) pitch for Middle and Outer Layers (ML/OL)
- ▶ **Readout strategy:** higher frequency for VD, lower for ML/OL
- ▶ **Integration:** multiple matrix units assembled into large-area sensors (up to  $\sim 2 \times 3 \text{ cm}^2$  for ML/OL, larger sensors for VD)
- ▶ **Performance targets:**
  - Spatial resolution: 2.5  $\mu\text{m}$   $\rightarrow$  10  $\mu\text{m}$  pitch (VD) ,  $\sim 10 \mu\text{m}$  (ML/OL)
  - Power density:  $\sim 70 \text{ mW/cm}^2$  (VD), 20-30  $\text{mW/cm}^2$  (ML/OL)
  - Radiation tolerance:  $3 \times 10^{15} \text{ 1 MeV n}_{\text{eq/cm}^2}$
- ▶ **Engineering / R&D challenge:** internal routing with analog signals crossing digital regions, and vice versa

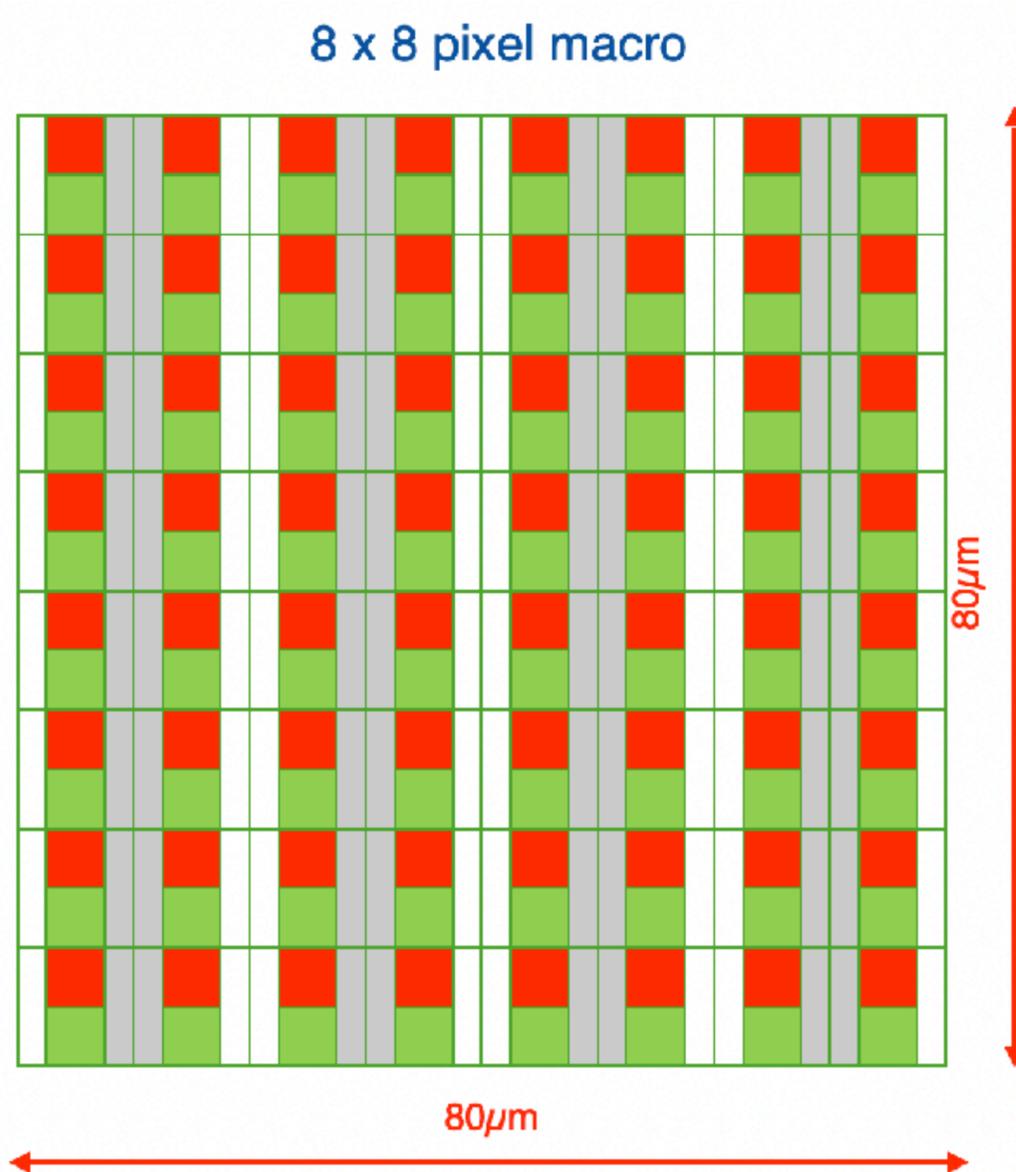
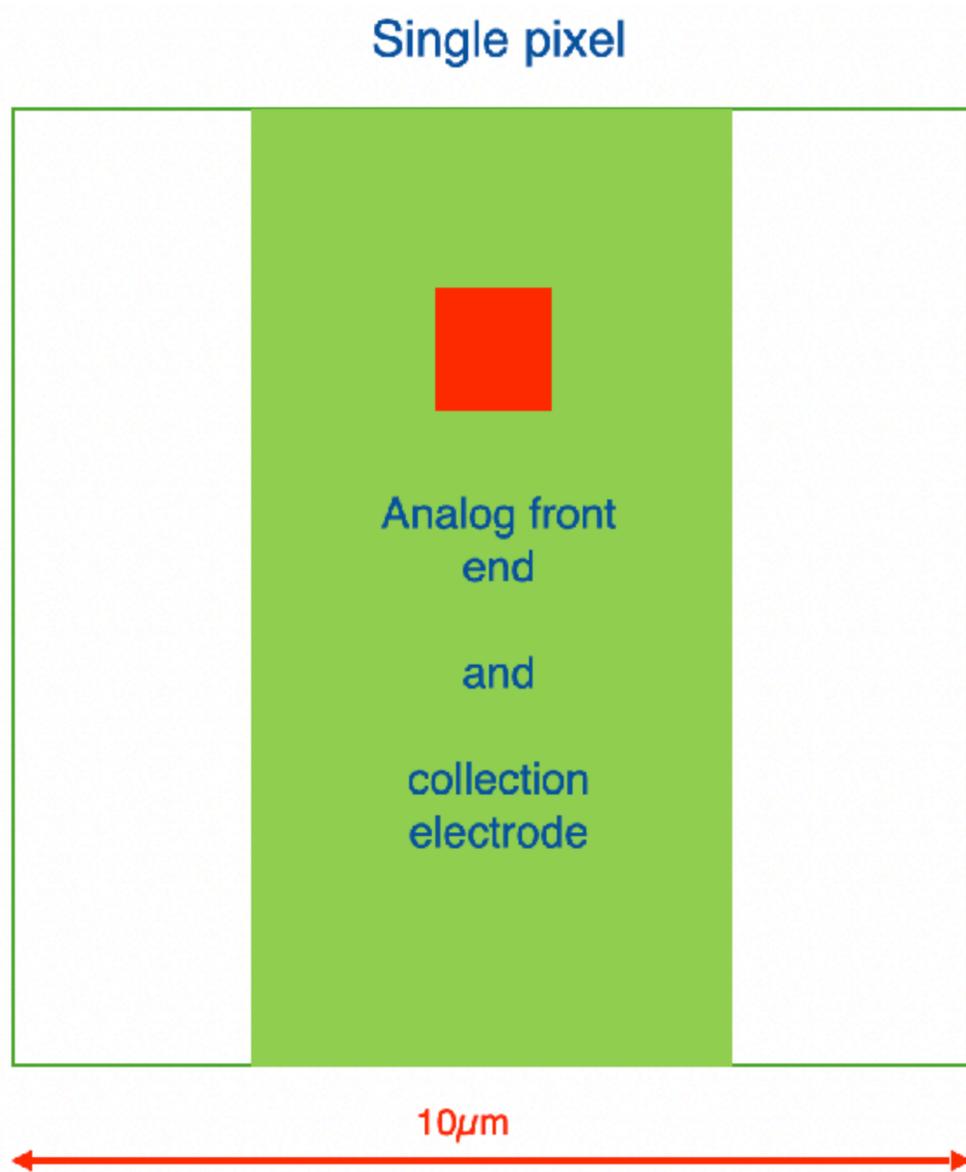
# Global architecture

## *working ideas*



- ▶ **Central concept:** build sensors from a modular Pixel Macro (e.g. a  $80\ \mu\text{m} \times 80\ \mu\text{m}$  block)
- ▶ **Pixel pitch flexibility:**  $10\ \mu\text{m} \times 10\ \mu\text{m}$  or  $20\ \mu\text{m} \times 20\ \mu\text{m}$  (extendable to larger pitches)
- ▶ **Matrix Core:**
  - $128 \times 128$  Pixel Macros  $\rightarrow$   $1\ \text{cm} \times 1\ \text{cm}$  matrix
  - Peripheral logic for control, aggregation, serialization
- ▶ **Scalability:**
  - Tile Matrix Cores into larger sensors (e.g.  $2 \times 3\ \text{cm}$  for ML/OL)
  - Larger sensors for VD, stitching (if needed) limited to periphery
- ▶ **Technology baseline:** 65 nm CMOS, 7 + 1 metal layers, including thick layer(s) for power grid

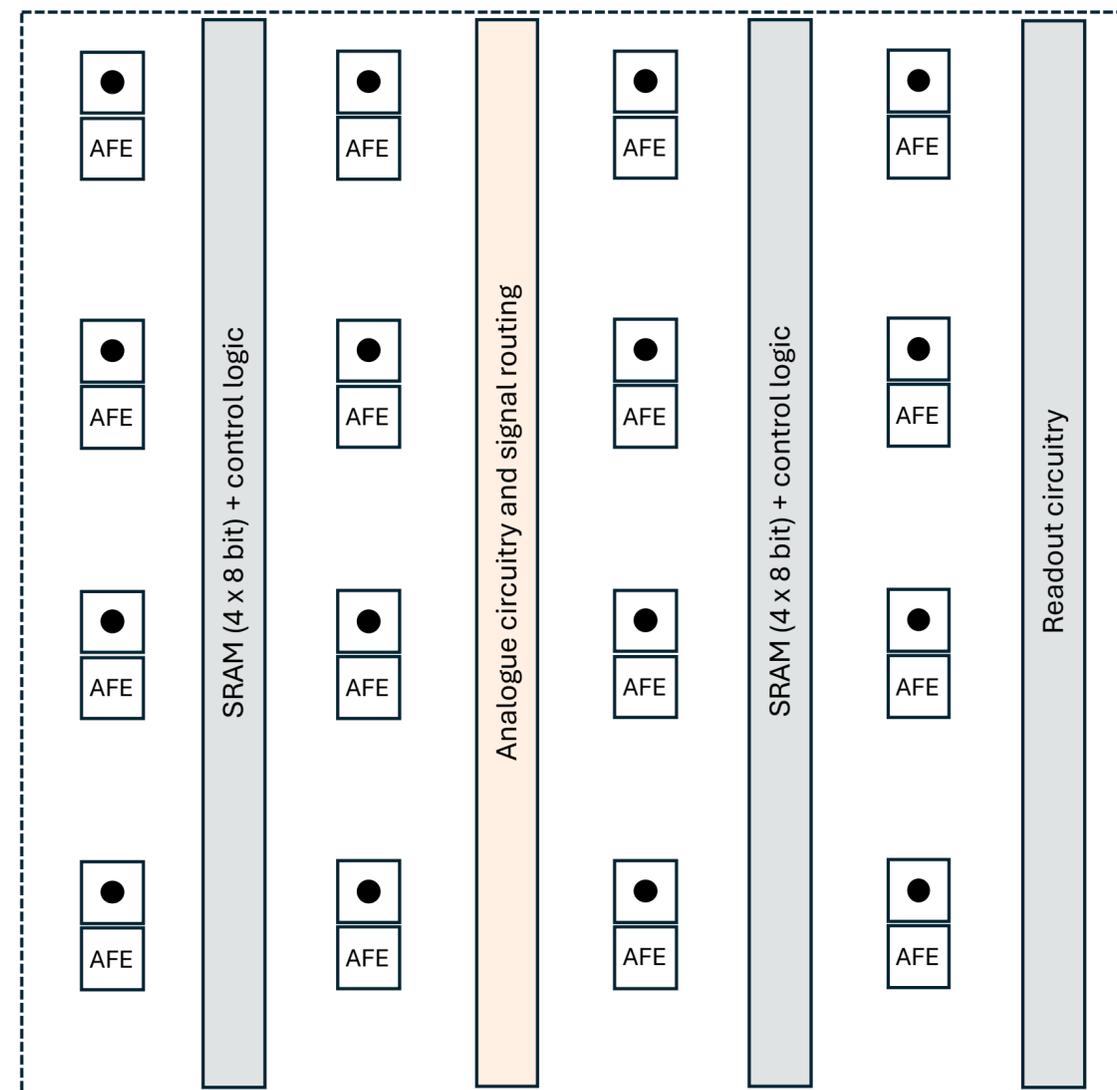
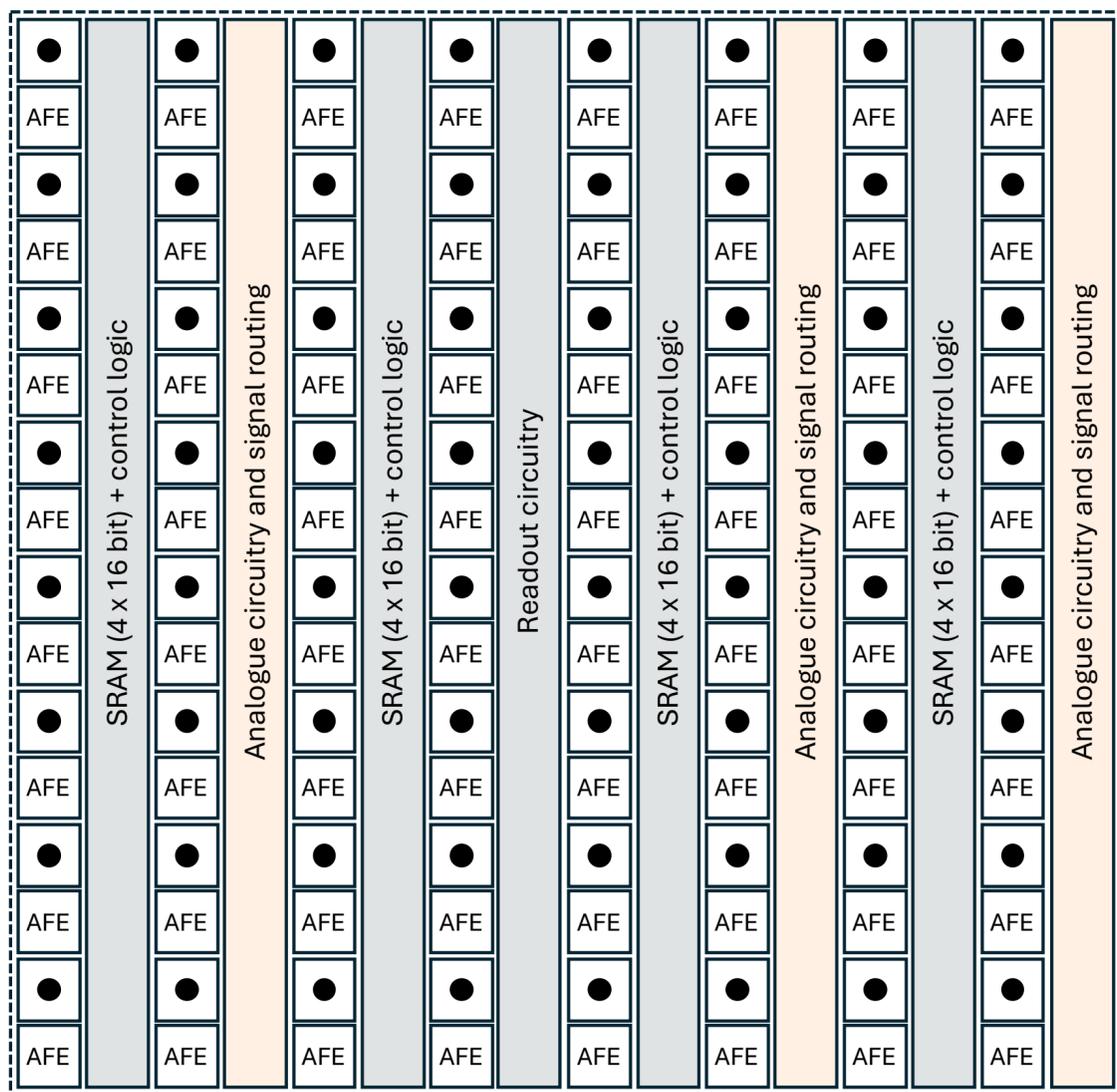
# 10 $\mu\text{m}$ pixels



- Analog with collection electrode/contact to sensor (50 % of the area)
- Data buffer + readout (25 % of the area)
- Reserved for supporting circuitry (25 % of the area)

► **R&D:** internal routing with analog signals crossing digital regions, and vice versa

# Modular: 10 $\mu\text{m}$ $\rightarrow$ 20 $\mu\text{m}$



● Charge Collection Electrode

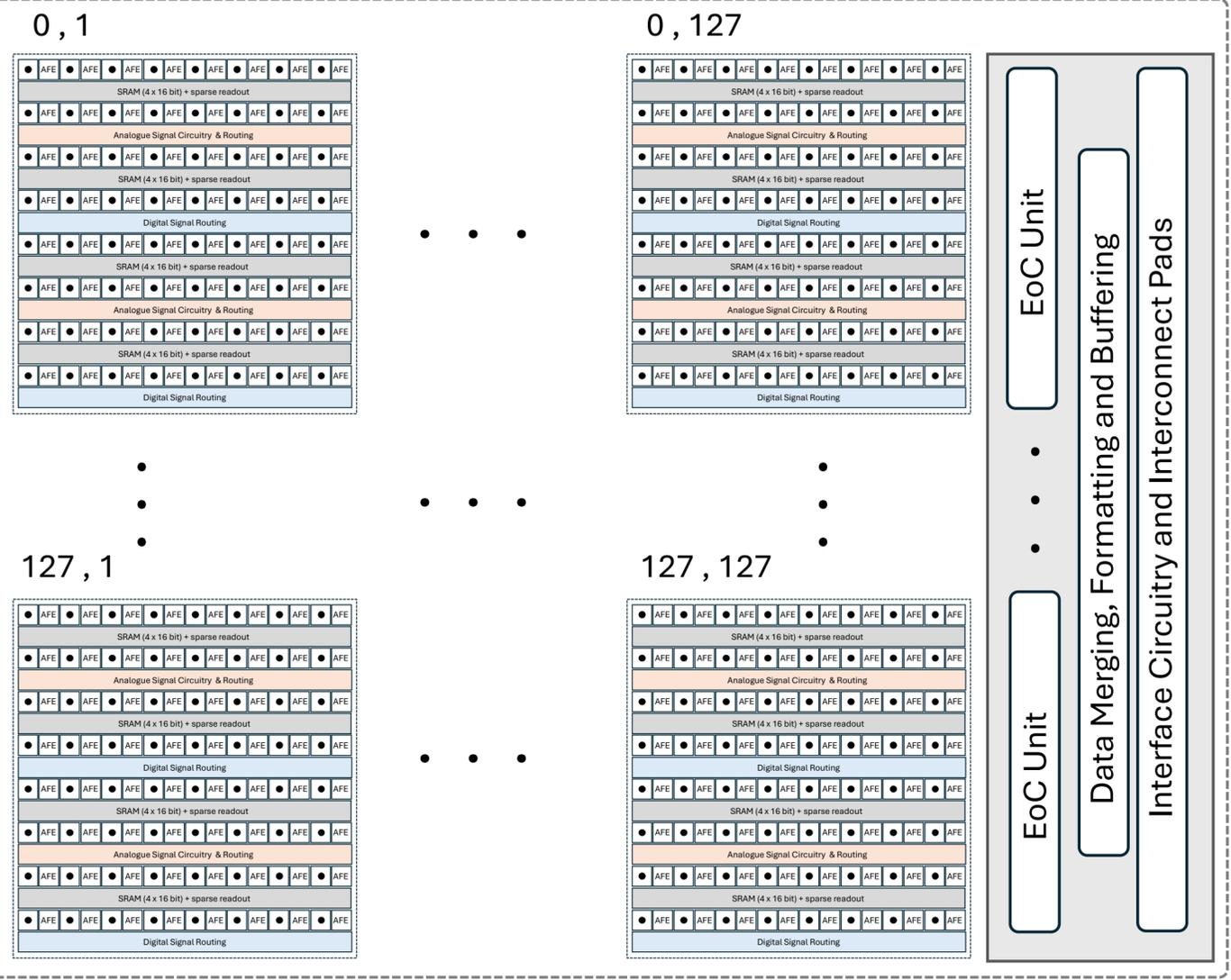
AFE Analogue Frontend Circuit

► Simplification to larger pitches possible (e.g. Outer Tracker), potentially yielding:

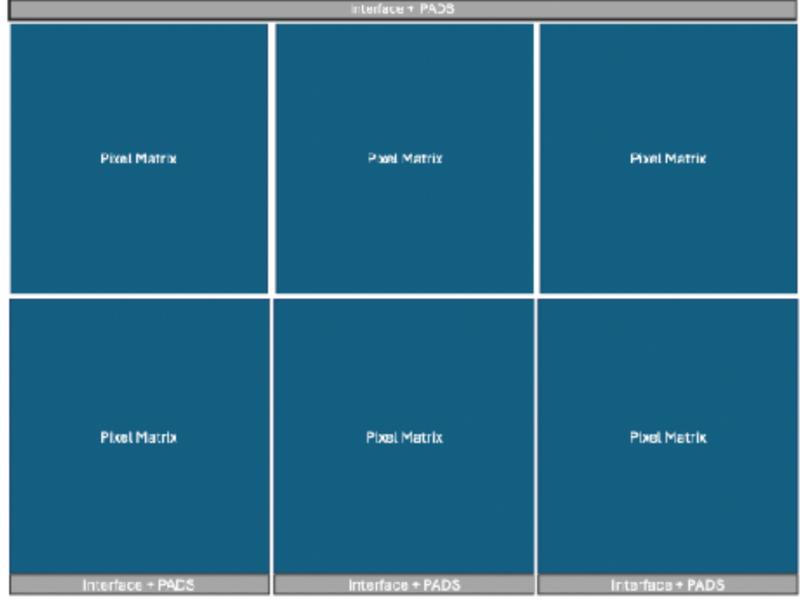
- higher yield
- lower power

# Sensor assembly

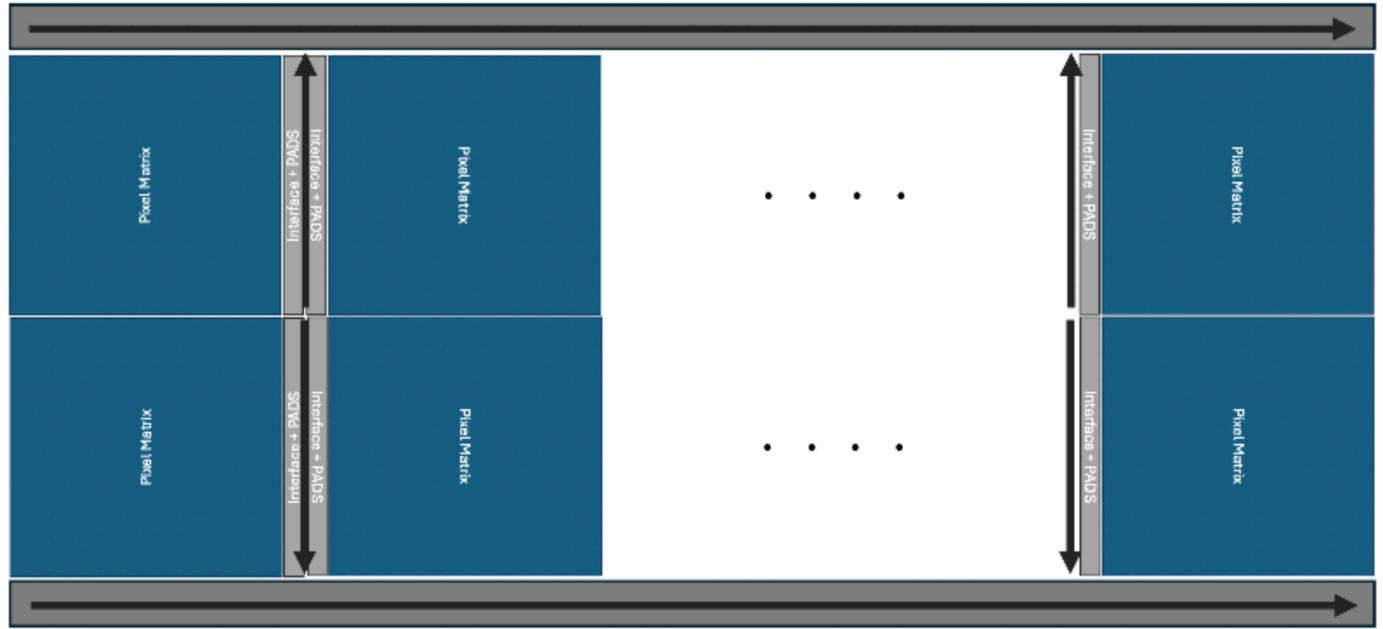
- ▶ Pixel macros will be instantiated to build the full matrix
- ▶ Different arrangements possible to serve different detector requirements



## Option for reticle-size sensor

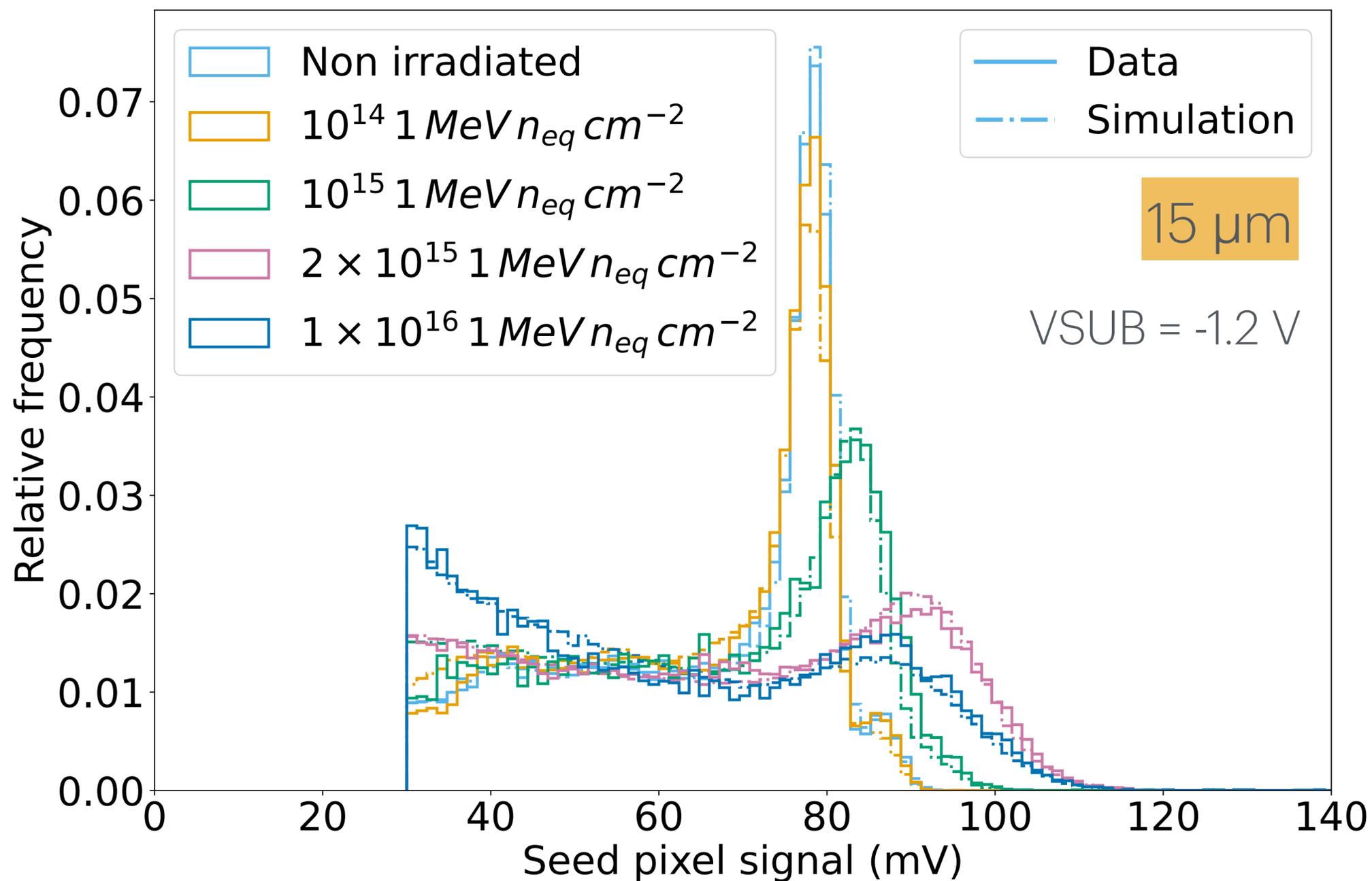


## Option for stitched sensor



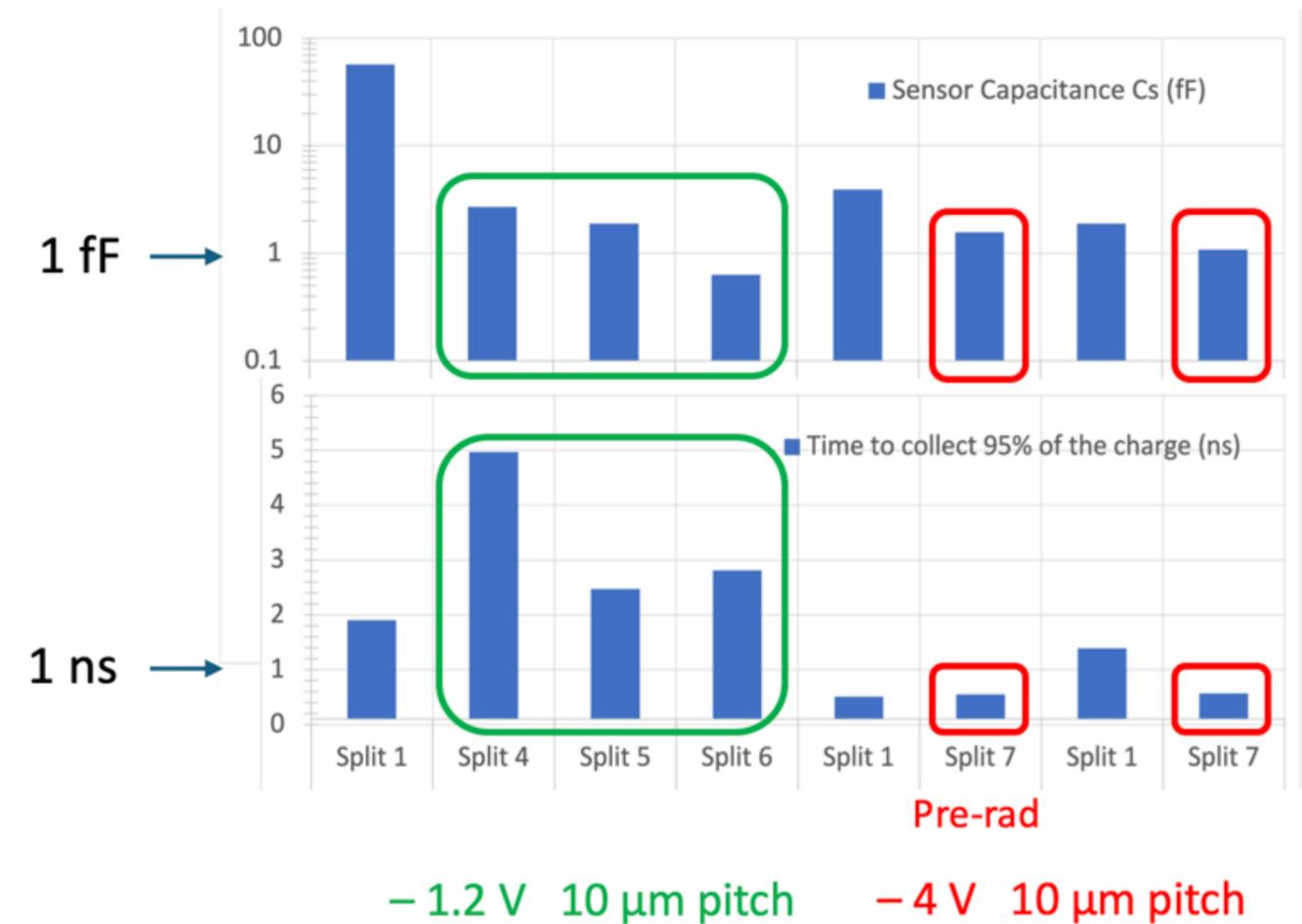
# Radiation hardness

- ▶ Main principle challenge
- ▶ Already assessed with ITS3 prototype chips
- ▶ Excellent starting point
- ▶ Further improvements by:
  - reduction of pixel pitch
  - further process optimization



# Process optimization for radiation hardness

- ▶ Continued improvement over the last decade
  - MLR1 Dec. 2020: split 1 (std) - split 4
  - ER1 Dec. 2022: split 4
  - ER2 Aug. 2025
- ▶ Different optimizations:
  - split 4-6 for -1.2 V and 20  $\mu\text{m}$  pitch optimized for ITS3 and outer layers
  - split 7 for -4 V and 10  $\mu\text{m}$  pitch towards higher radiation tolerance circuit to be compatible with -4 V
- ▶ TID in TPSCo 65 nm:
  - No showstopper, typical transistor radiation tolerance for a 65 nm technology
  - However, in MOSS a sensitivity to TID observed (increased fake hit rate)
  - topology dependent, to be investigated for the new front end





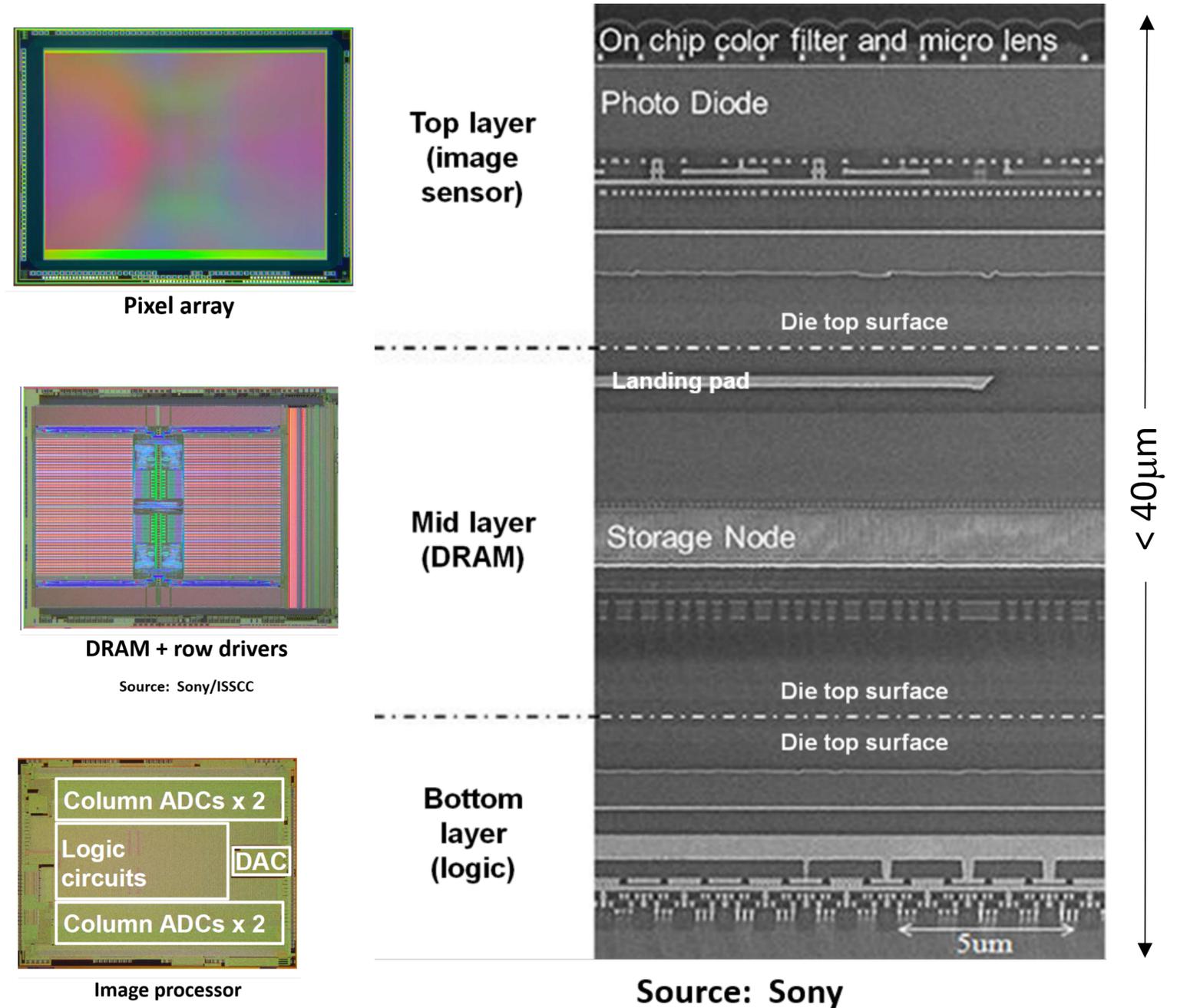
ALICE

# More future opportunities

personal selection

# Wafer stacking

“monolithic hybrids”



- ▶ Many modern (optical) pixel sensors are **stacks of different chips**
- ▶ Smears the boundaries between monolithic and hybrid detectors
  - but: stays an industrial process
- ▶ Optimized choice for technology for each function can be taken, e.g.
  - sensor + first level amplification
  - readout
- ▶ NB: sensor layer can still be “MAPS”-like, i.e. contain active elements

# Time over threshold

dE/dx, PID

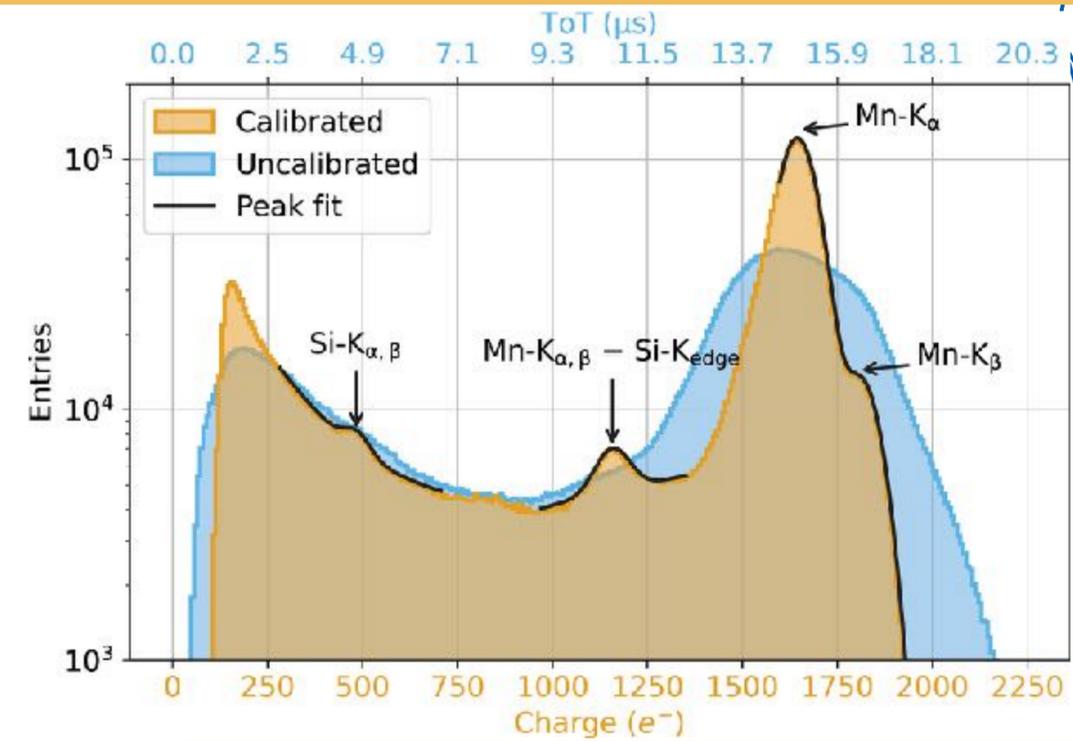
► Pixels with binary (yes/no) readout can still measure charge by looking at how long the signal is seen by the electronics (~Wilkinson ADC): **time over threshold, ToT**

► **Potential benefits**

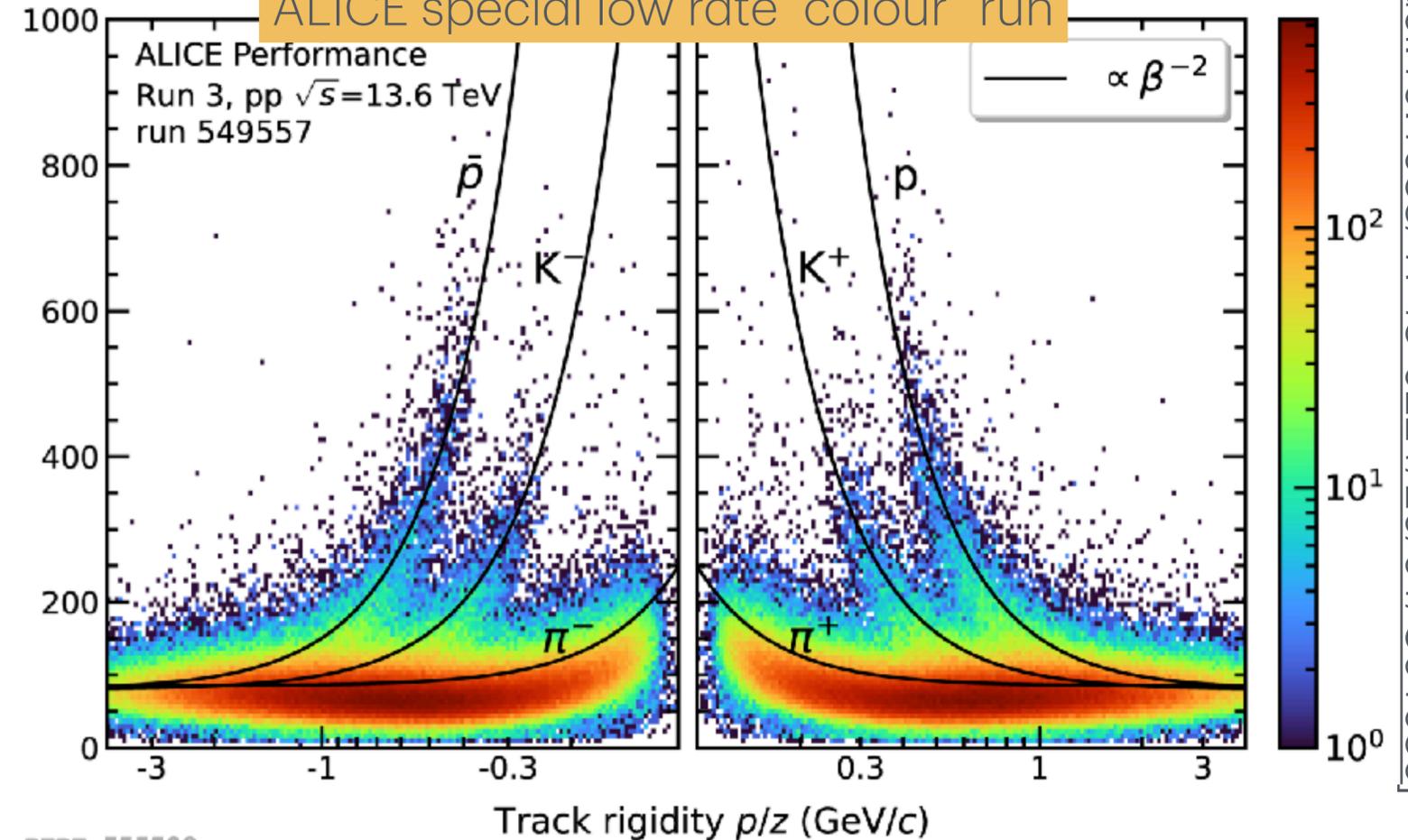
- position resolution: measurement of charge sharing
- time resolution: time walk correction
- particle identification: specific energy loss, dE/dx

► **Particle identification** with silicon

- (+) good ratio of ionization potential to multiple scattering
- (-) too coarse segmentation (too few measurement points): Landau tails difficult to remove
- still: applicable for low momentum particles



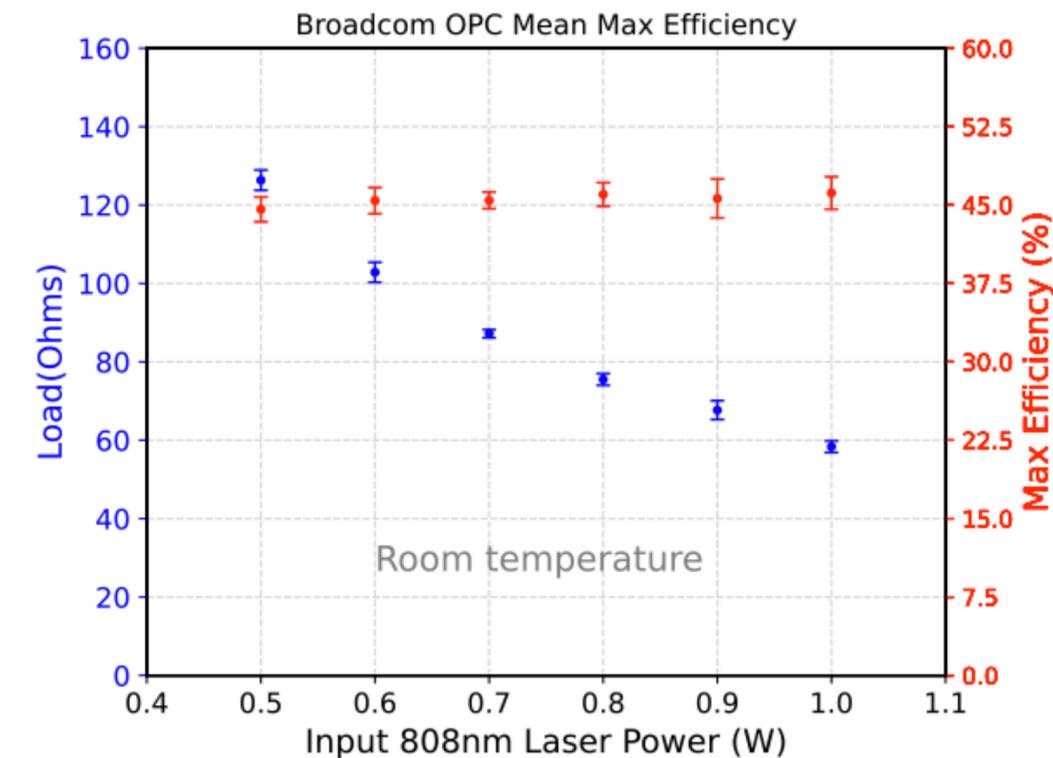
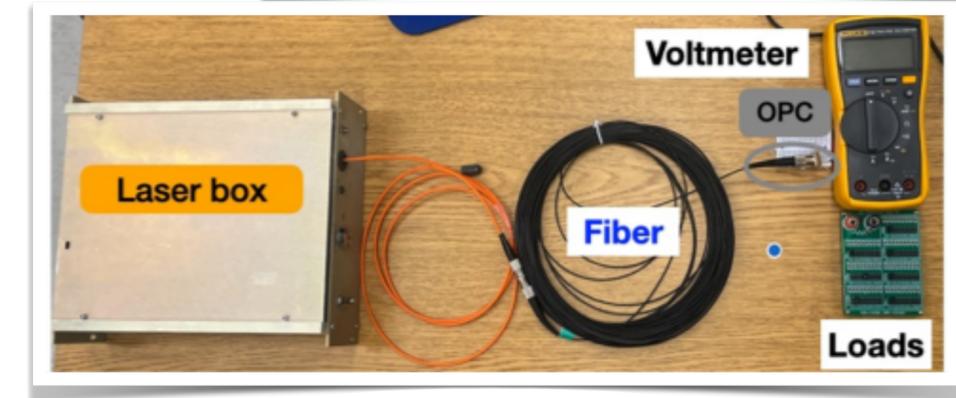
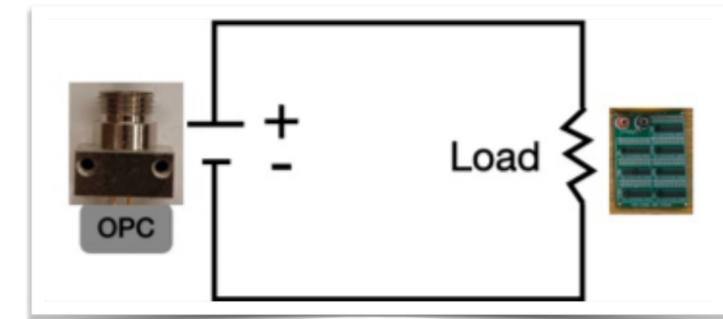
ALICE special low rate "colour" run



# Future trends

powering (serial, optical, mechanical, chemical, nuclear)

- ▶ **Powering is one of the key difficulties** in the design of low mass detectors
- ▶ **Novel ideas and solutions are necessary** to get to large-scale low mass detectors
- ▶ **Serial powering**
  - put detectors in series instead of parallel
  - employed in LHC upgrades
  - to be ported to CMOS detectors (planned for ALICE 3)
- ▶ **Optical powering (“power over fibre”, POF):**
  - shoot a laser onto a photocell
  - commercially available solutions exist
  - used e.g. by DUNE
- ▶ **More “exotic” ideas:** use fuel cells, piezo transformers, batteries, ...



[doi:10.48550/arXiv.2405.16816]

# Summary and outlook



- ▶ **CMOS Monolithic Active Pixel Sensors (MAPS) are an established technology**
  - provide excellent spacial resolution at lowest material budgets
  - ALICE is currently operating 24k sensors on its inner tracking system (ITS2)
  - rapid development over last 2 decades
- ▶ **ITS3 project introduced and proved feasibility of a new class of ultra-light vertex detectors**
  - **bent MAPS** work very well
  - **65 nm** process is established for HEP applications
  - **Stitched** (wafer-scale) design and associated yield is understood
  - **Bent, large, thin** sensors can be handled and mechanically integrated
  - **Air cooling** is proved to be sufficient
  - to be installed in LHC Long Shutdown 3
- ▶ **ALICE 3 sensor R&D is starting**
  - further process optimizations to reach higher radiation hardness
  - conceptional road towards 10  $\mu\text{m}$  pitch laid out

**MAPS have a bright future and will**